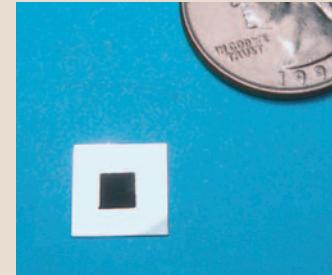


Black silicon: Using lasers to make novel materials

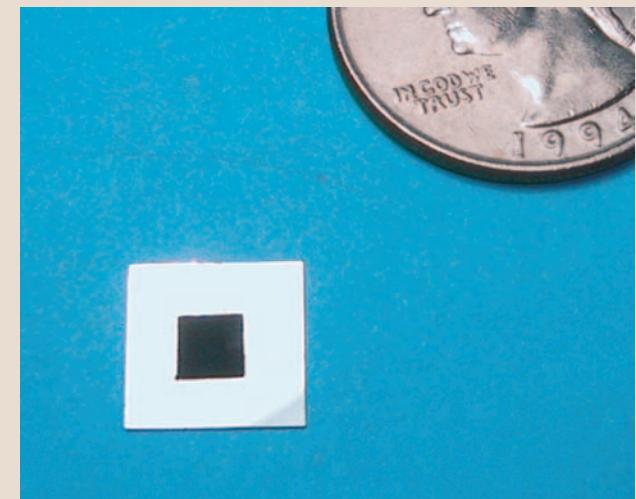


**Catherine H. Crouch
Harvard University**

**Harvard University
14 February 2003**

Study effect of extremely intense laser pulses

Develop novel materials



Femtosecond laser pulses

800 nm, 100 fs laser pulses

- ▶ last only 10^{-13} seconds
- ▶ 30 cycles of electromagnetic wave
- ▶ extend only 30 μm

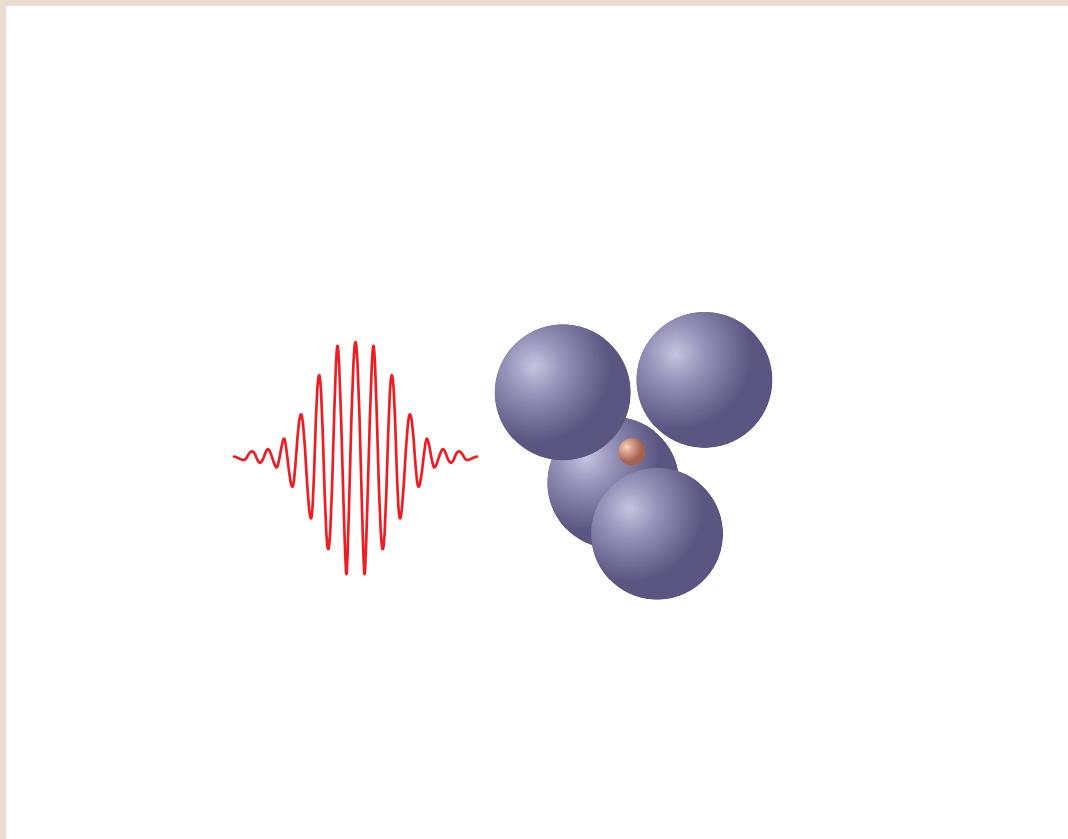


Extremely high peak power and intensity

- ▶ peak power $> 10^9 \text{ W}$
- ▶ focused beam: $\sim 10^{17} \text{ W/cm}^2$

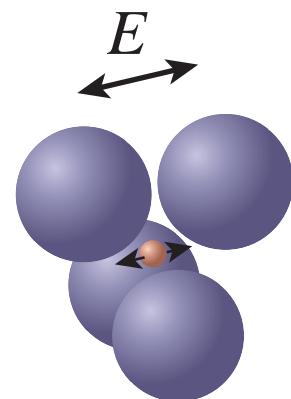
Modification of materials

light-matter interactions



Modification of materials

temporary effect on material

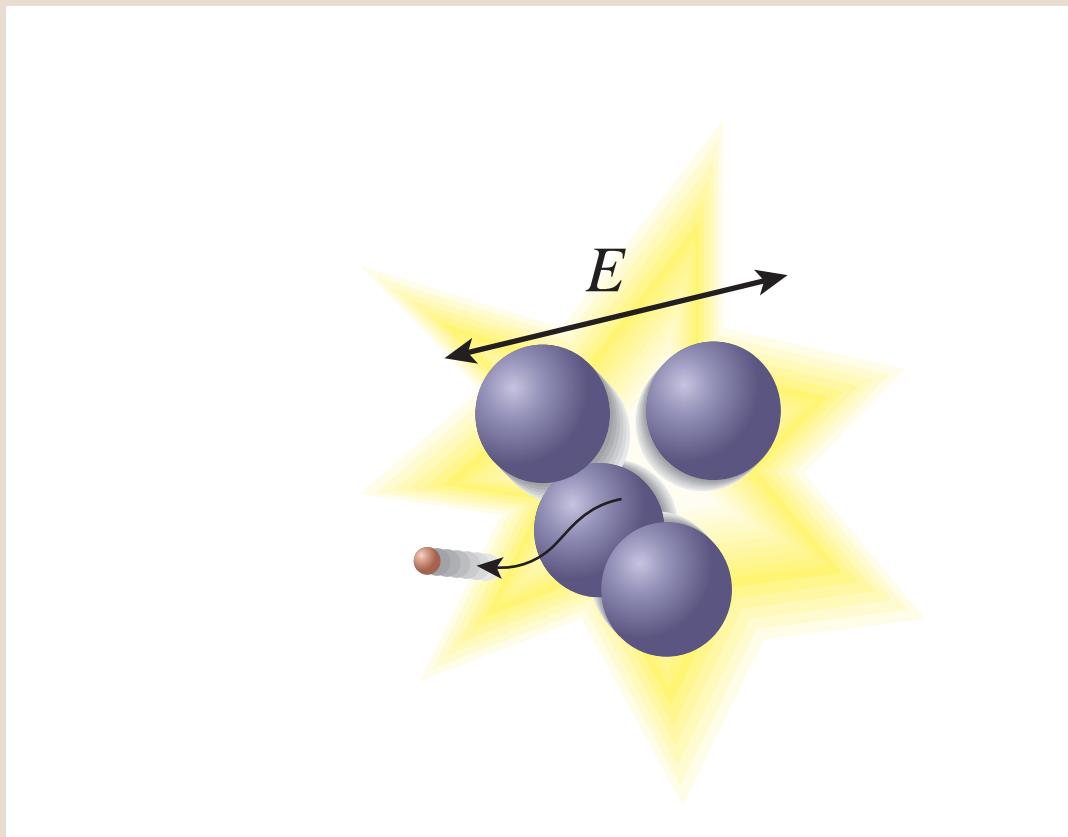


$$\vec{P} = \chi \vec{E}$$

χ is constant

Modification of materials

permanent change to material

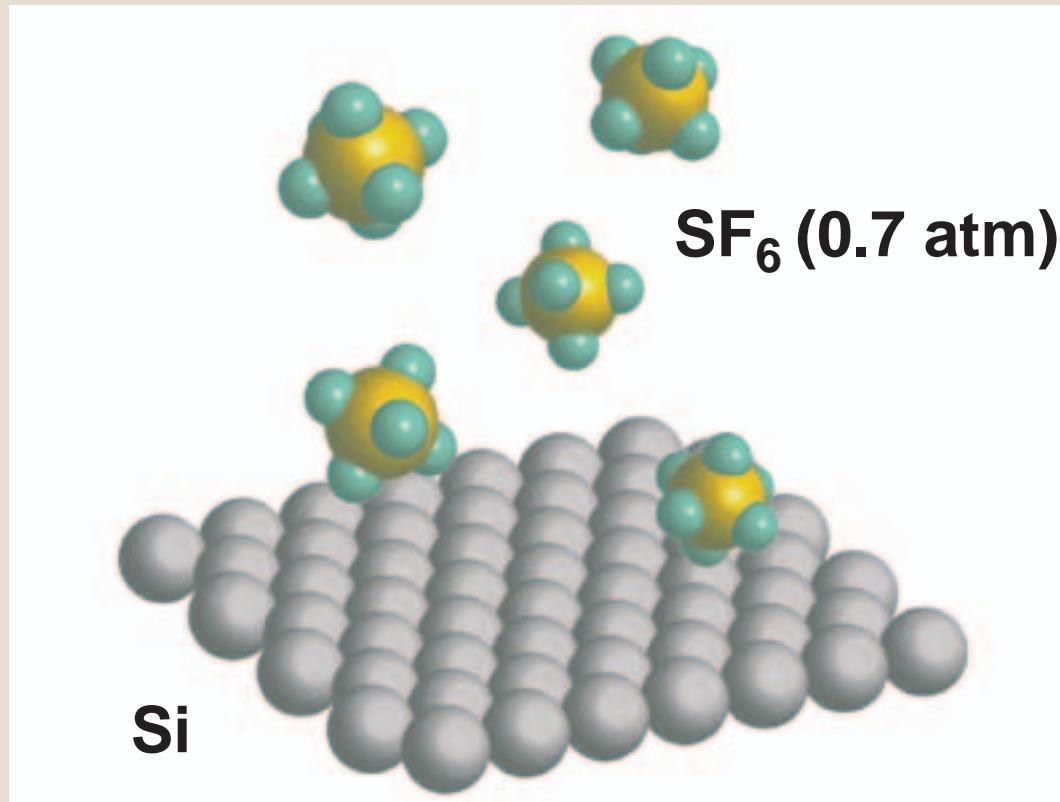


plasma formation

1. What is black silicon?

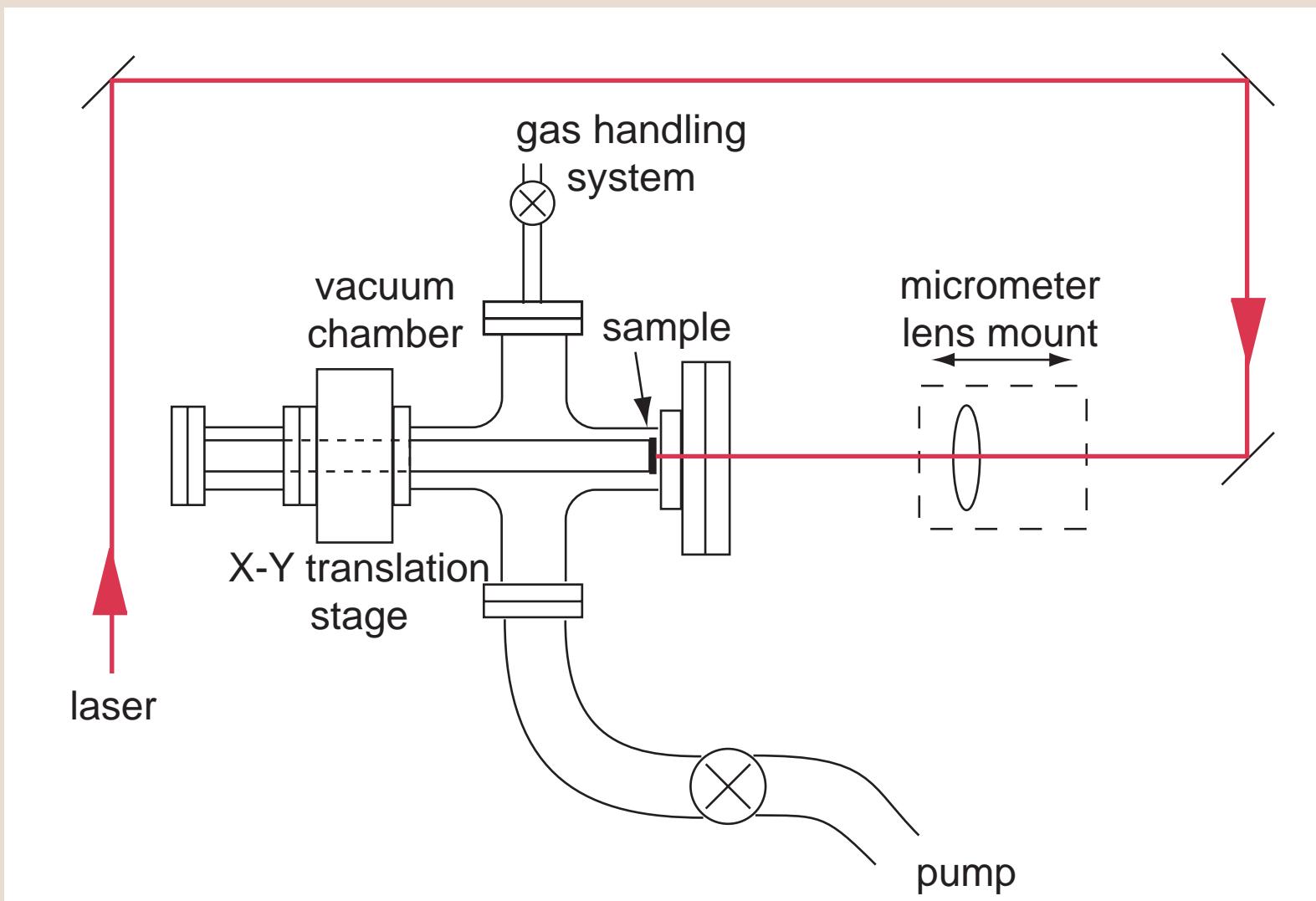
2. Why is it black?

3. How does it get that way?

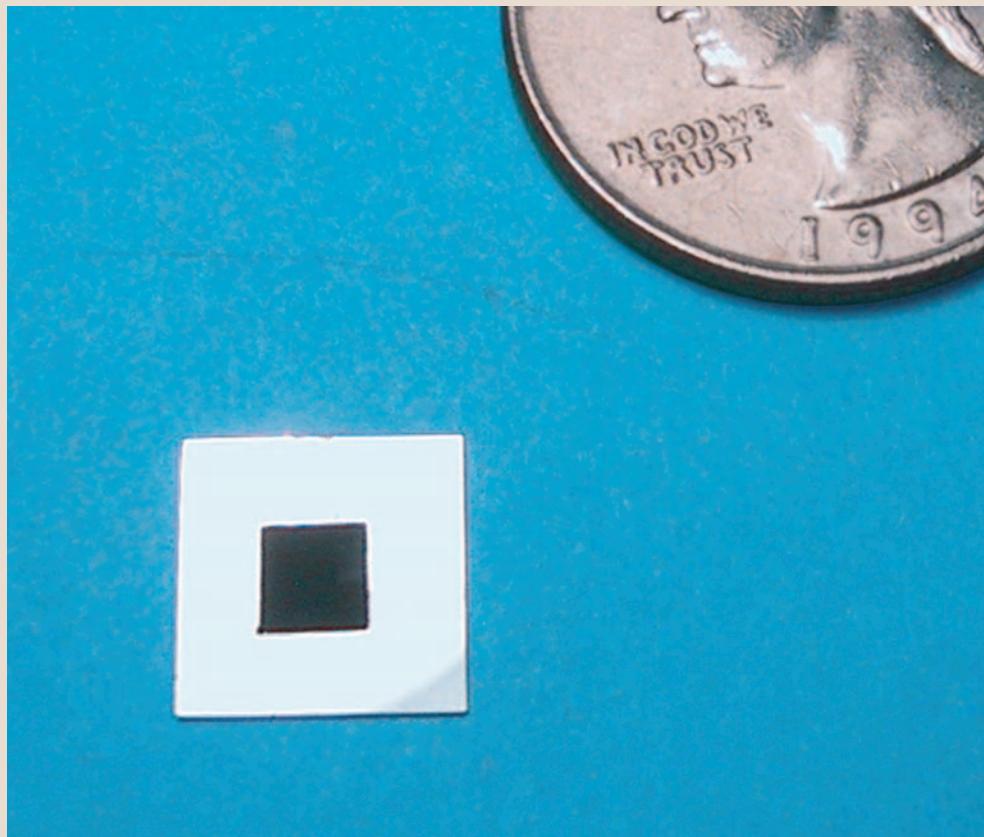


**irradiate surface with femtosecond laser pulses
(800 nm, 100 fs, 500 pulses, 10 kJ/m²)**

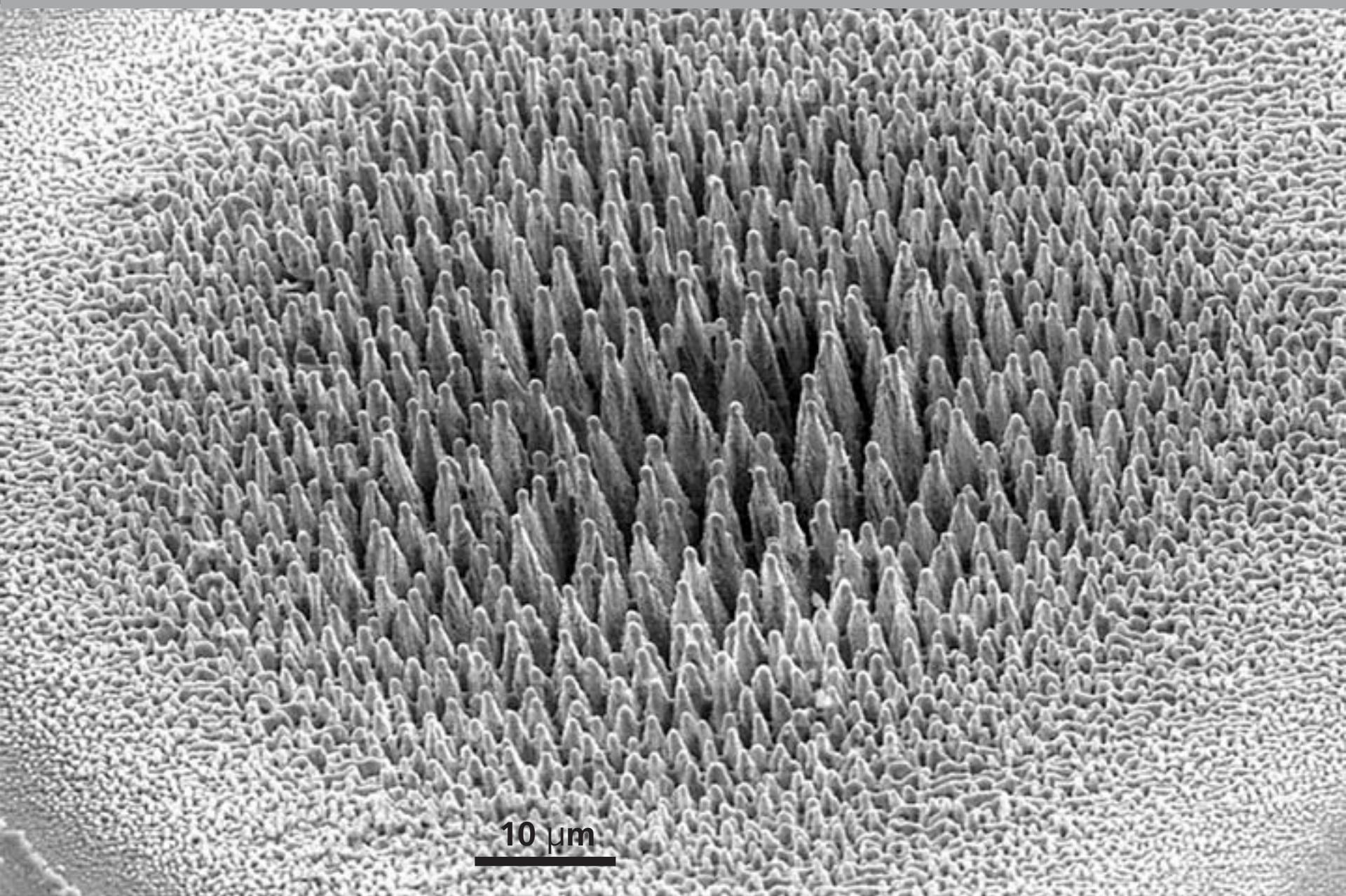
Black silicon



Black silicon

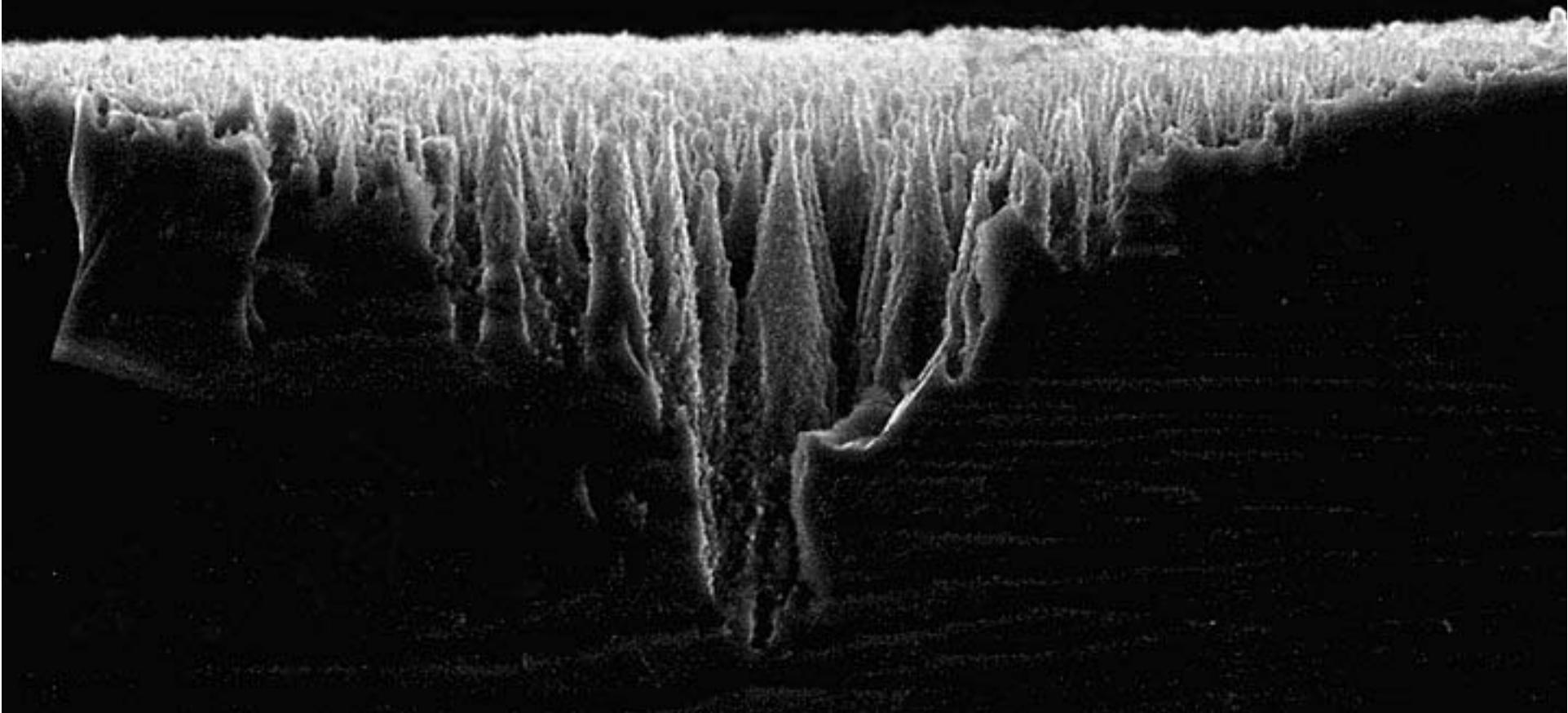


Black silicon



10 μm

Black silicon



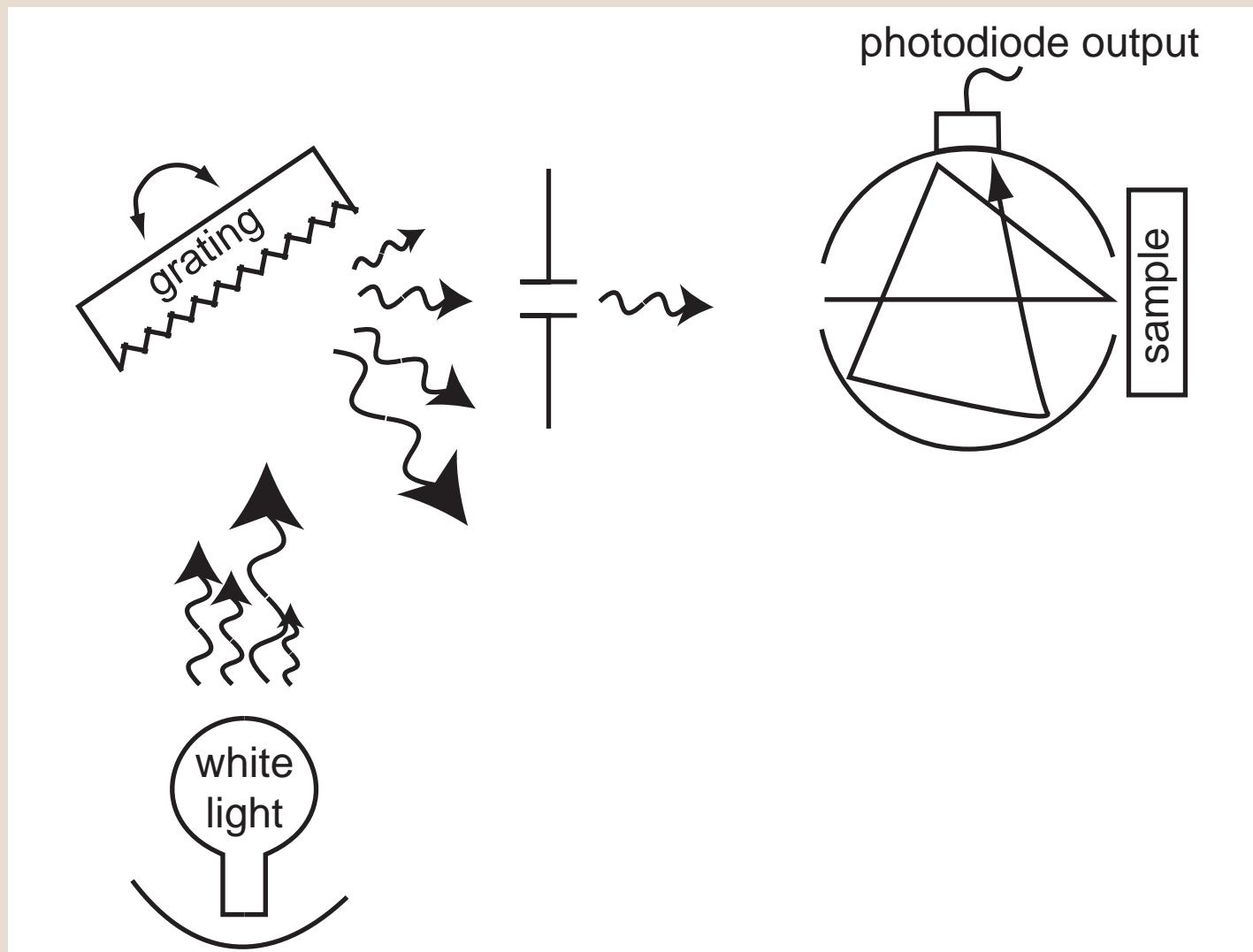
Black silicon

Optical properties

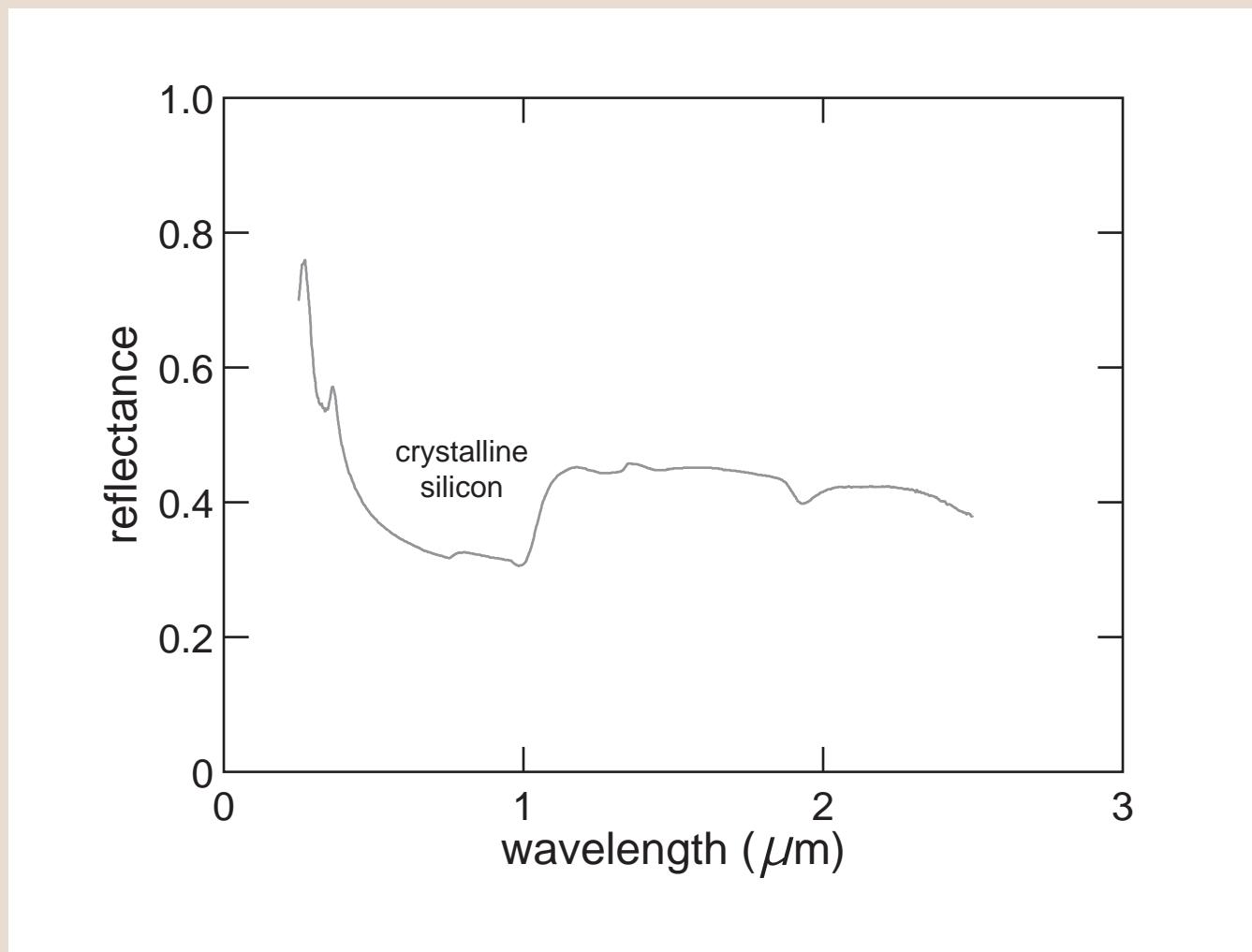
3 μm

Optical properties

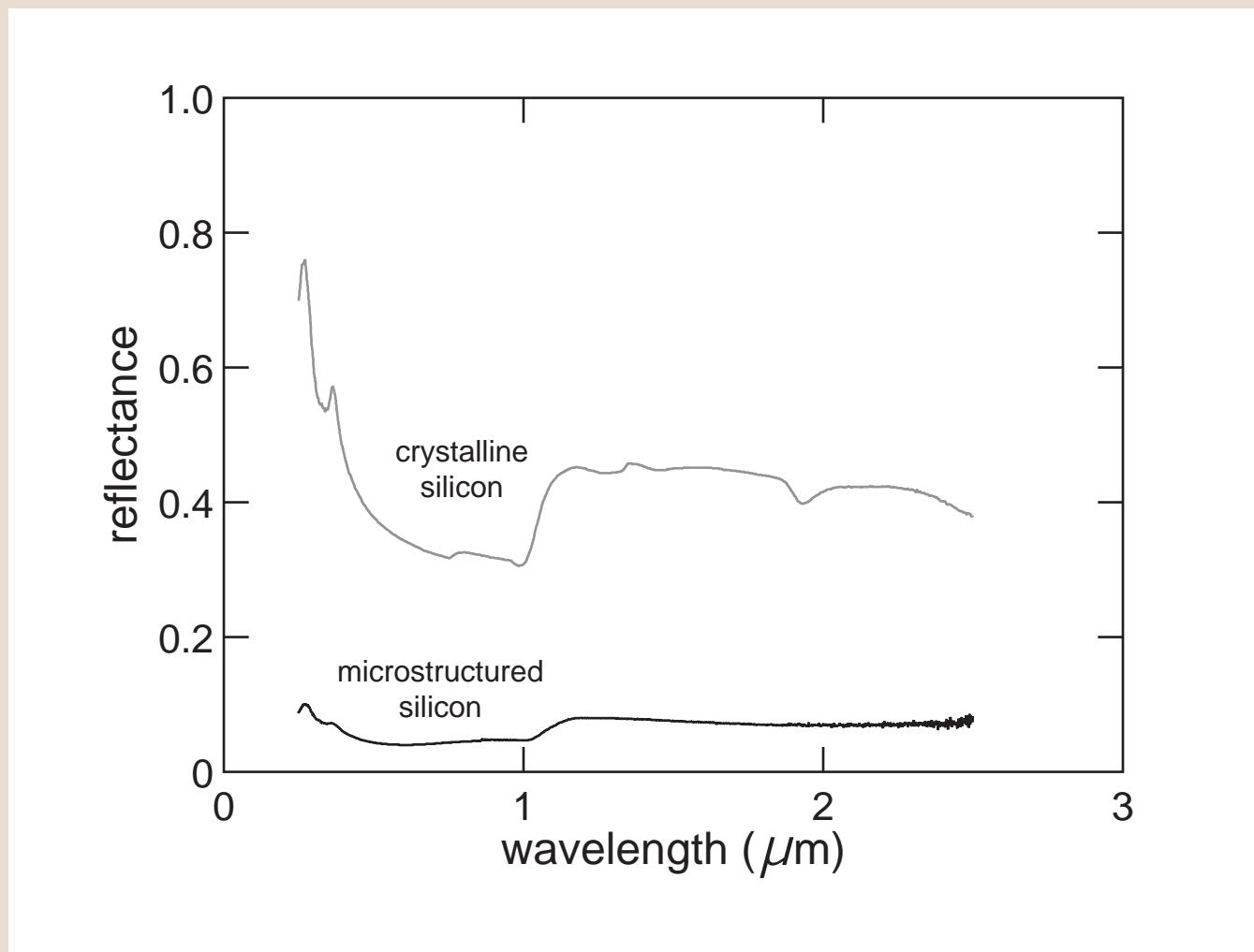
measure reflectance, transmittance with integrating sphere



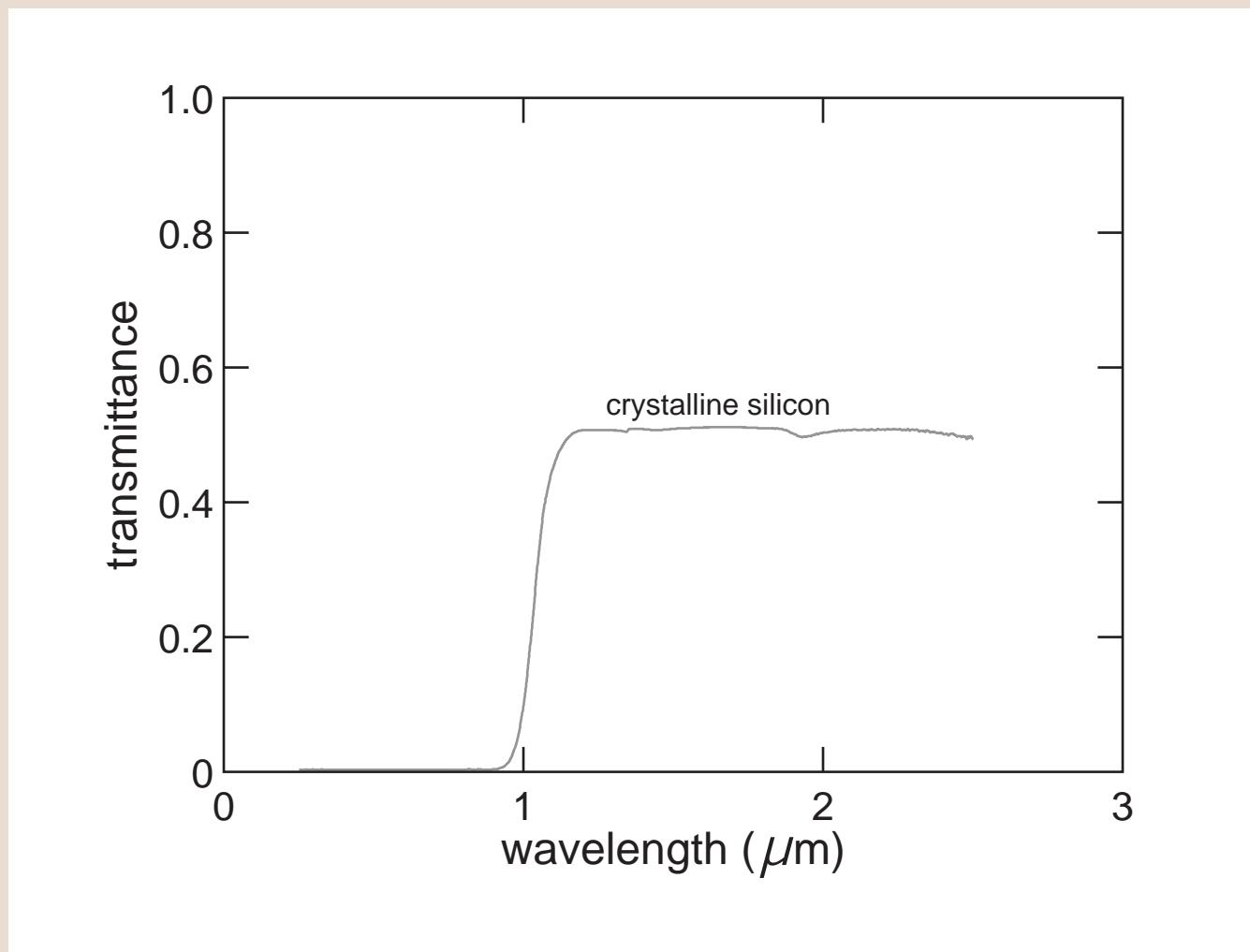
reflectance



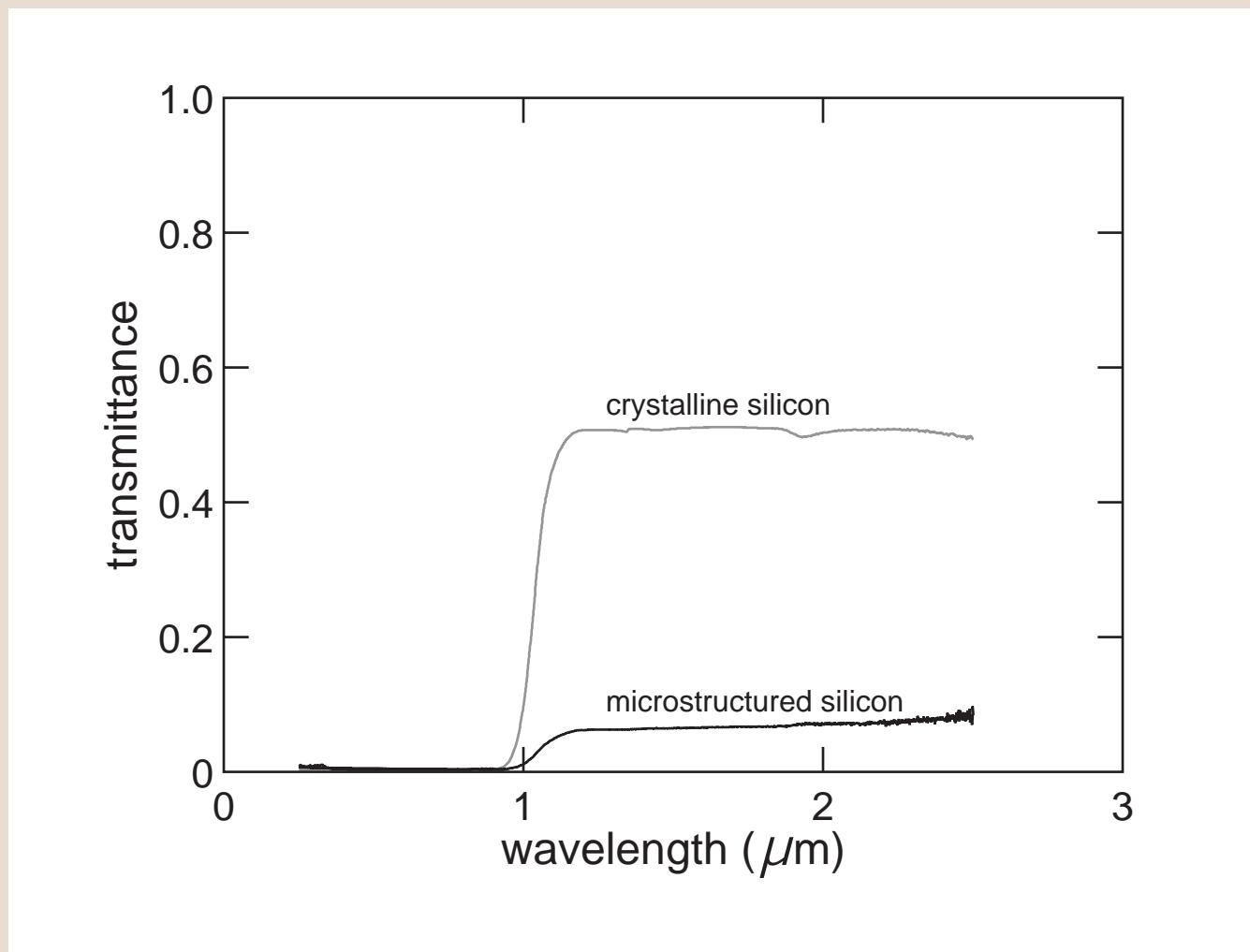
reflectance



transmittance

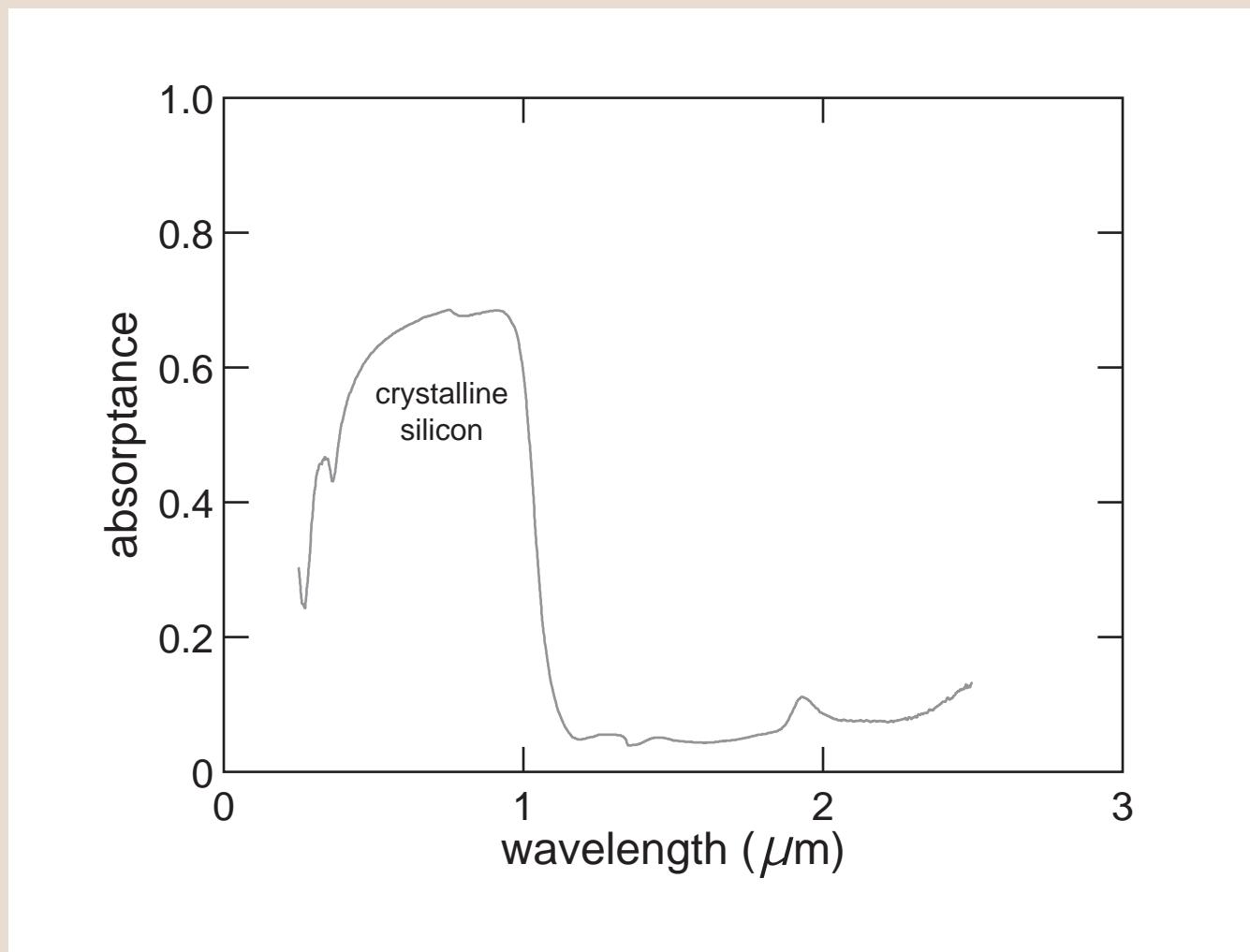


transmittance

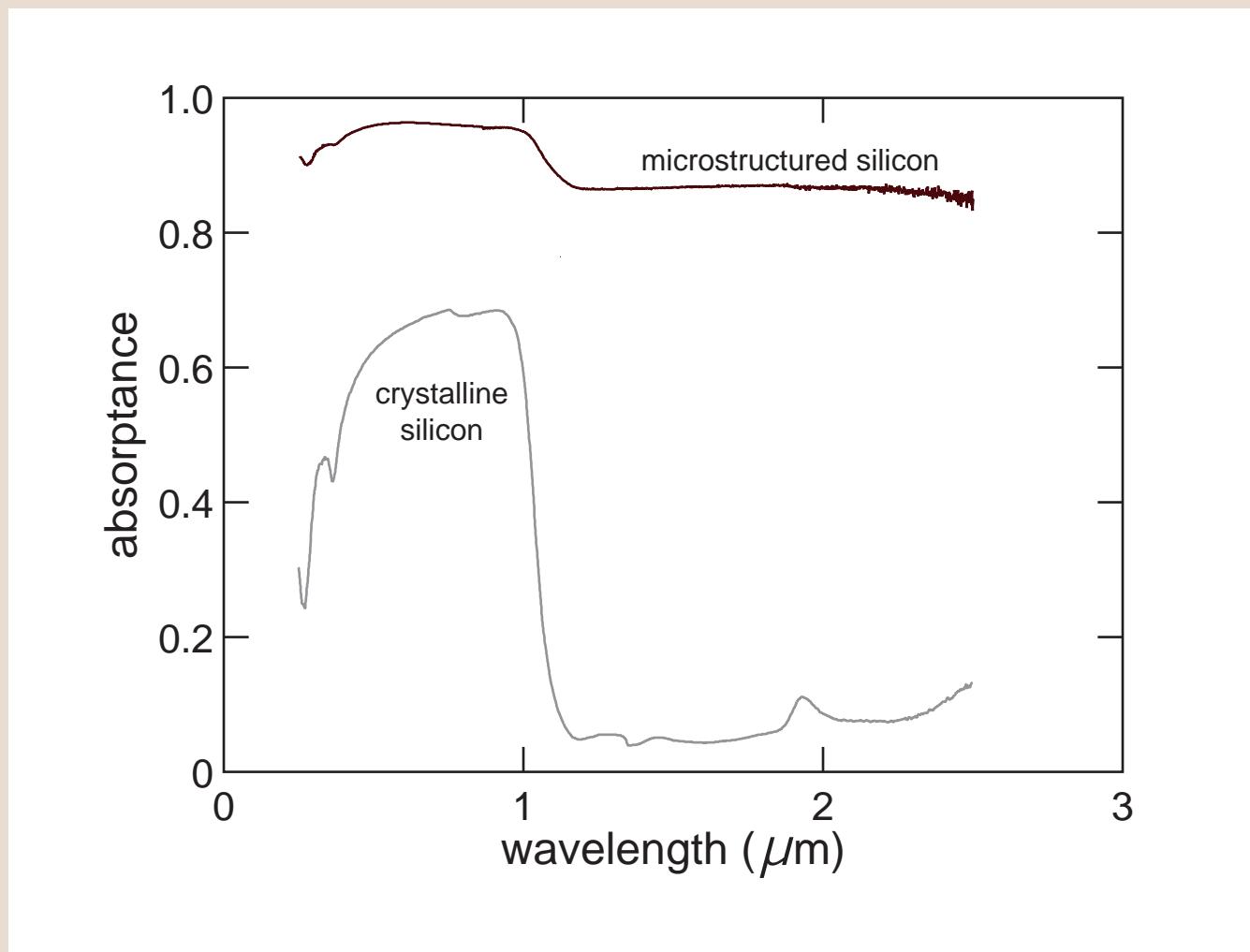


Optical properties

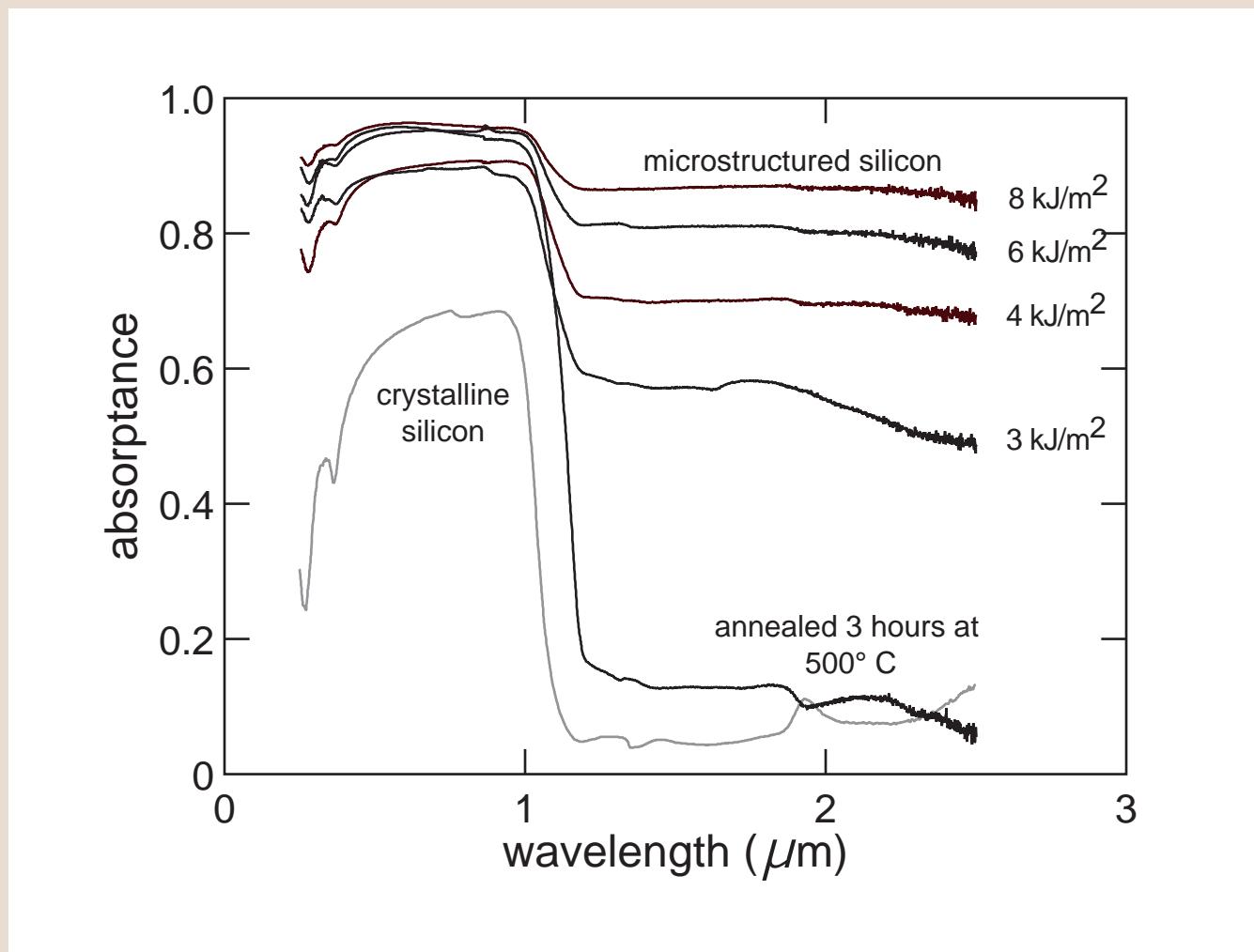
absorptance ($A = 1 - R - T$)



absorptance

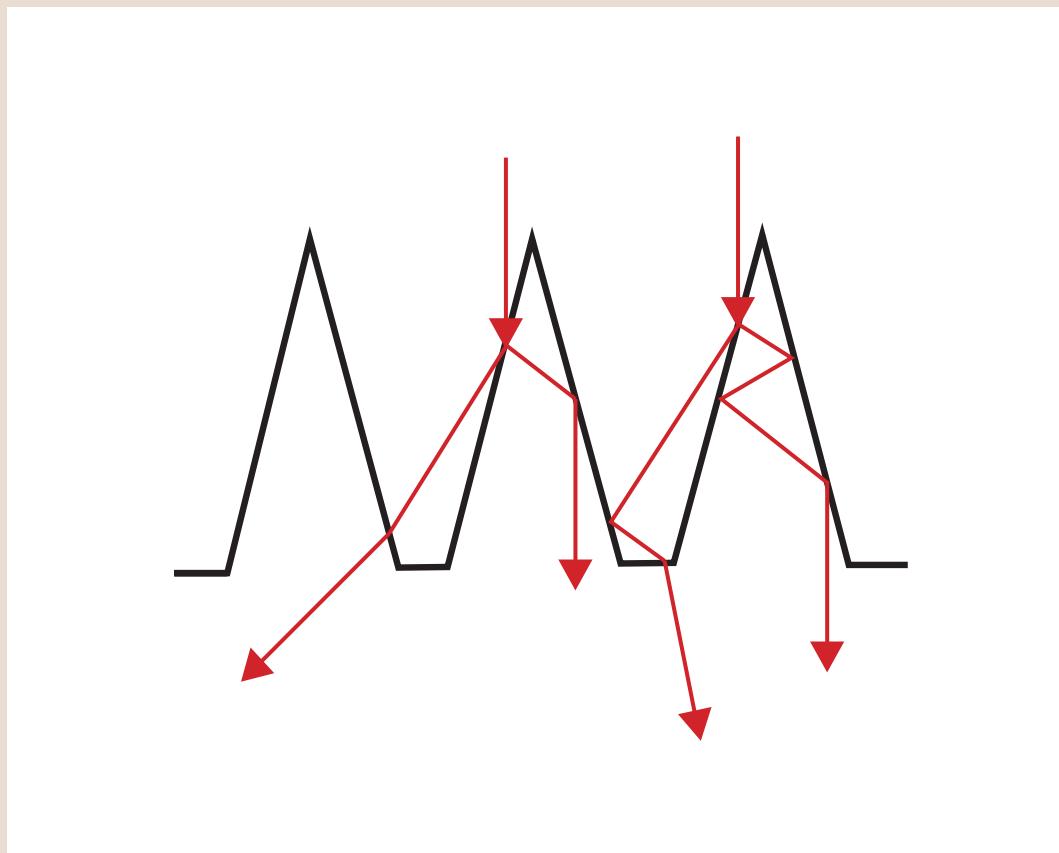


absorptance

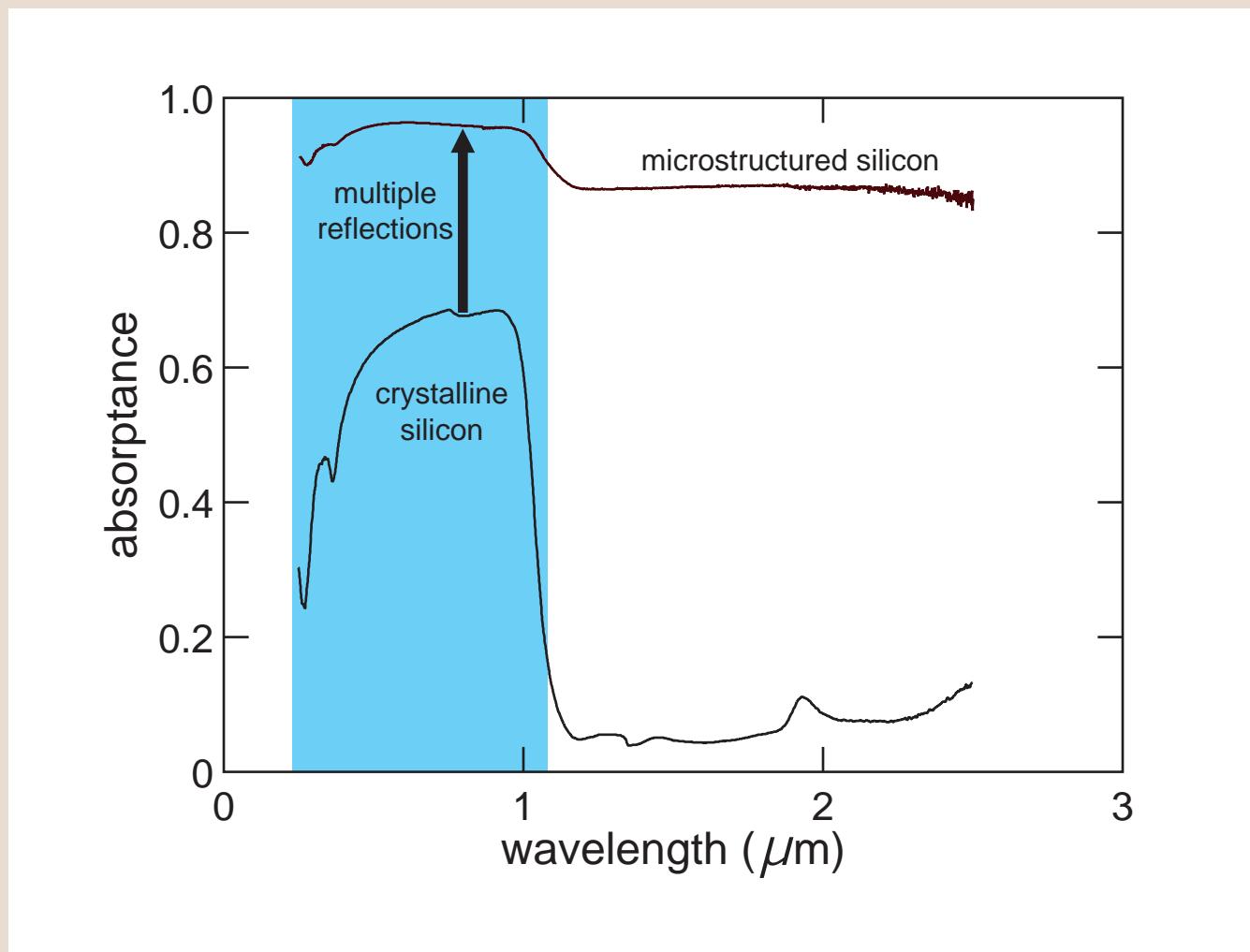


Why is it black?

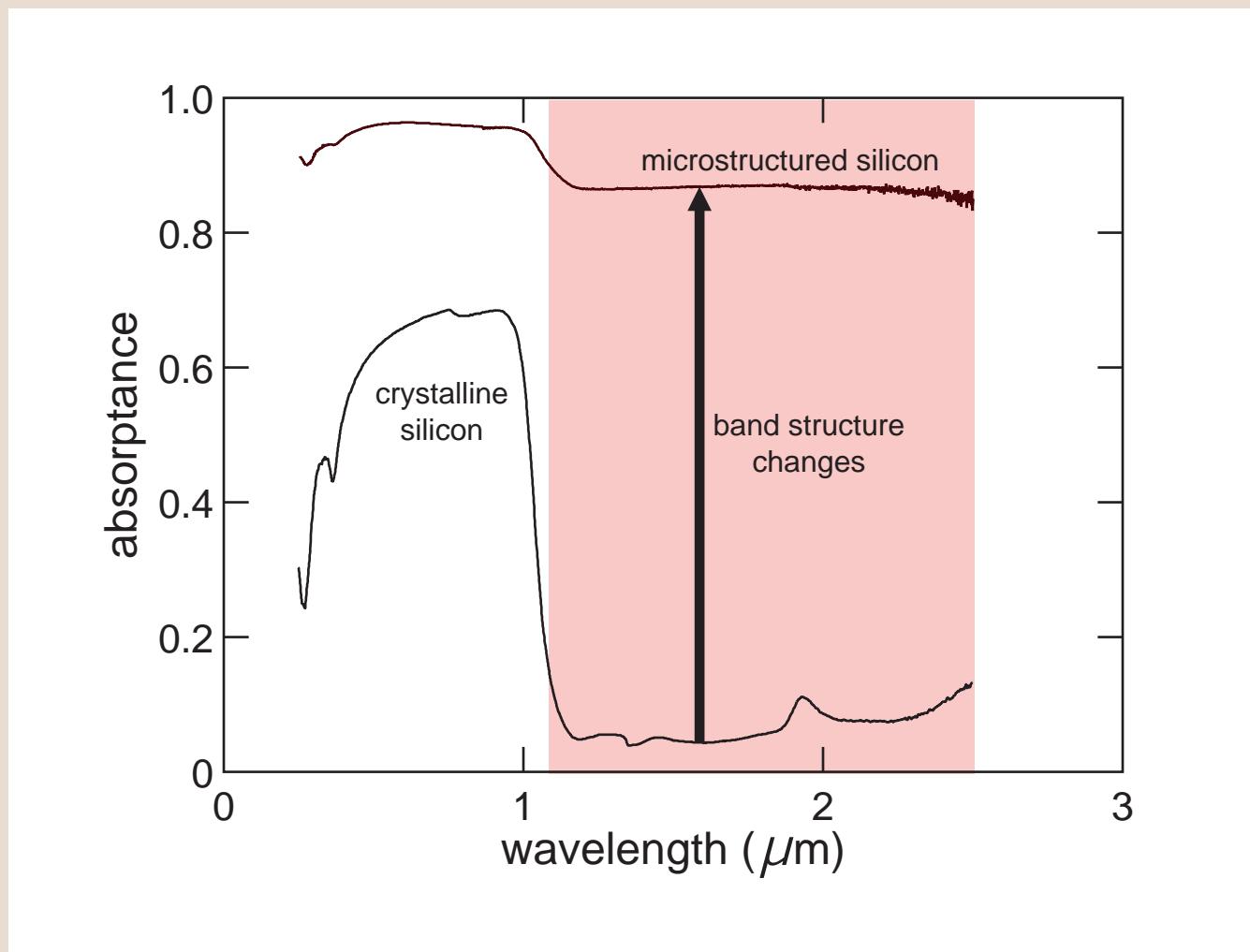
Multiple reflections can enhance absorption



absorptance



absorptance



What produces the below-band gap absorption?

What changes band structure?

- impurities
- defects

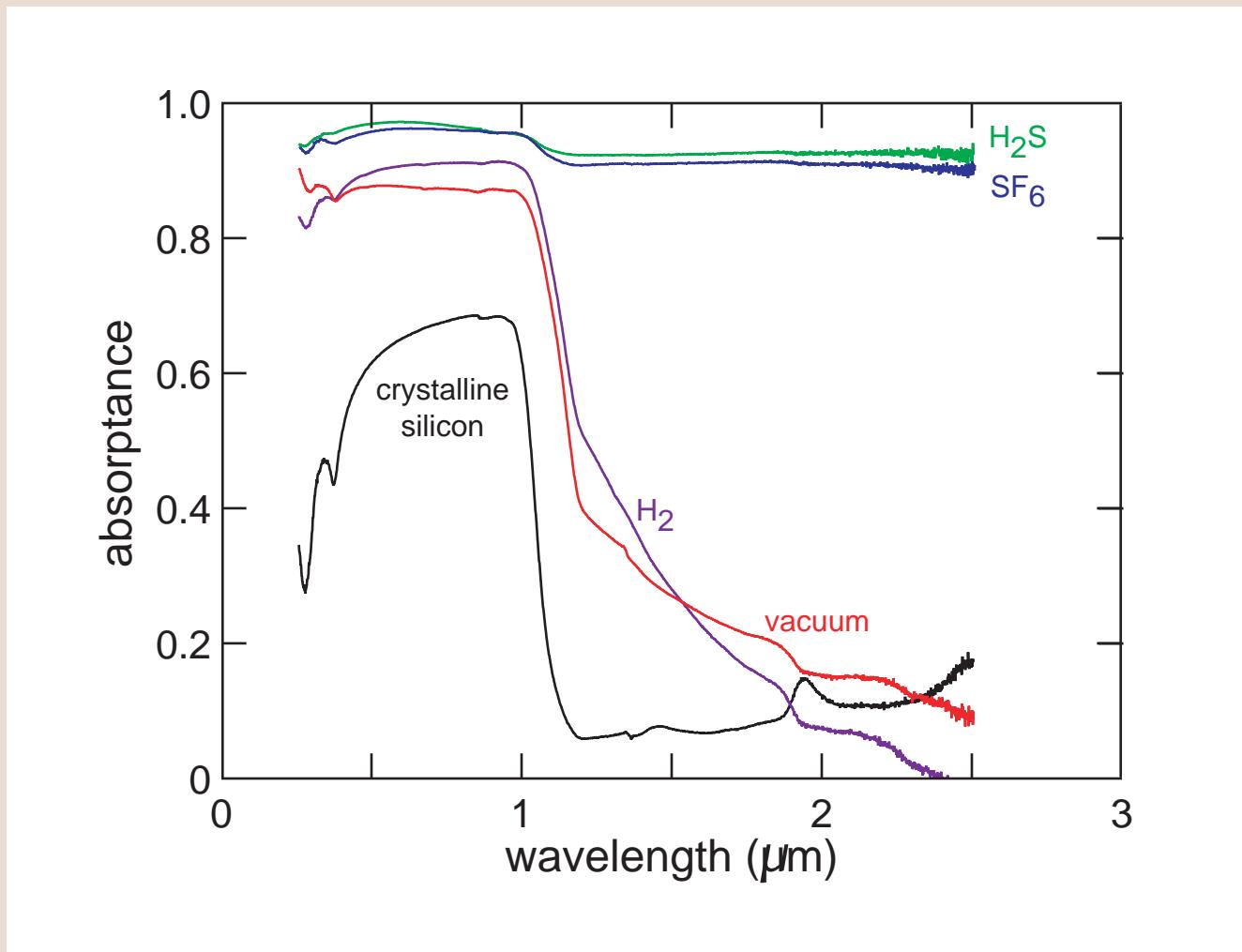
Work with other gases:

gas species incorporated into surface layer

sulfur required for below-band gap absorption
(H_2S , SF_6)

Chemical analysis

absorptance



Sheehy *et al.*, in preparation

Surfaces structured in SF₆:

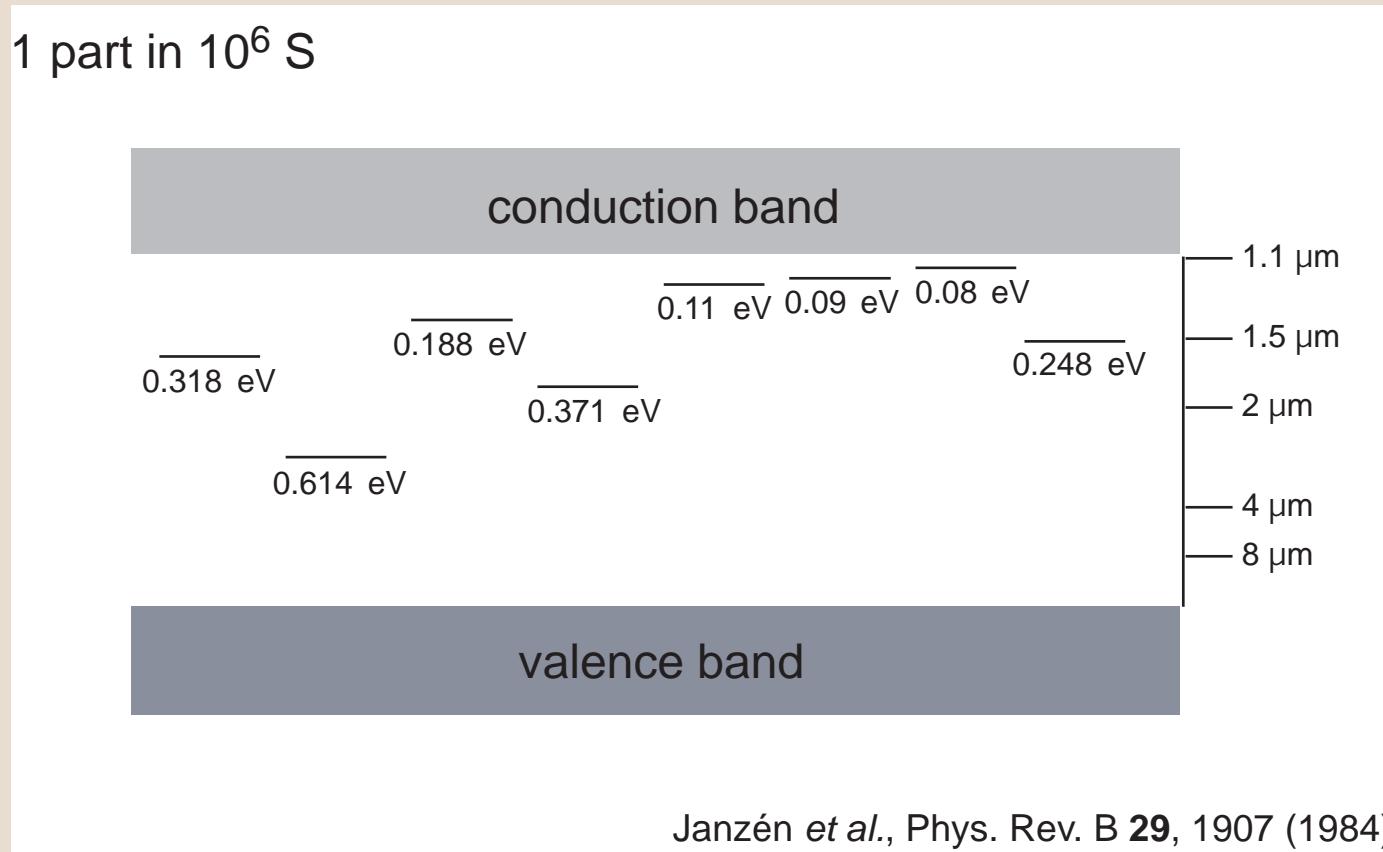
1.6% sulfur in surface layer (RBS)

also fluorine, oxygen

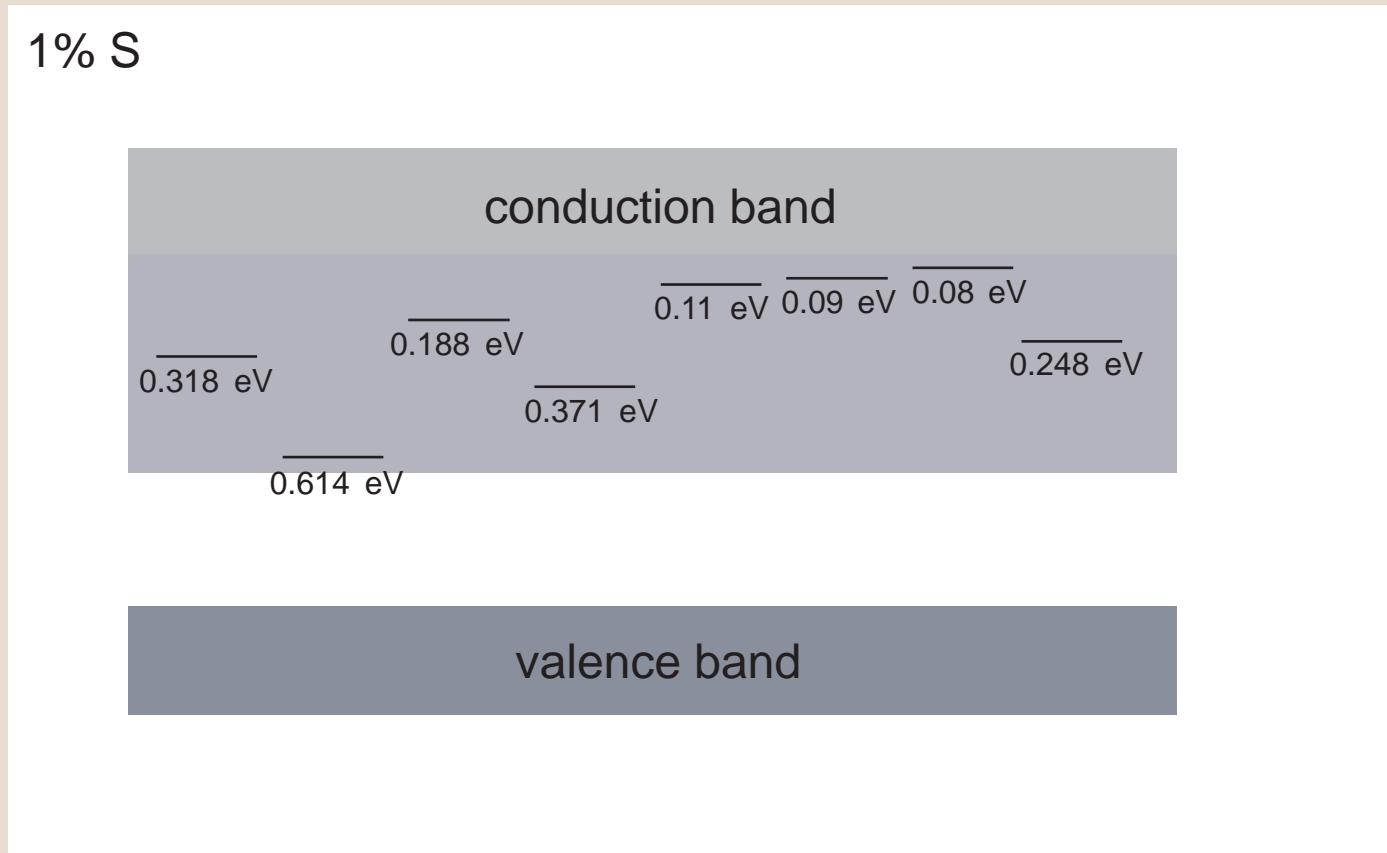
sulfur content decreases significantly on annealing

sulfur introduces states in silicon band gap

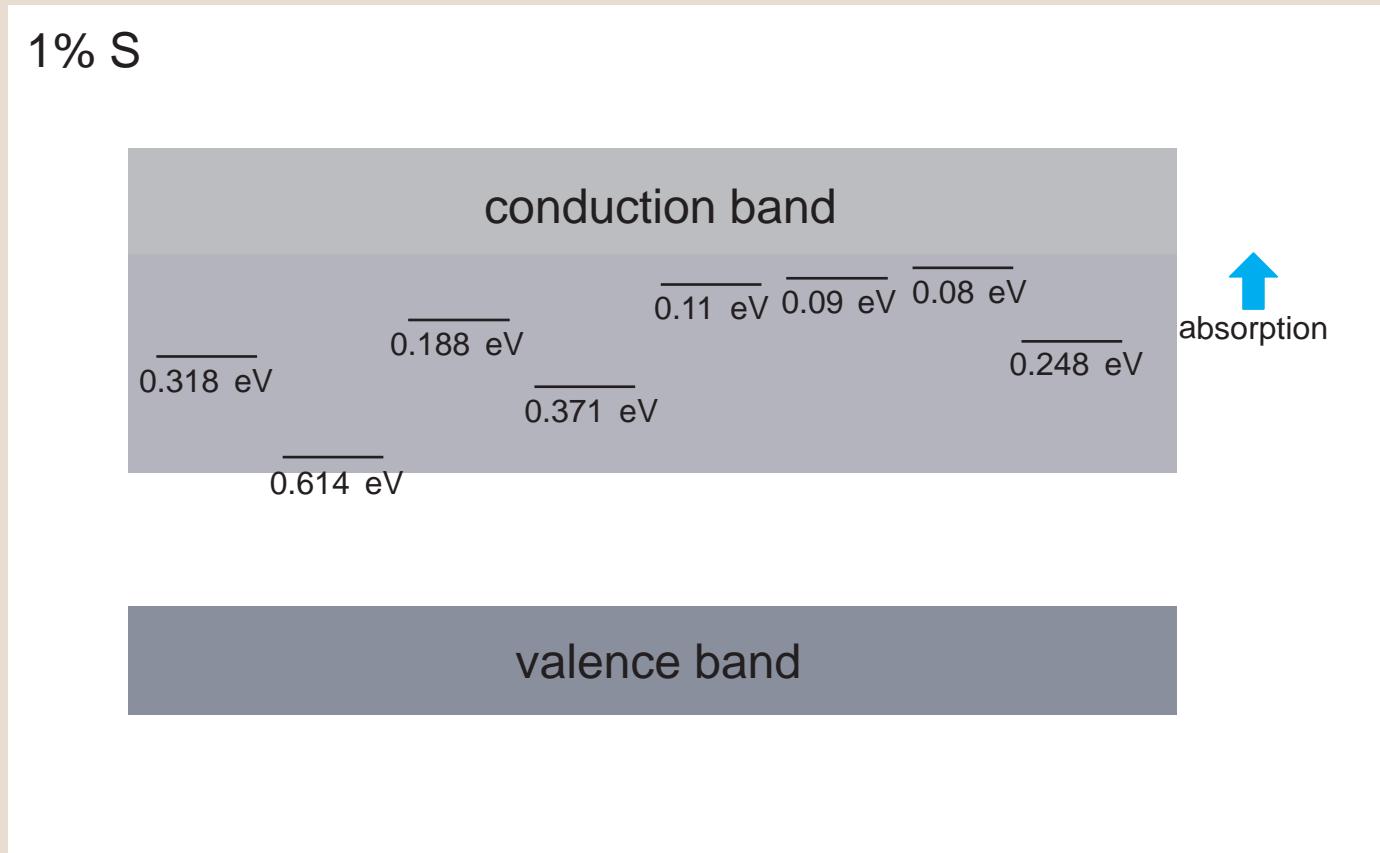
1 part in 10^6 S



at high concentrations, states may broaden into a band

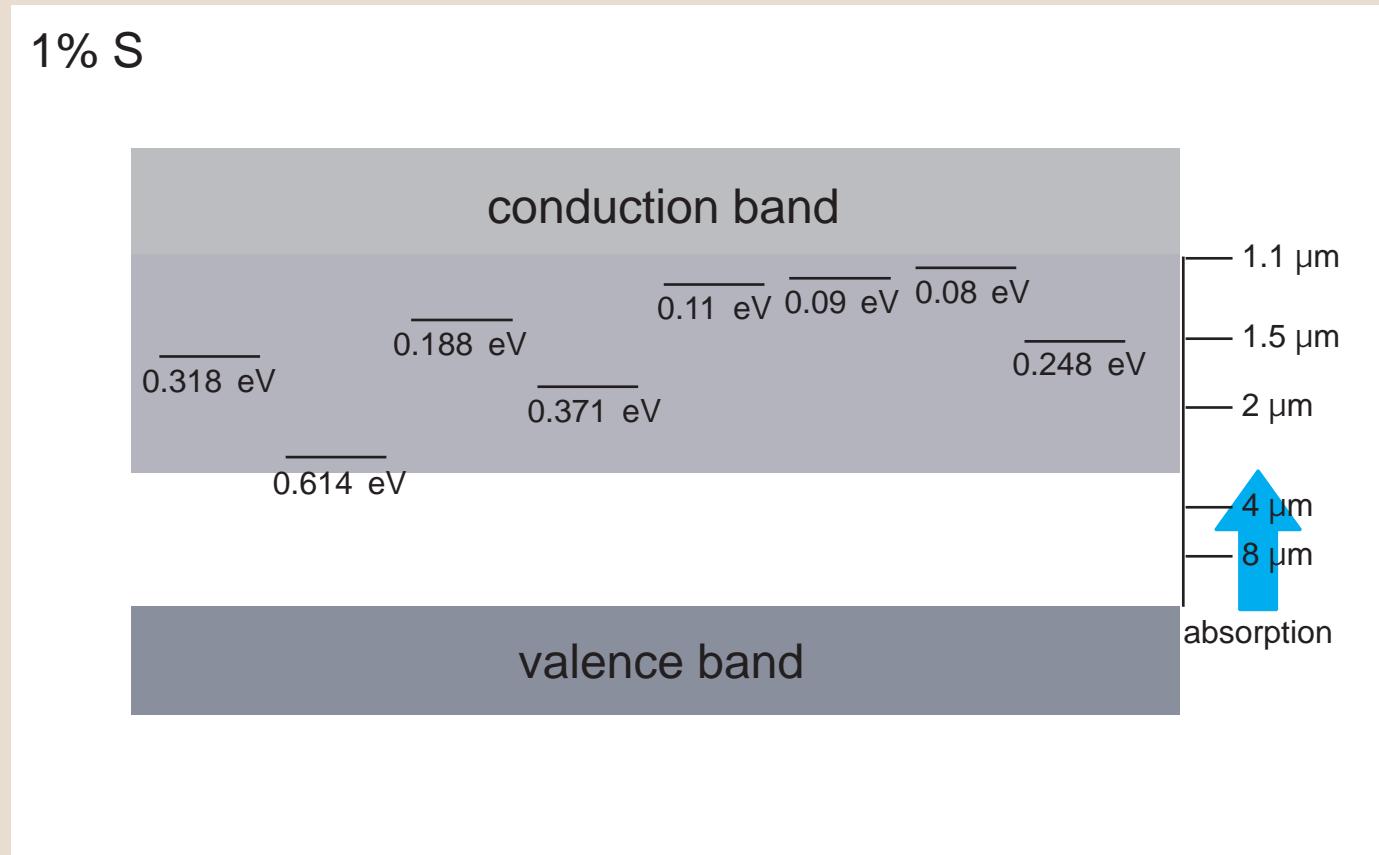


at high concentrations, states may broaden into a band



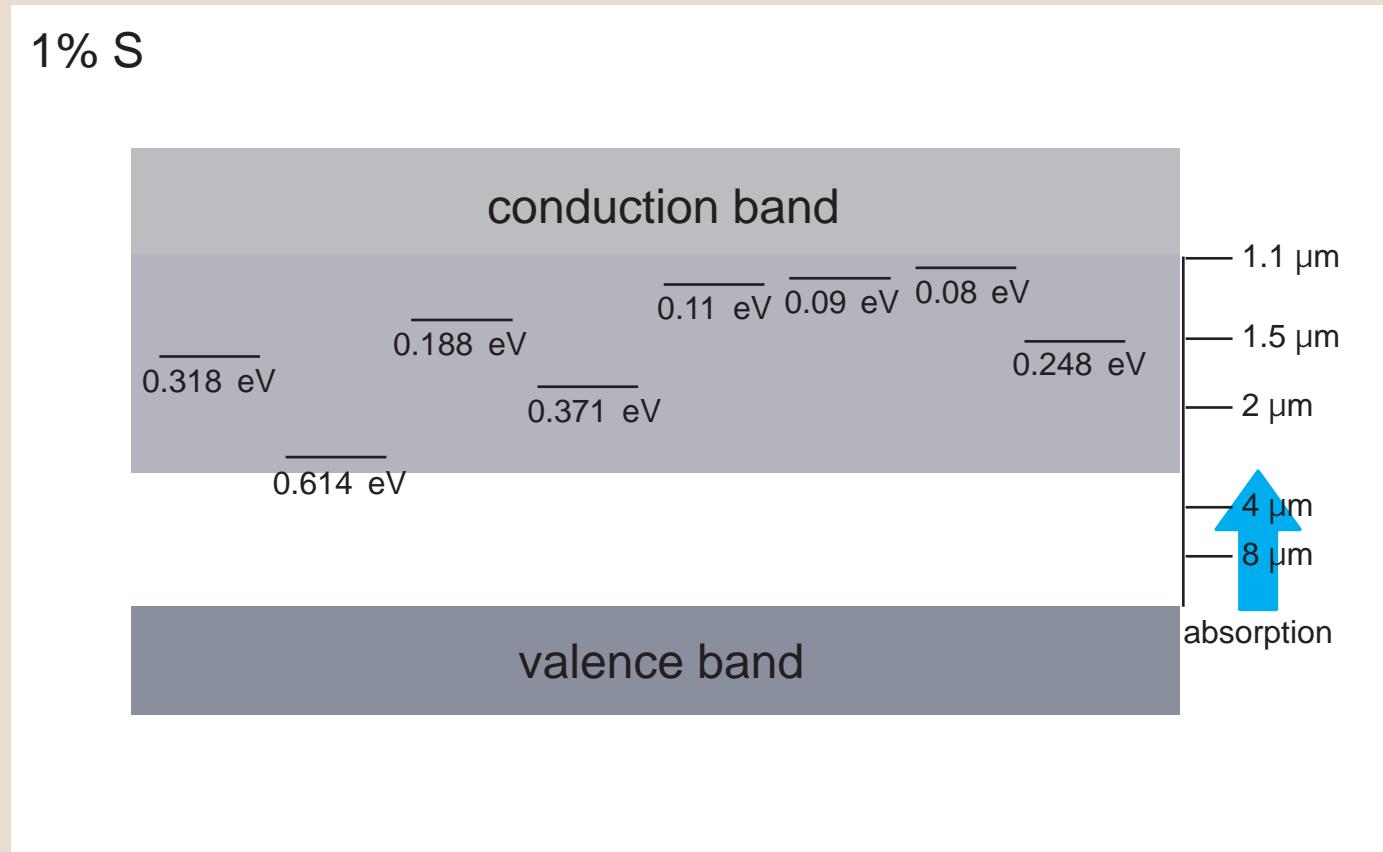
n-type impurity band: metallic

at high concentrations, states may broaden into a band



**p-type impurity band: reduced band gap,
absorption should drop off around 3 μm**

near-IR transmittance rises around 3 μm : *p*-type



Further evidence for p -type impurity band:

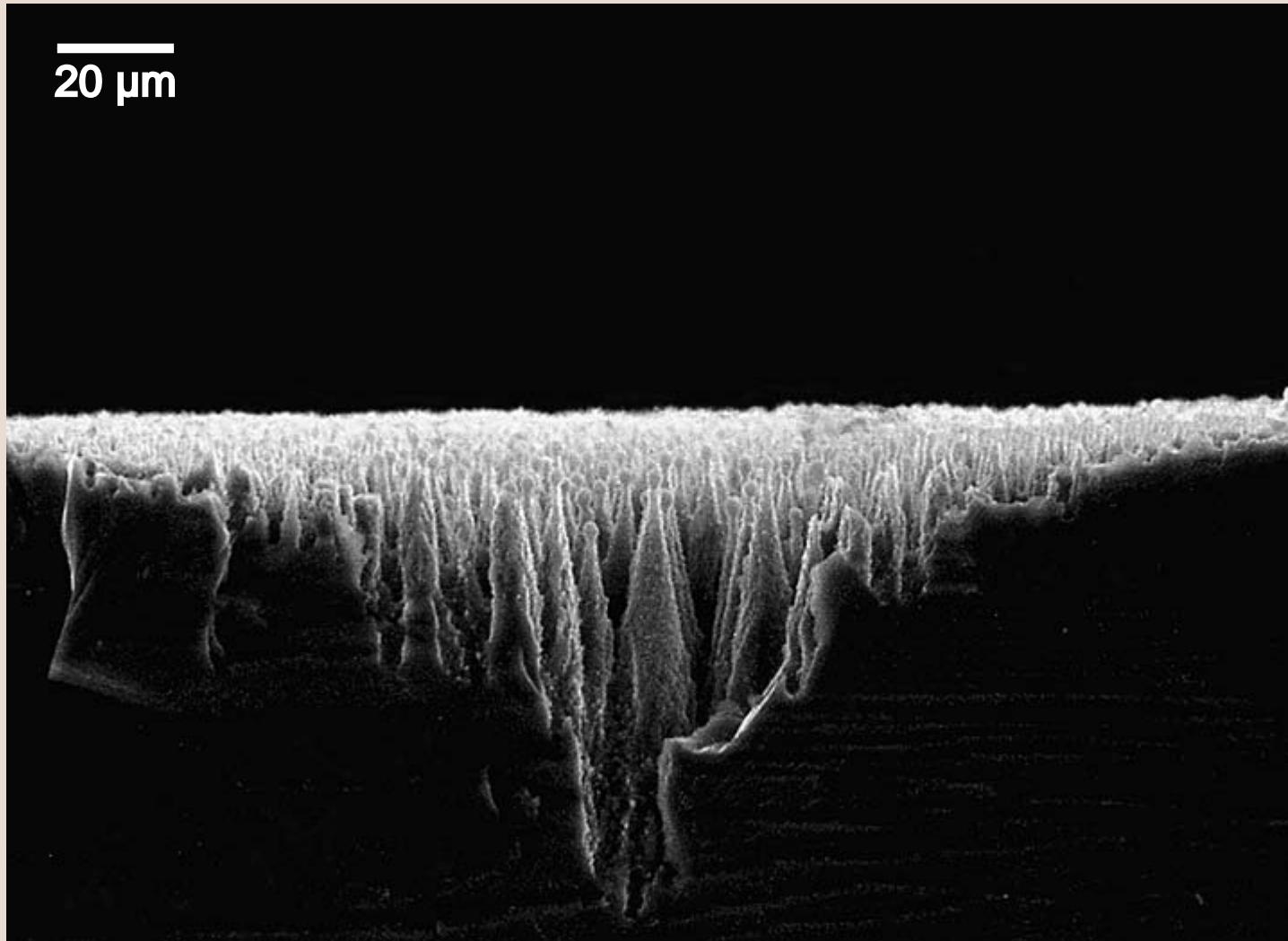
- ▶ n -type material behaves like p - n junction after structuring
- ▶ p -type material does not

Sulfur a likely explanation:

- ▶ sulfur required for below-band gap absorption
- ▶ annealing reduces sulfur and absorption
- ▶ appropriate wavelength range (*p*-type)

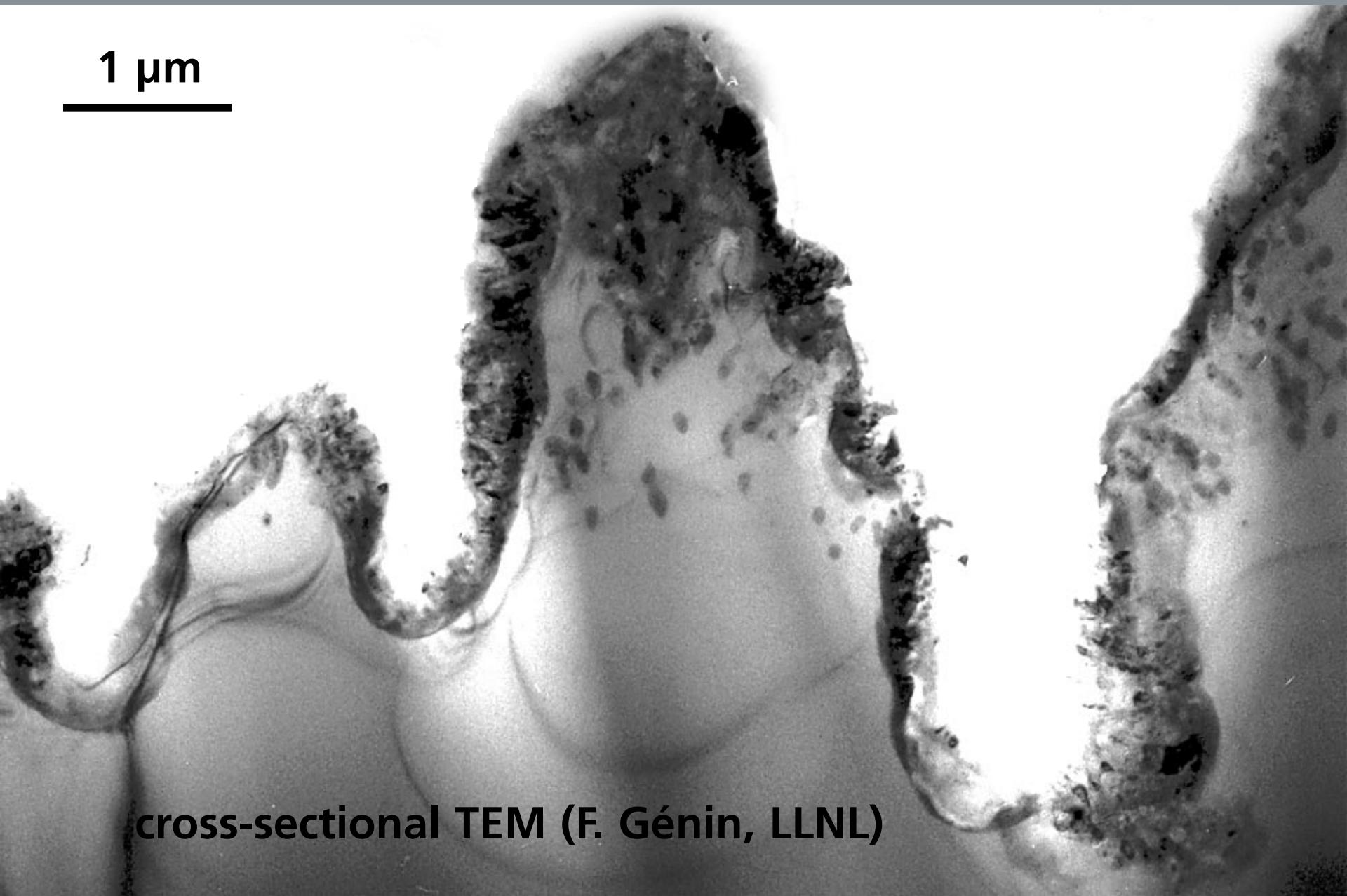
What is the underlying structure?

Structural analysis



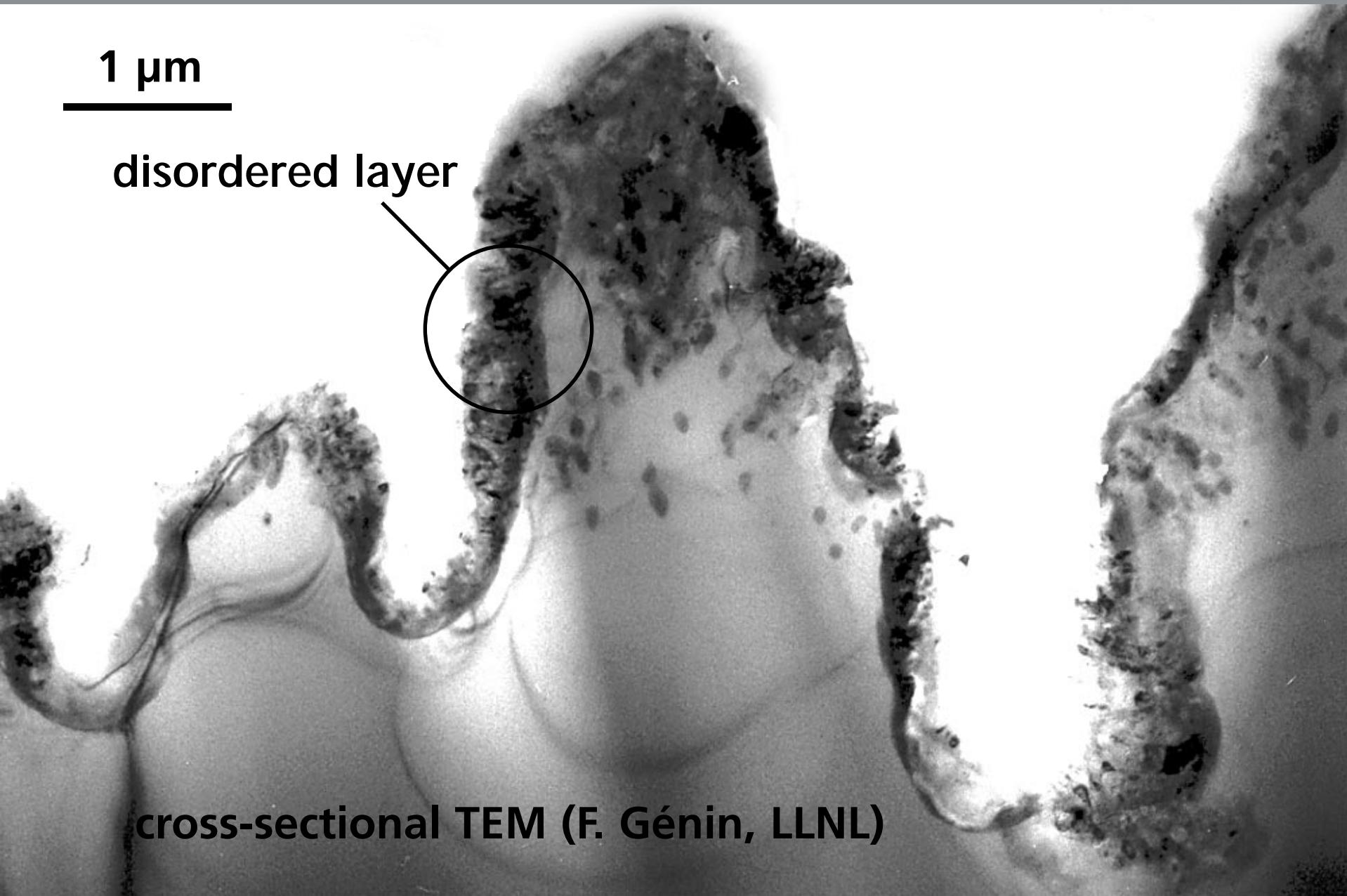
Structural and chemical analysis

1 μm



cross-sectional TEM (F. Génin, LLNL)

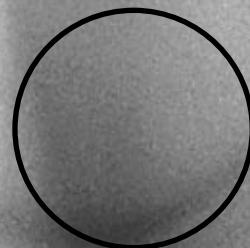
Structural and chemical analysis



Structural and chemical analysis

1 μm

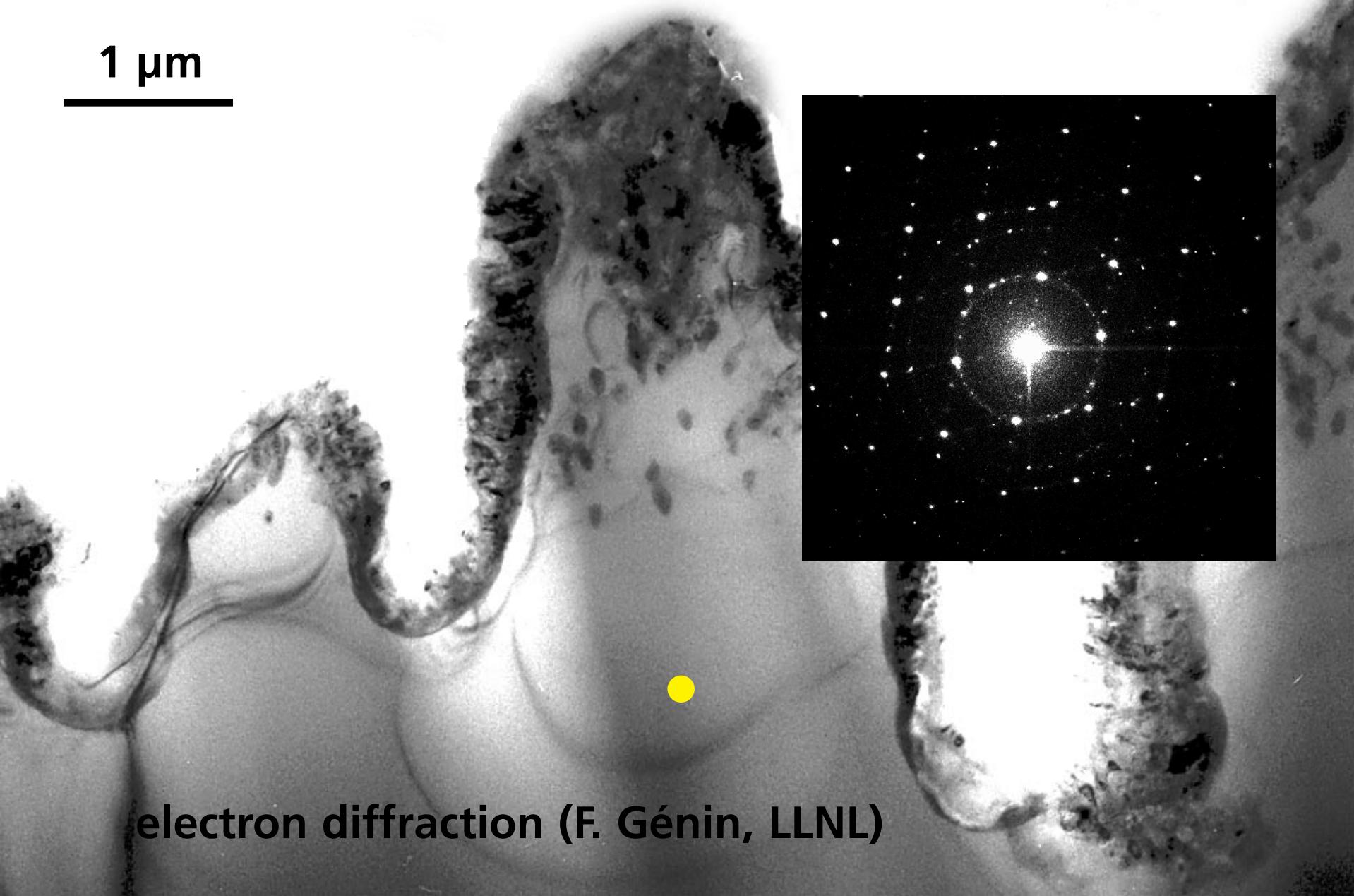
crystalline Si



cross-sectional TEM (F. Génin, LLNL)

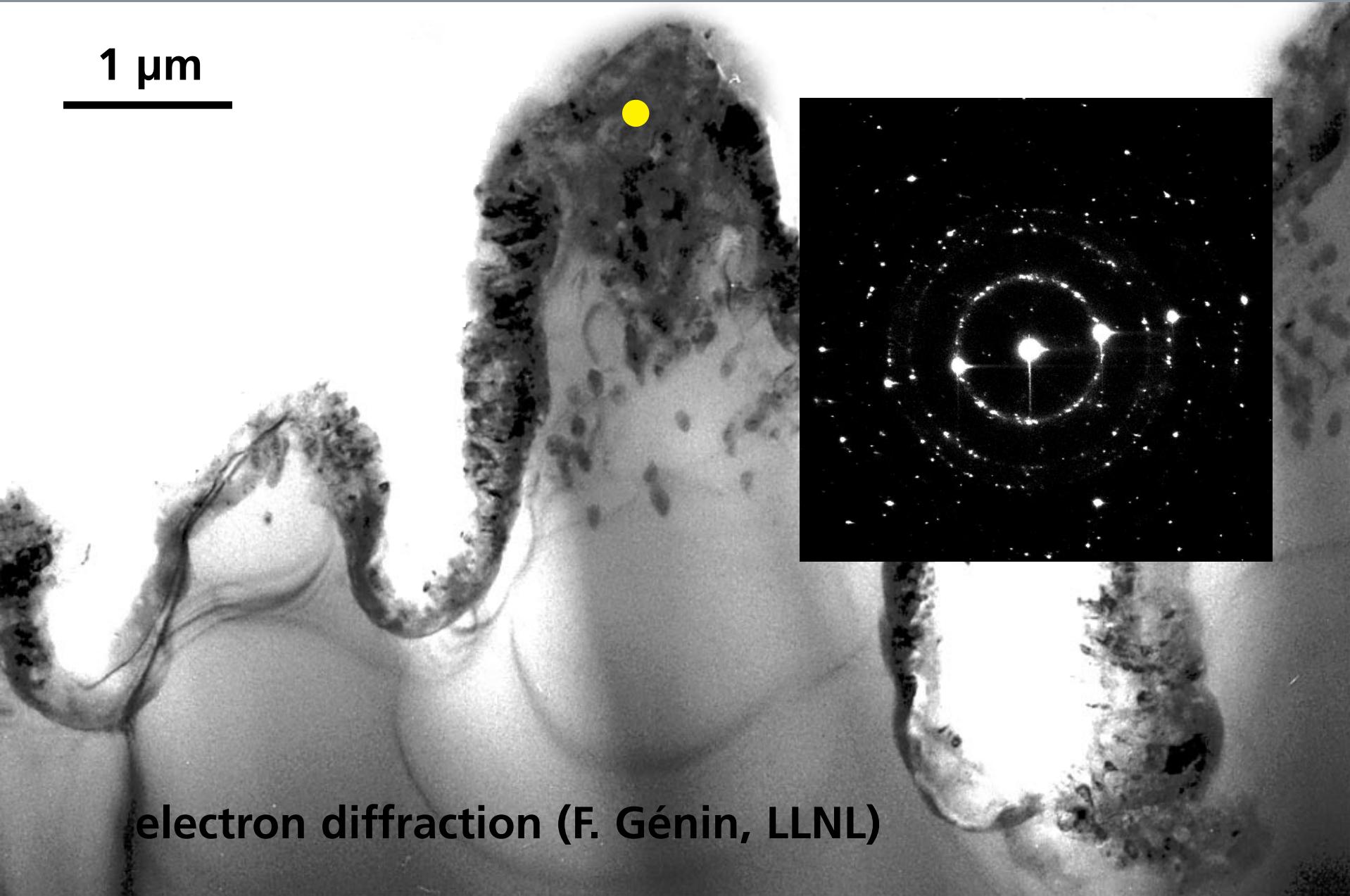
Structural and chemical analysis

1 μm



electron diffraction (F. Génin, LLNL)

Structural and chemical analysis



electron diffraction (F. Génin, LLNL)

Structural and chemical analysis

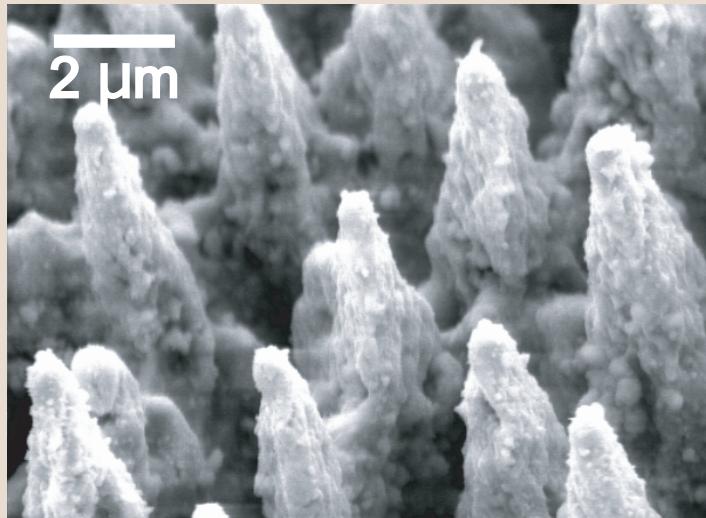
cross-sectional TEM, ion channeling:

- ▶ **core of spikes: undisturbed Si**
- ▶ **surface layer: polycrystalline Si, impurities, embedded nanocrystallites and pores**

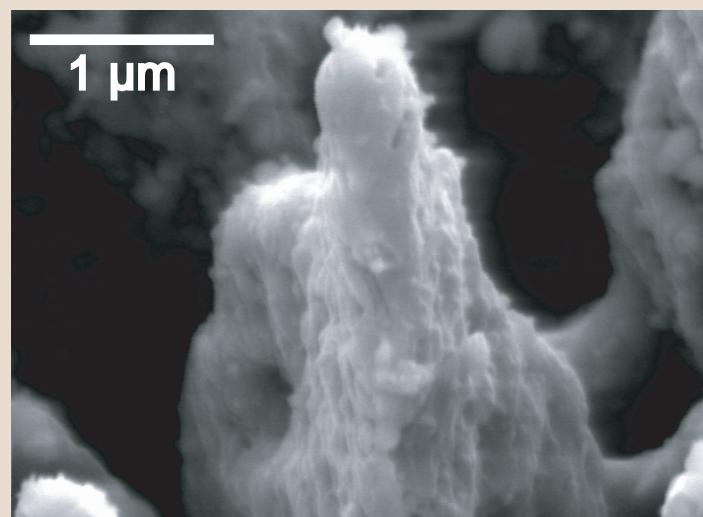
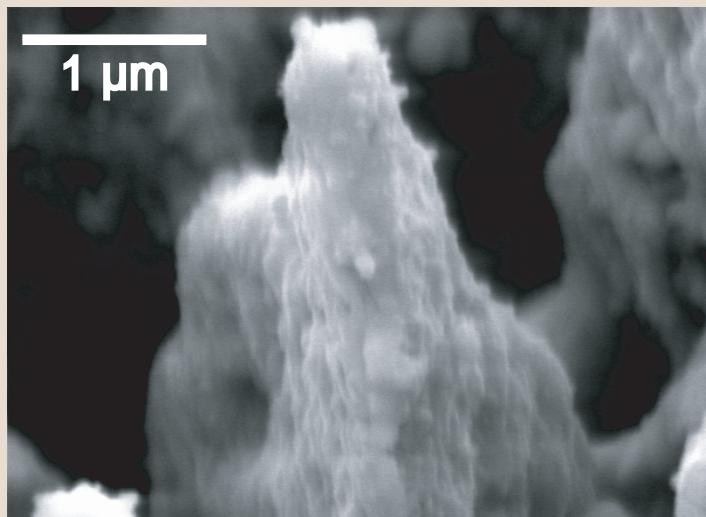
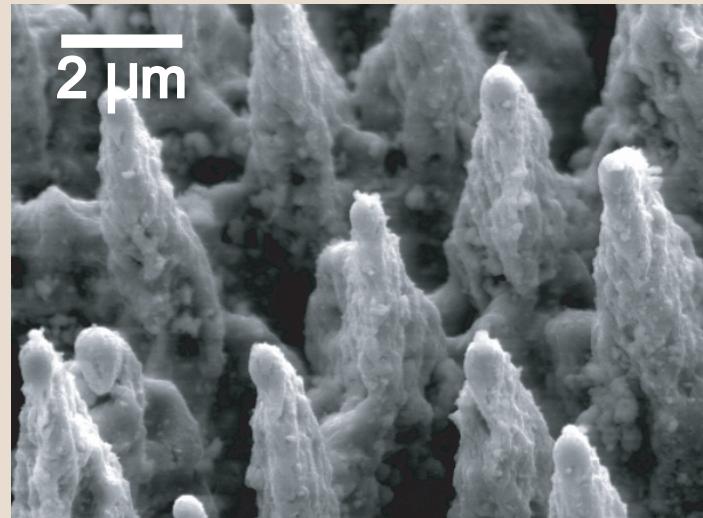
Structural analysis

Annealing at 500 C for three hours:

before

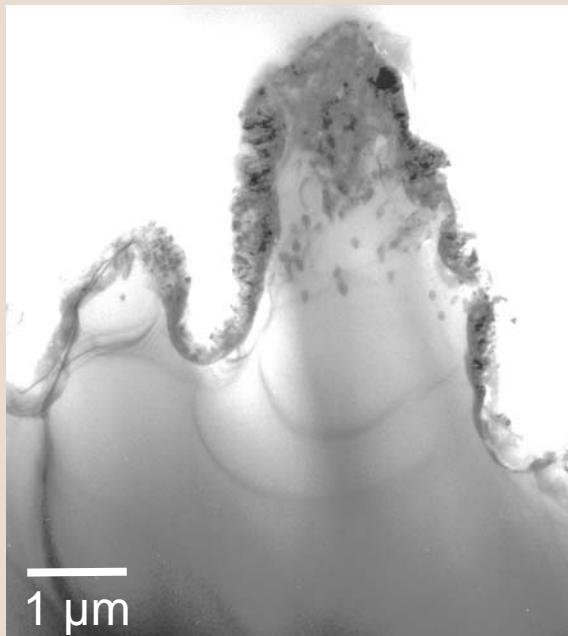


after

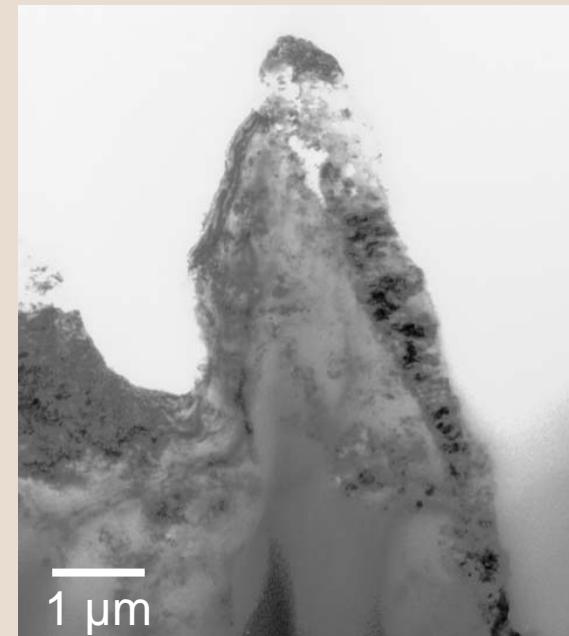


Structural analysis

not annealed



annealed



annealing does not affect visible structure

What happens with nanosecond pulses?

Nanosecond vs. femtosecond

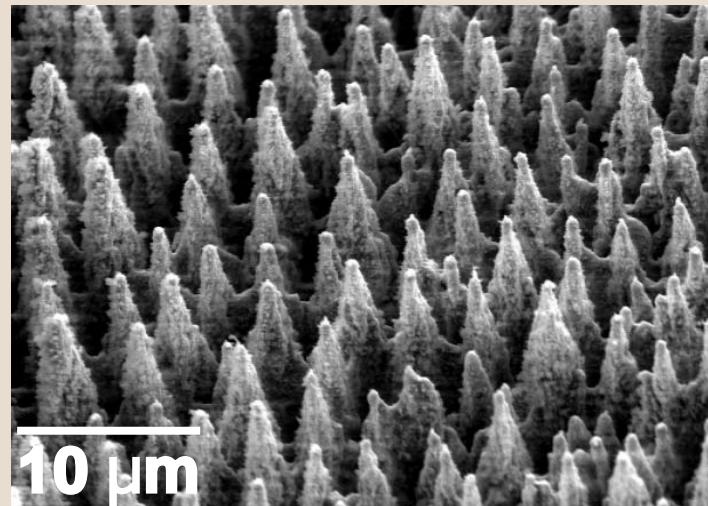
fs pulses: Her *et al.*, APL 73, 1673 (1998)

ns pulses: Pedraza *et al.*, APL 74, 2322 (1999).

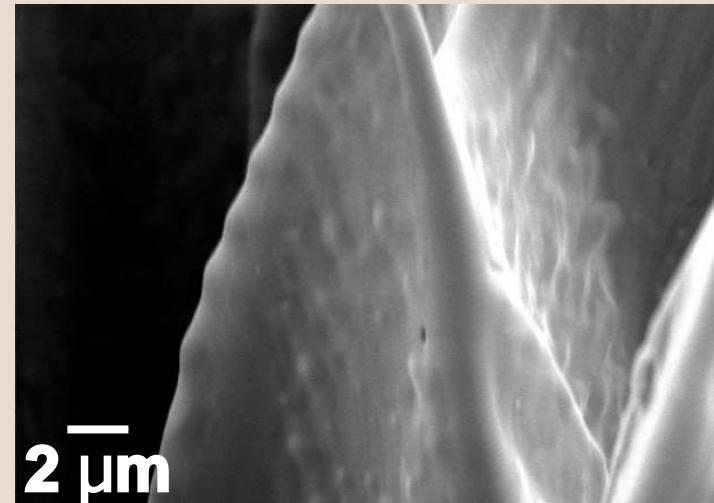
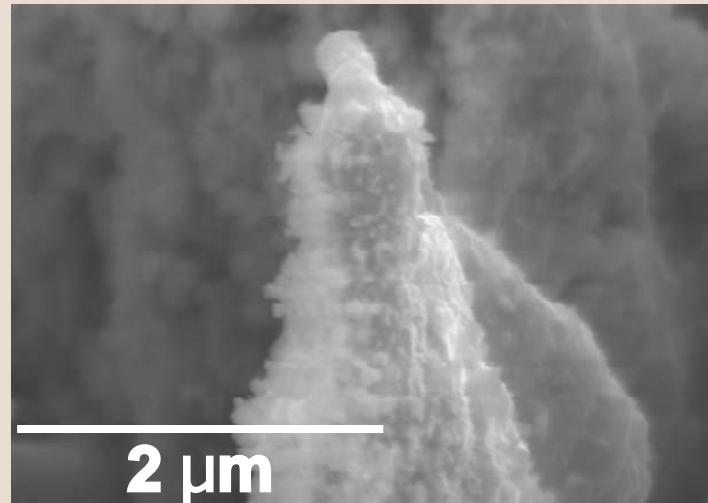
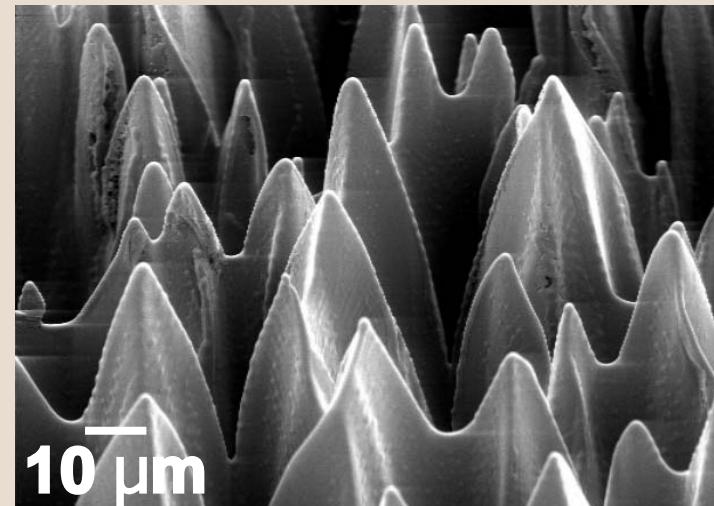
How do nanosecond and femtosecond compare?

Nanosecond vs. femtosecond

800 nm, 100 fs, 10 kJ/m²



248 nm, 30 ns, 30 kJ/m²

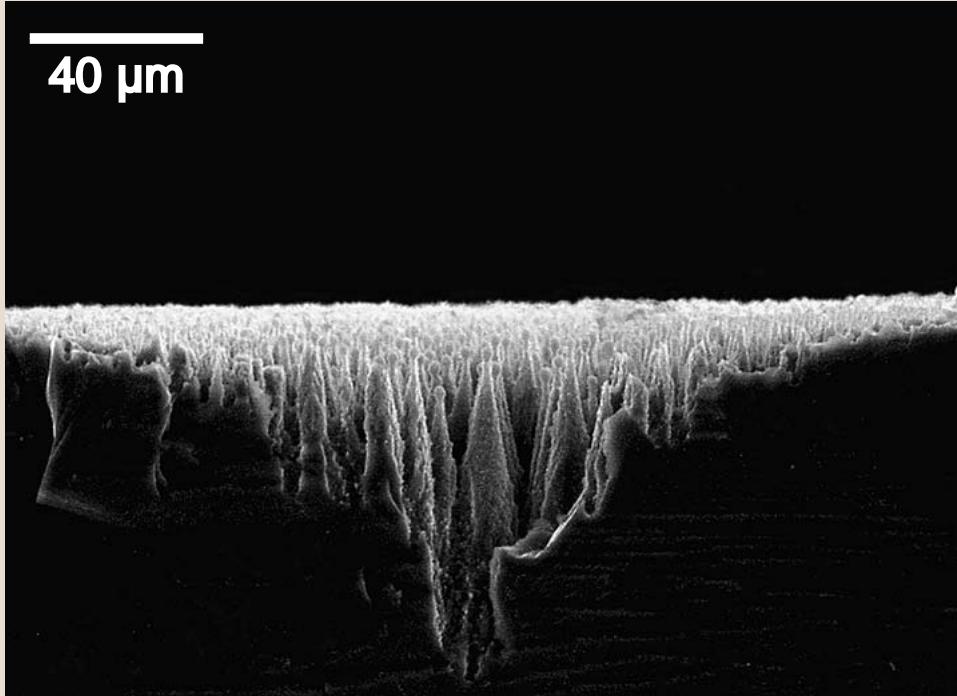


Nanosecond vs. femtosecond

Nanosecond cones bigger, smoother

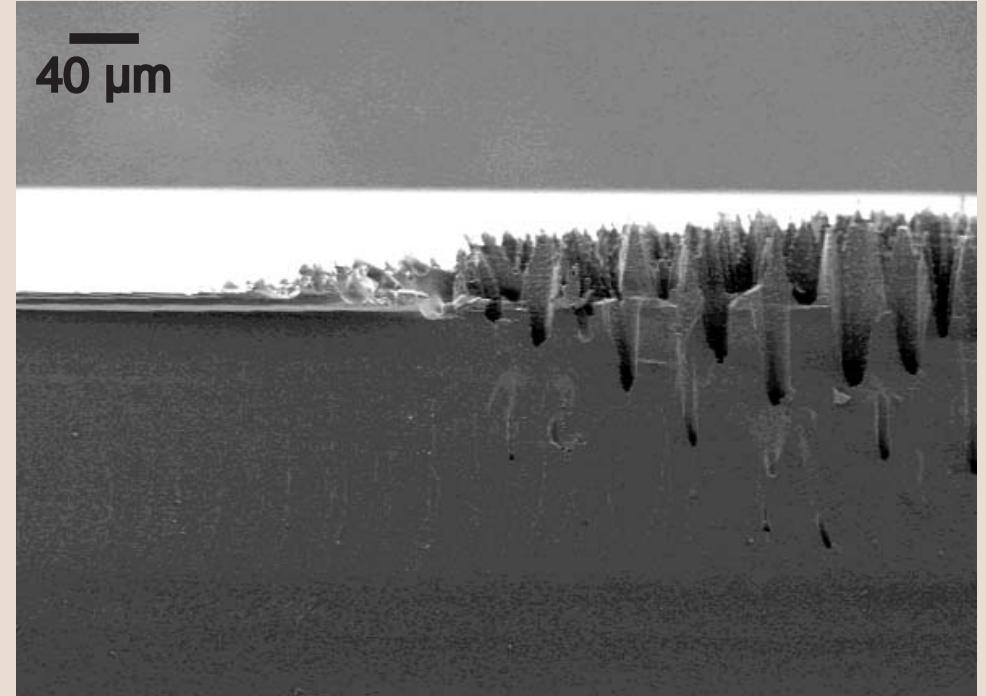
Nanosecond vs. femtosecond

800 nm, 100 fs, 10 kJ/m²



fs cones etched below surface

248 nm, 30 ns, 30 kJ/m²



ns cones grow above surface

Nanosecond vs. femtosecond

Nanosecond cones bigger, smoother

**Nanosecond cones grow, femtosecond
cones are etched**

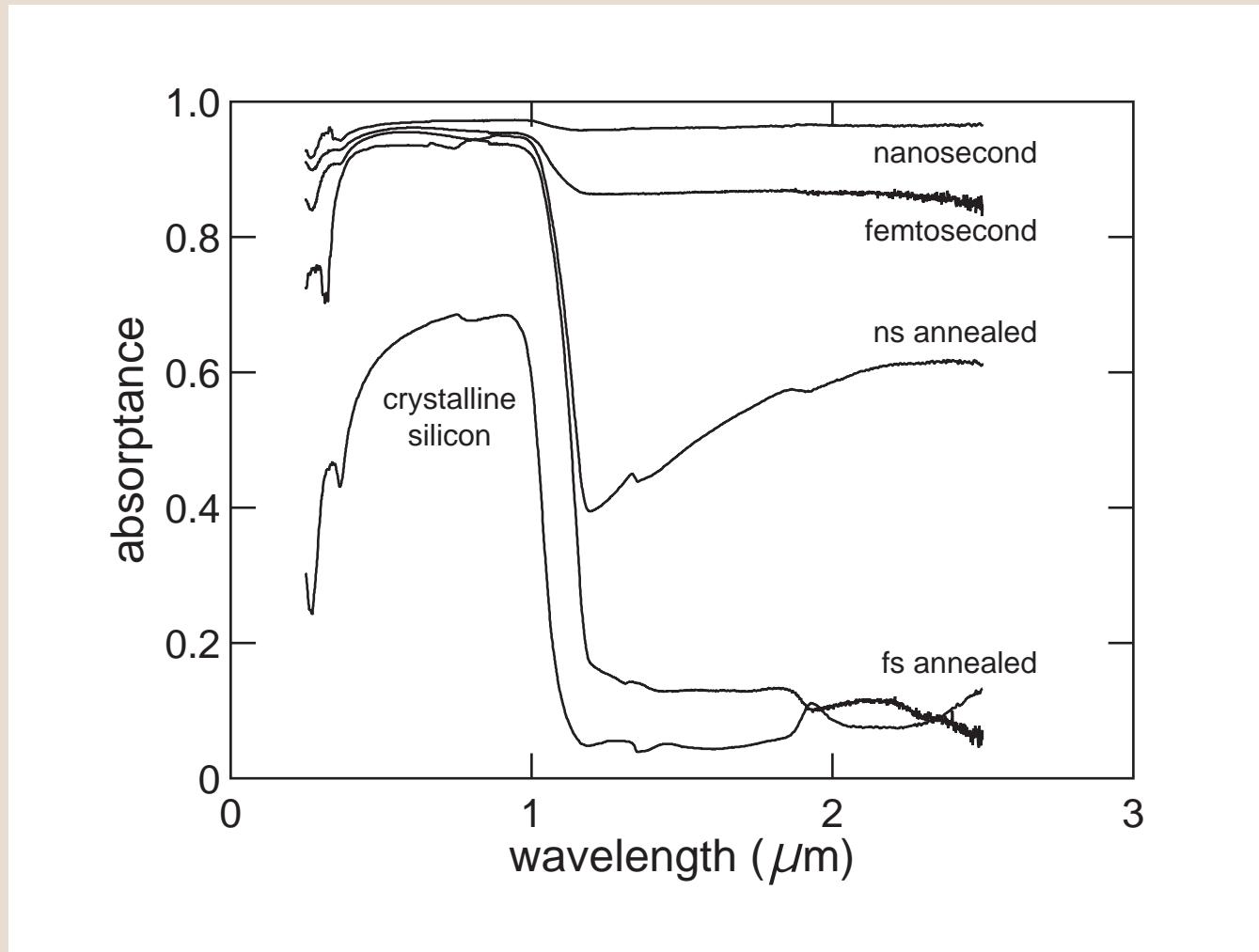
Nanosecond vs. femtosecond

Very different morphology!

How do optical properties compare?

Nanosecond vs. femtosecond

absorptance



Nanosecond vs. femtosecond

Ns and fs cone composition similar

ns: 0.7% sulfur (ion channeling)

fs: 1.6% sulfur (ion channeling)

both: sulfur content decreases significantly on annealing

also high fluorine content (ToF SIMS)

Nanosecond vs. femtosecond

Ns and fs ion channeling: structural differences

both: polycrystalline (not amorphous)

ns: significant crystallinity, sulfur 50% substitutional

fs: no substitutional sulfur

Nanosecond vs. femtosecond

Nanosecond vs. femtosecond:

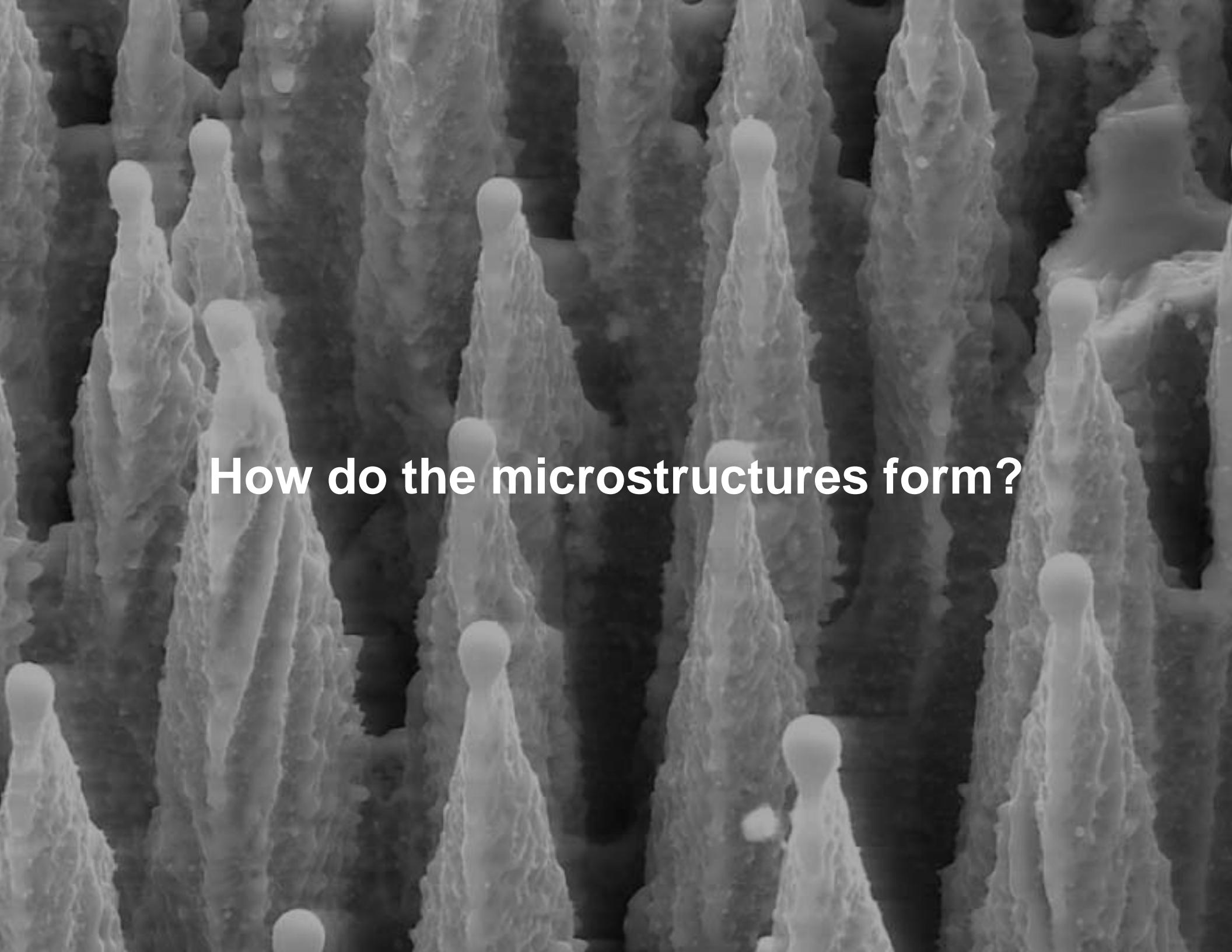
optical properties virtually identical

sulfur content similar

structure and morphology very different!

Summary of optical properties

- ▶ visible absorptance: multiple reflections
- ▶ infrared absorptance: new electronic states
- ▶ p-type sulfur impurity band below CB edge



How do the microstructures form?

x2000
#3548
512 x 480

20 μ m

10kV 15mm
0000



x2000

#3548

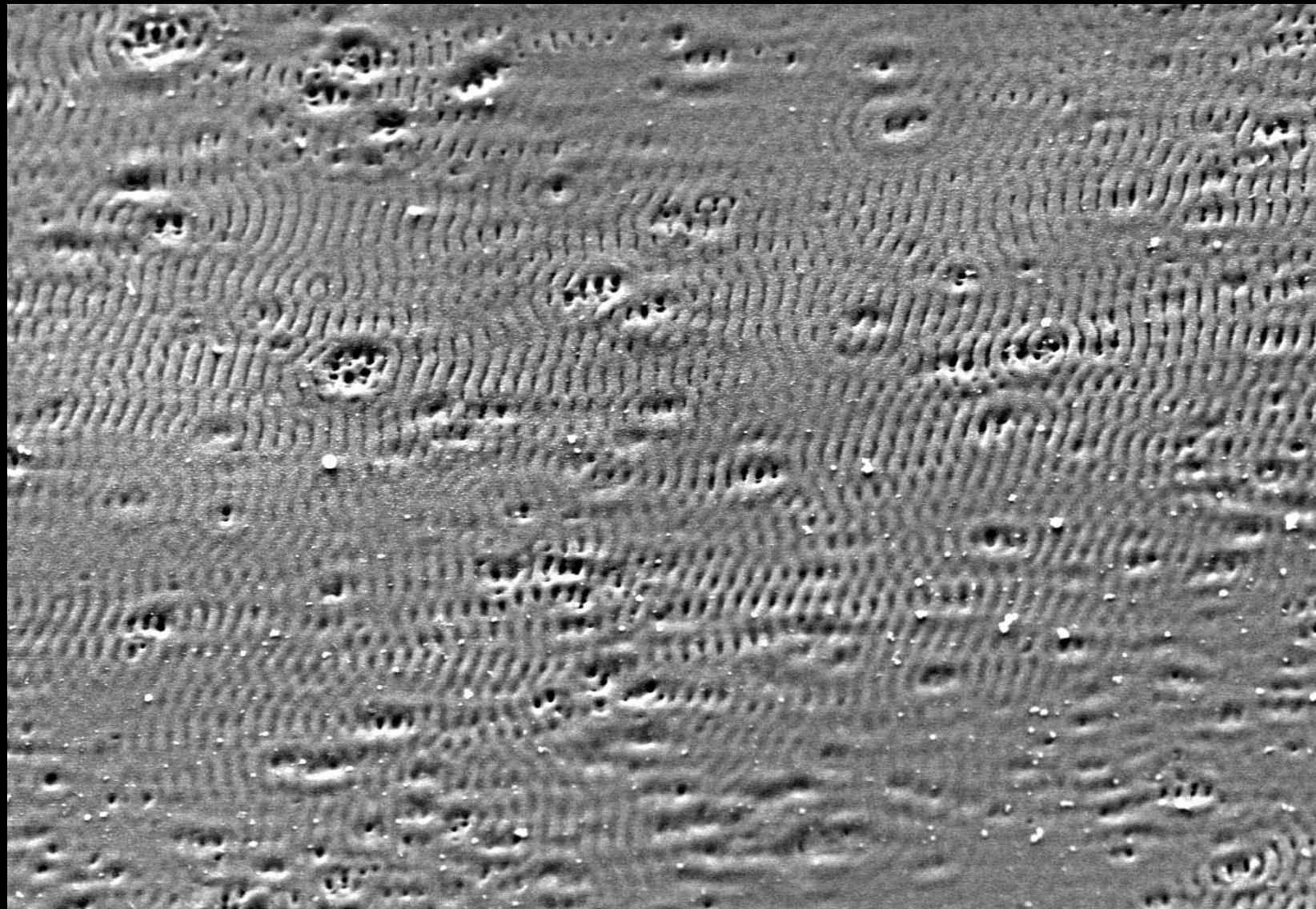
512 x 480

20 μm

10kV

15mm

0001



x2000

20 μm

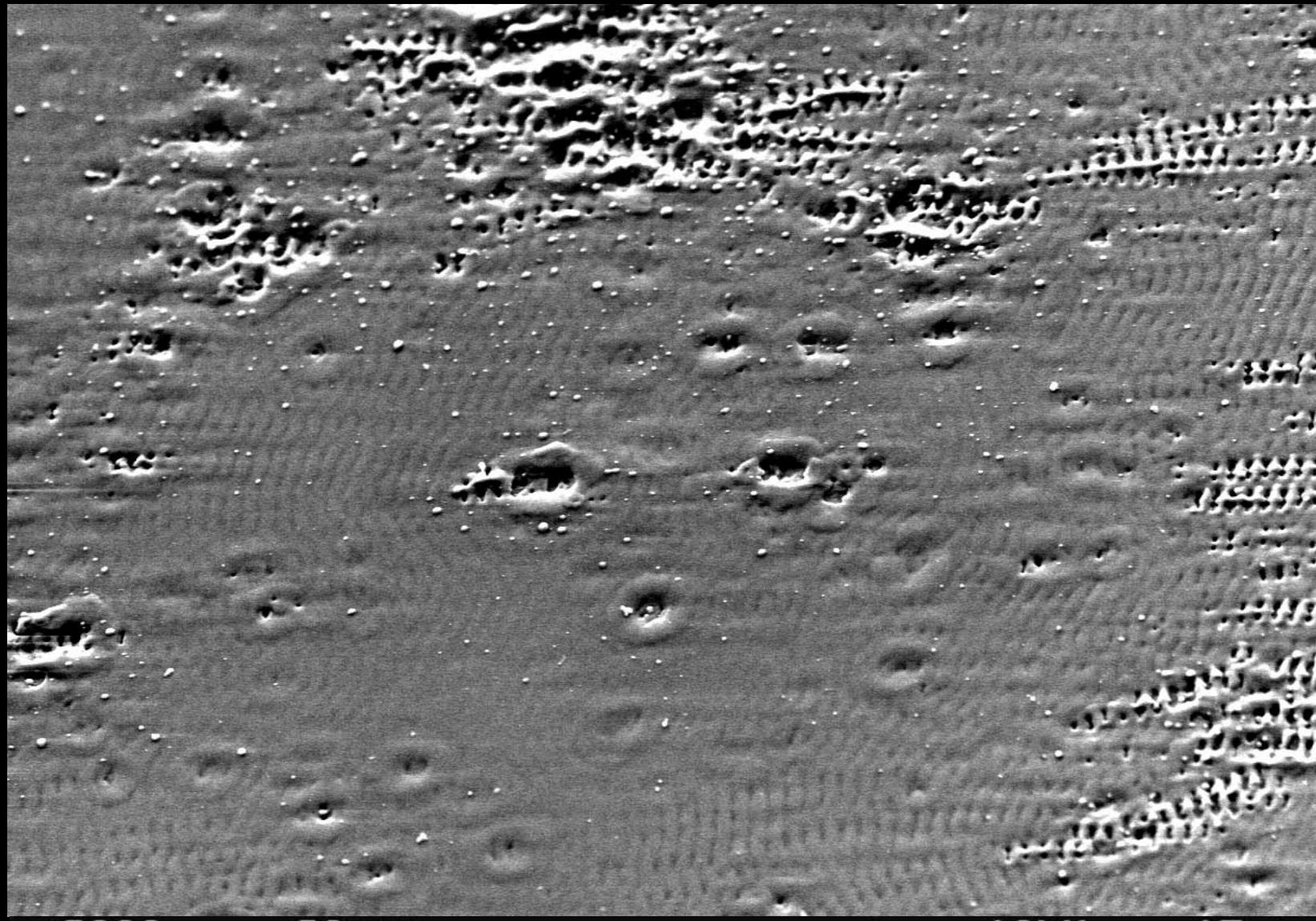
#3548

512 x 480

10kV

15mm

0002



x2000

#3548

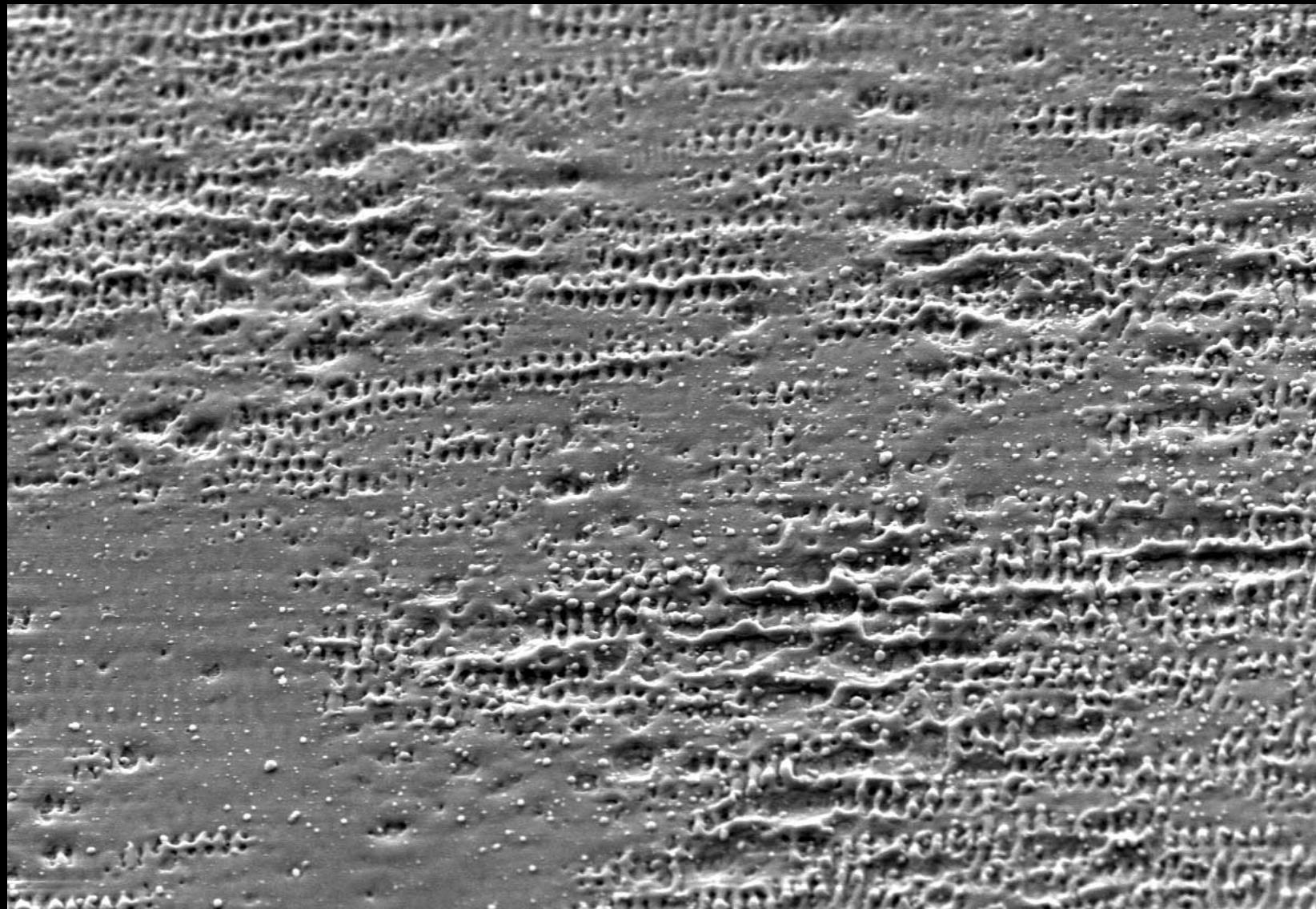
512 x 480

20 μm

10kV

15mm

0003



x2000

#3548

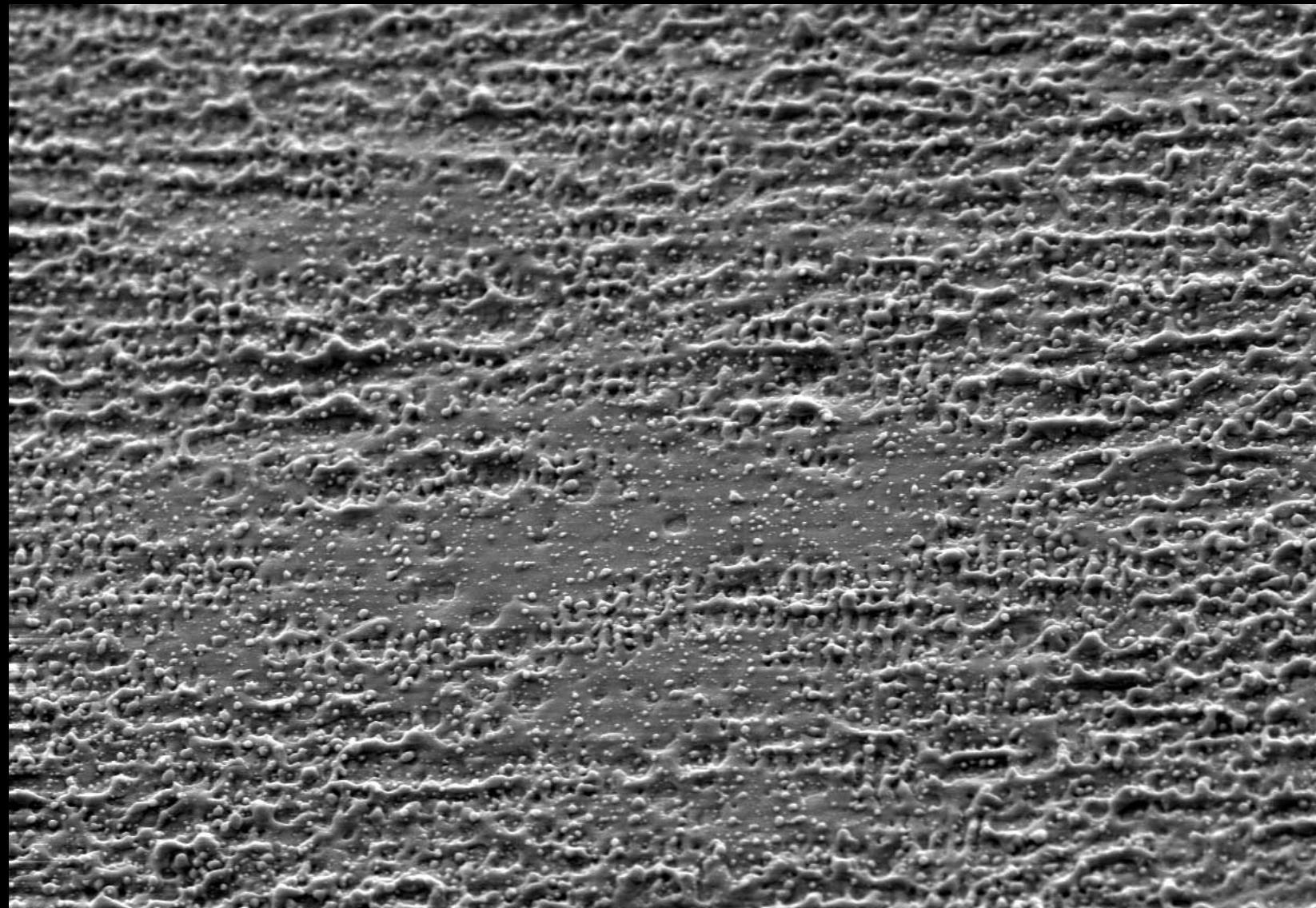
512 x 480

20 μm

10kV

15mm

0004



x2000

#3548

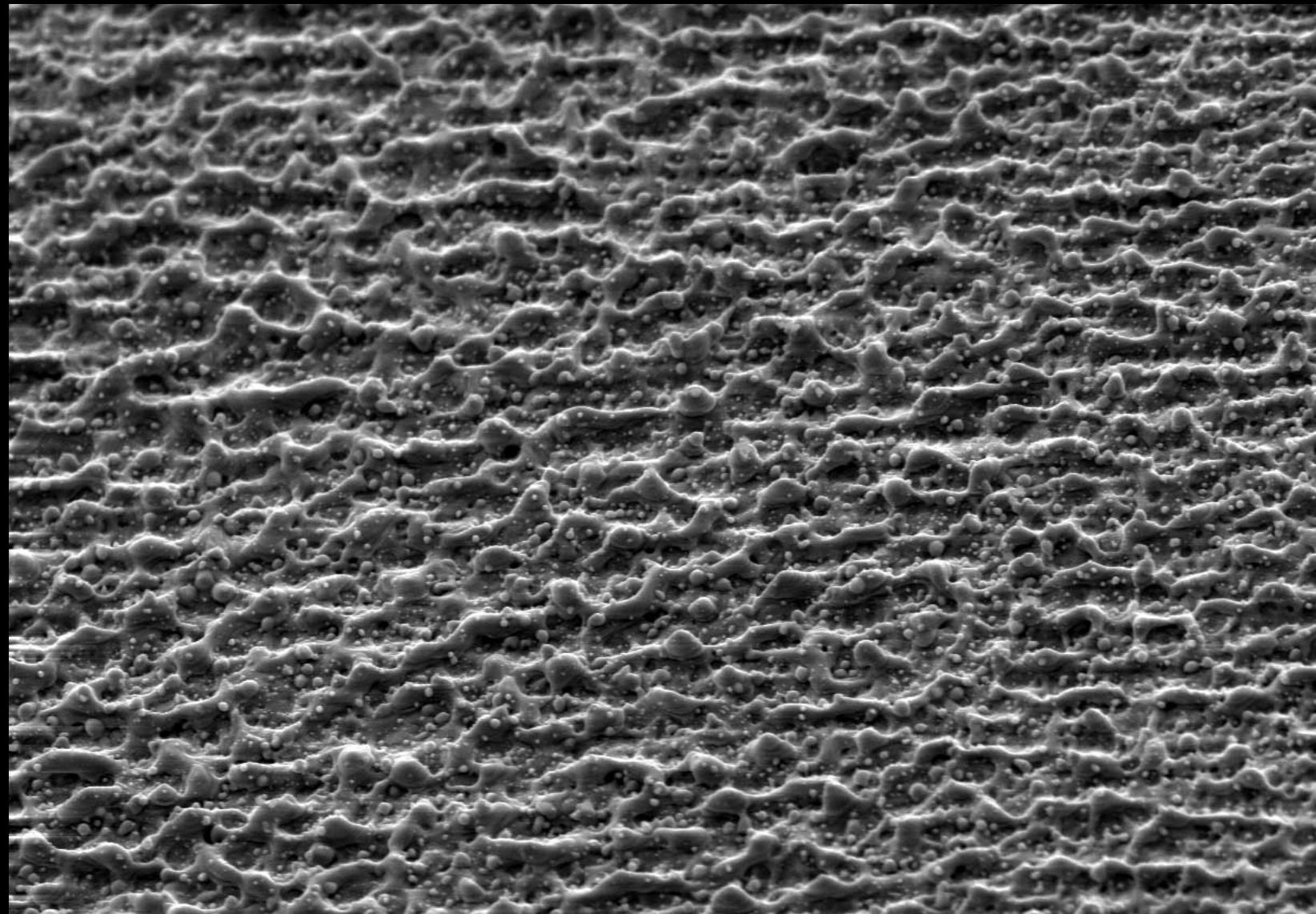
512 x 480

20 μm

10kV

15mm

0005



x2000

#3548

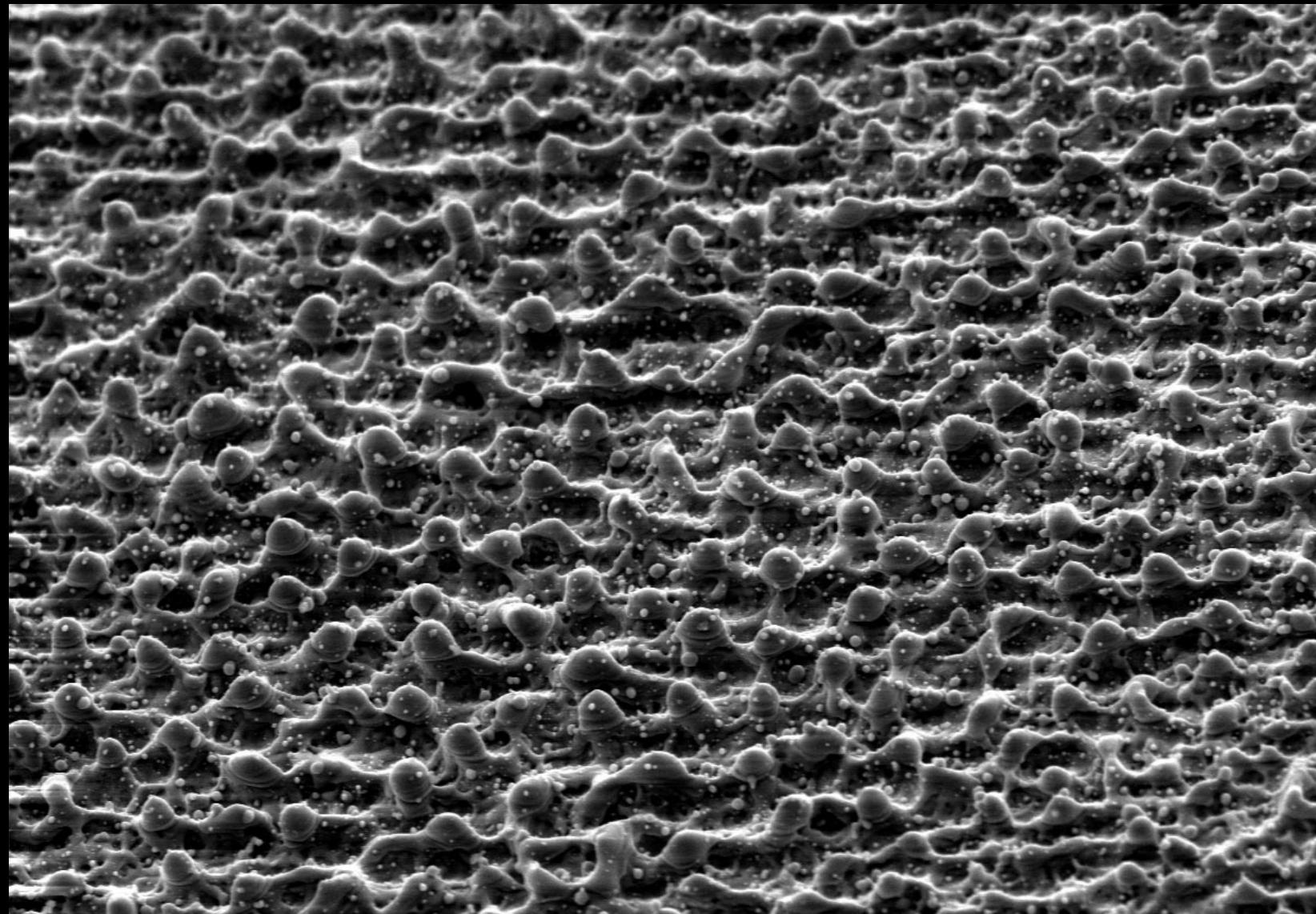
512 x 480

20 μm

10kV

15mm

0008



x2000

20 μm

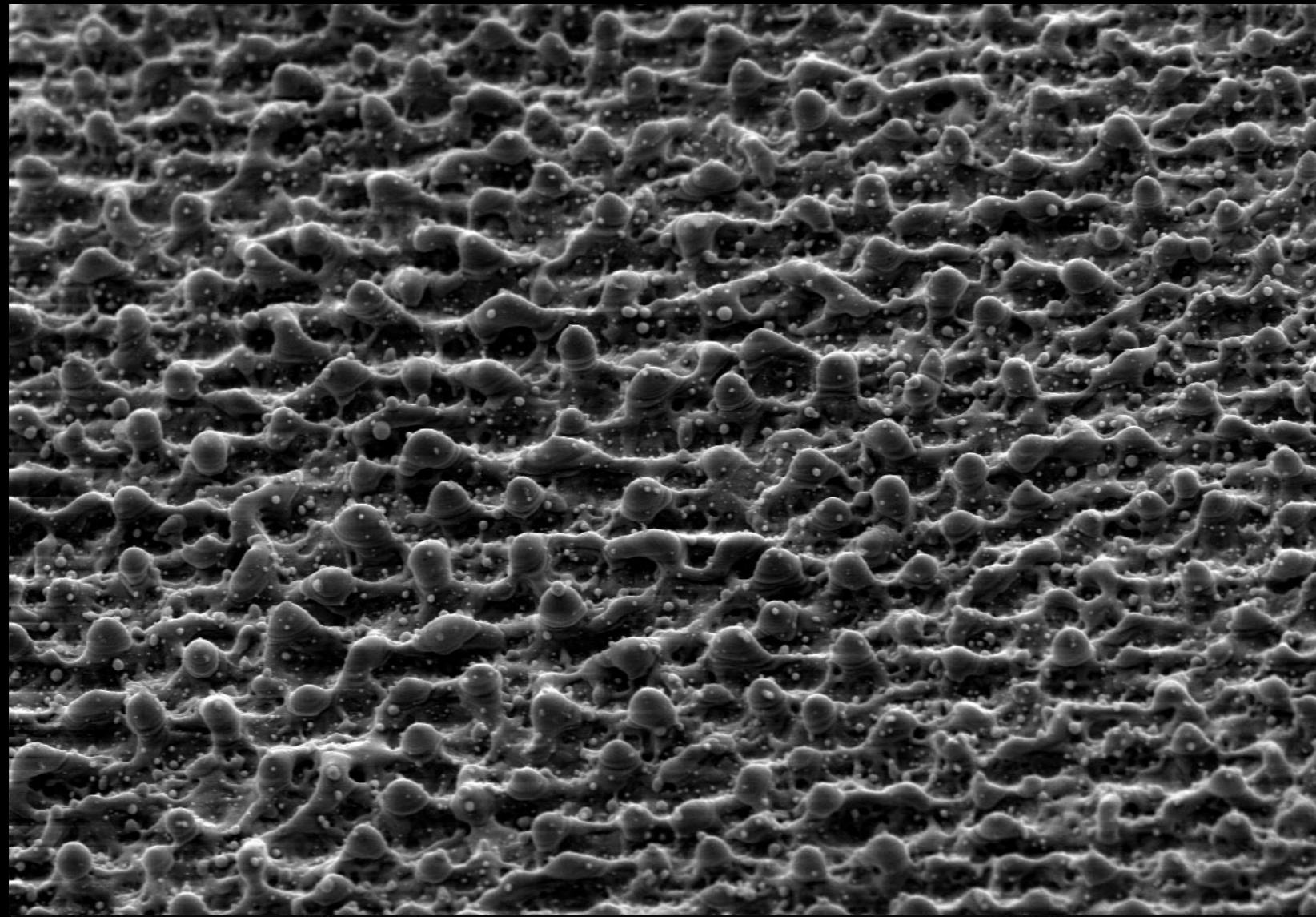
#3548

512 x 480

10kV

15mm

0010



x2000

#3548

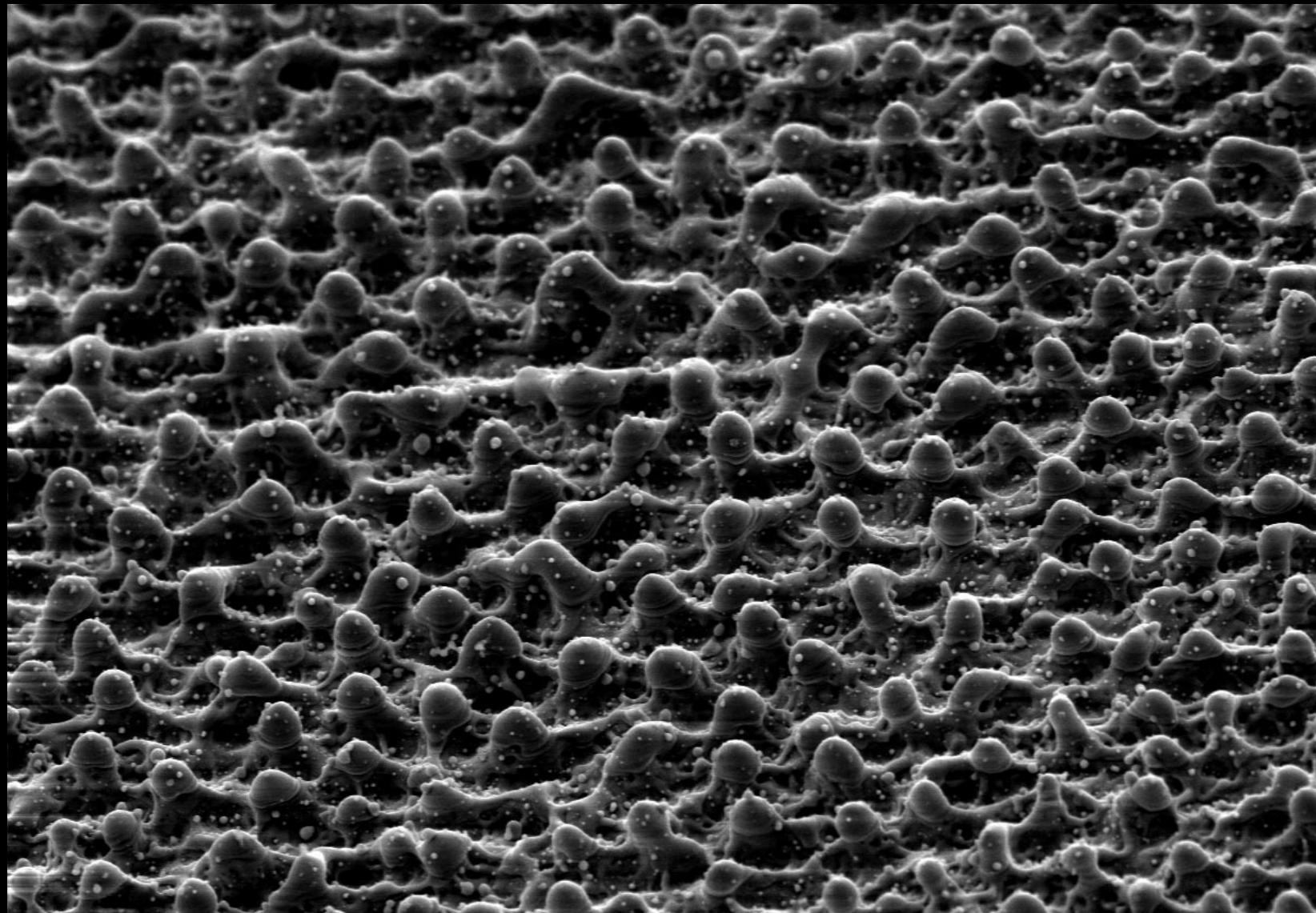
512 x 480

20 μm

10kV

15mm

0012



x2000

#3548

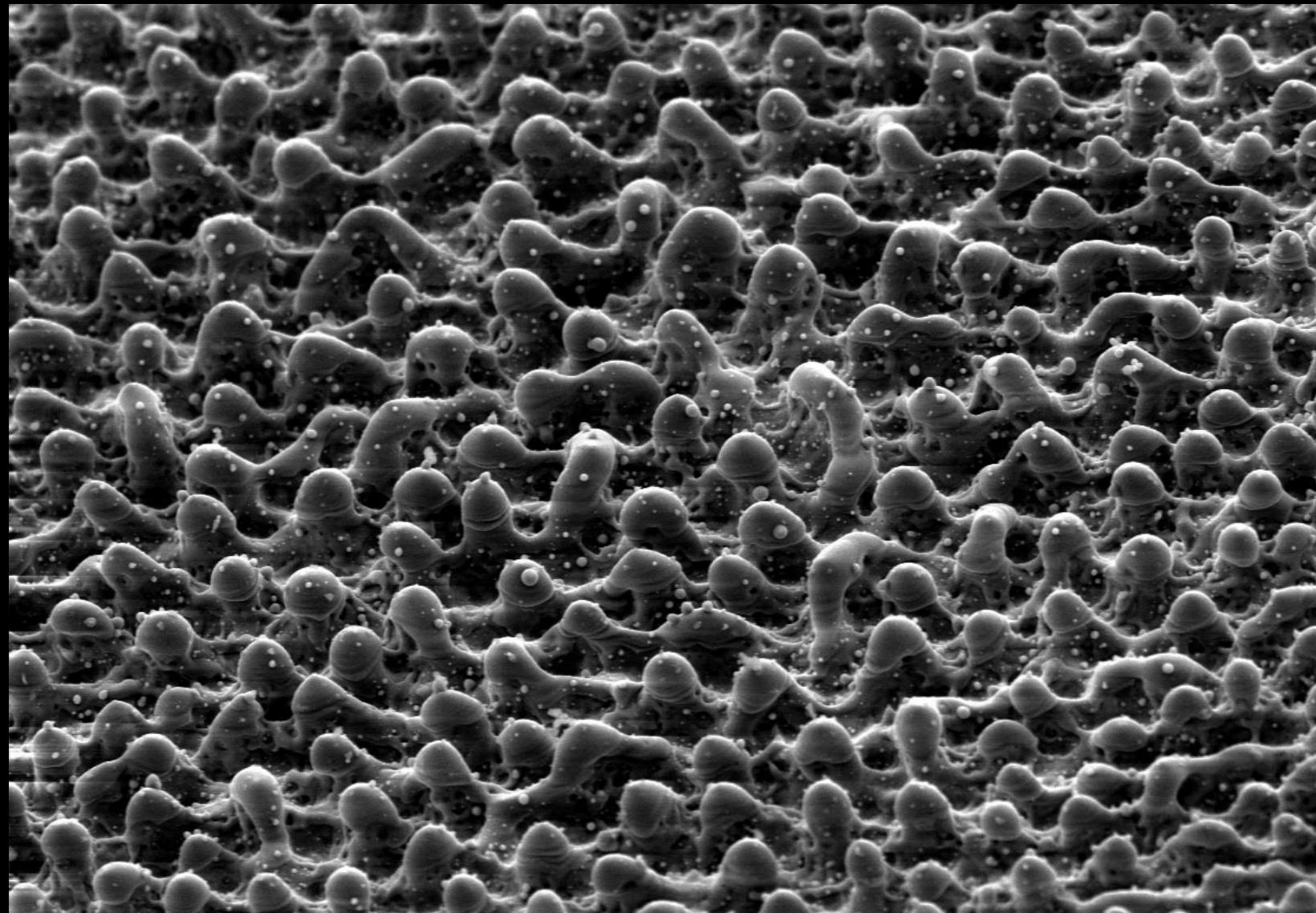
512 x 480

20 μm

10kV

15mm

0015



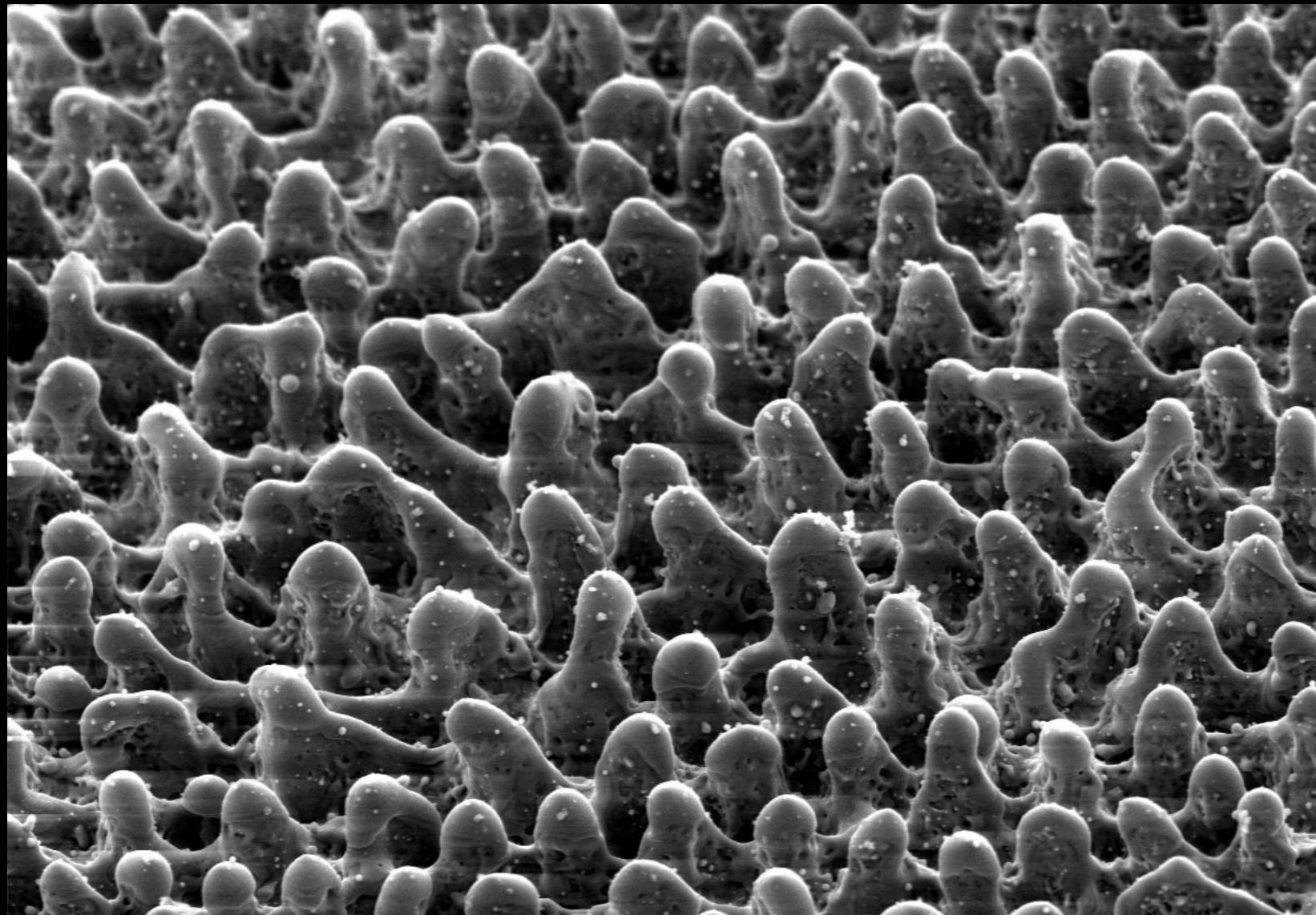
x2000
#3548
512 x 480

20 μ m

10kV

15mm

0020



x2000

#3548

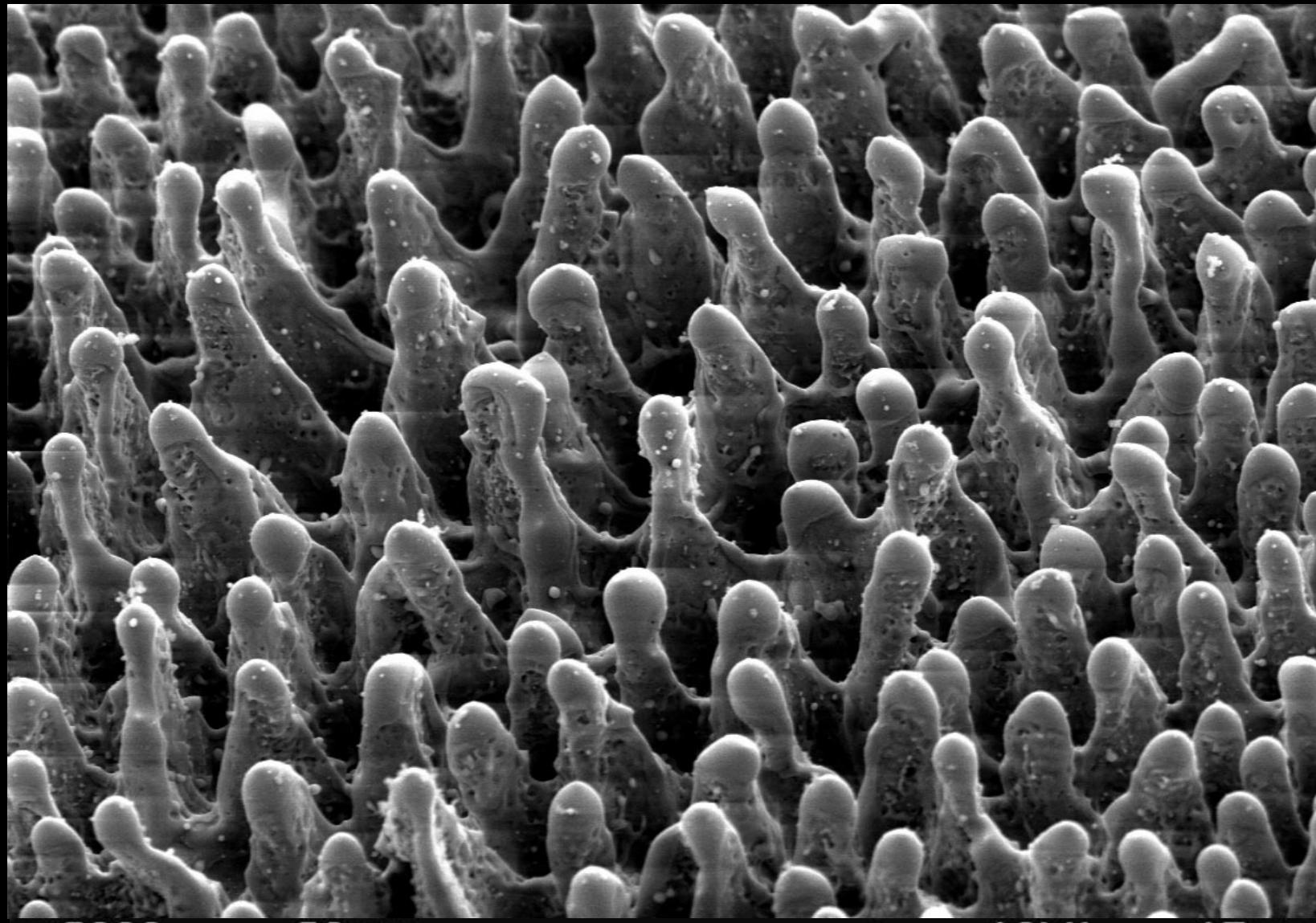
512 x 480

20 μm

10kV

15mm

0030



x2000

#3548

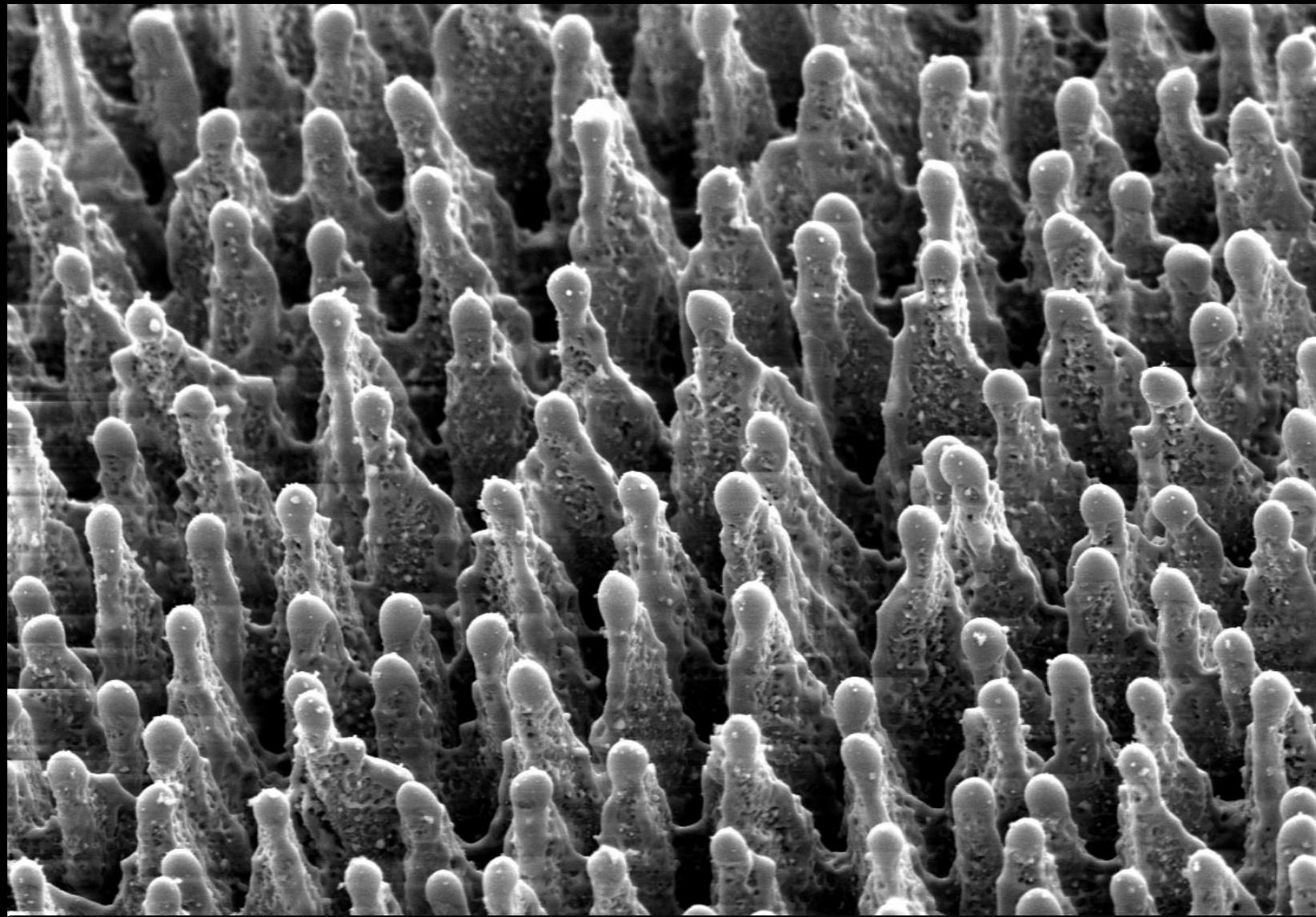
512 x 480

20 μ m

10kV

15mm

0050



x2000

20 μ m

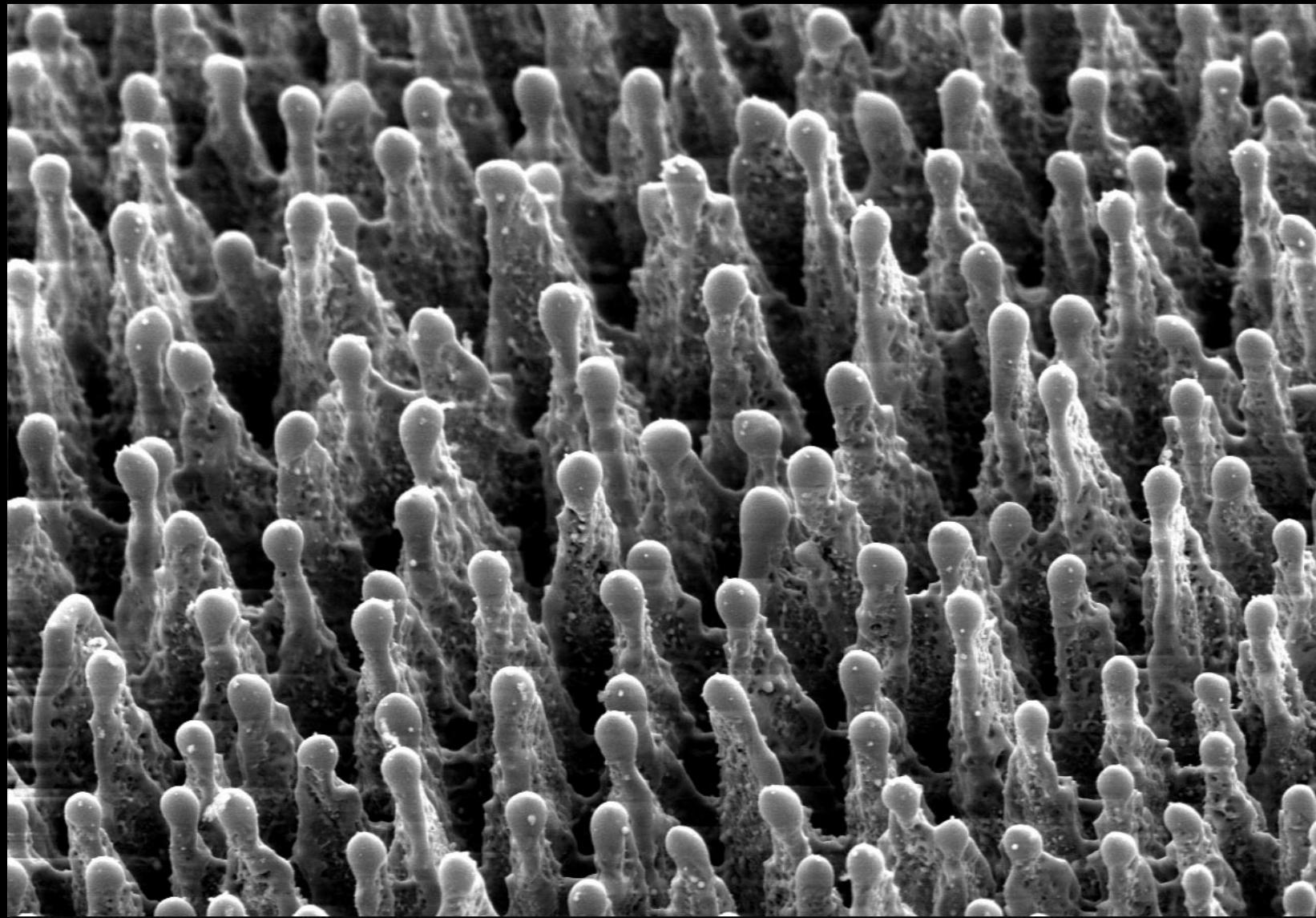
#3548

512 x 480

10kV

15mm

0070



x2000

20 μm

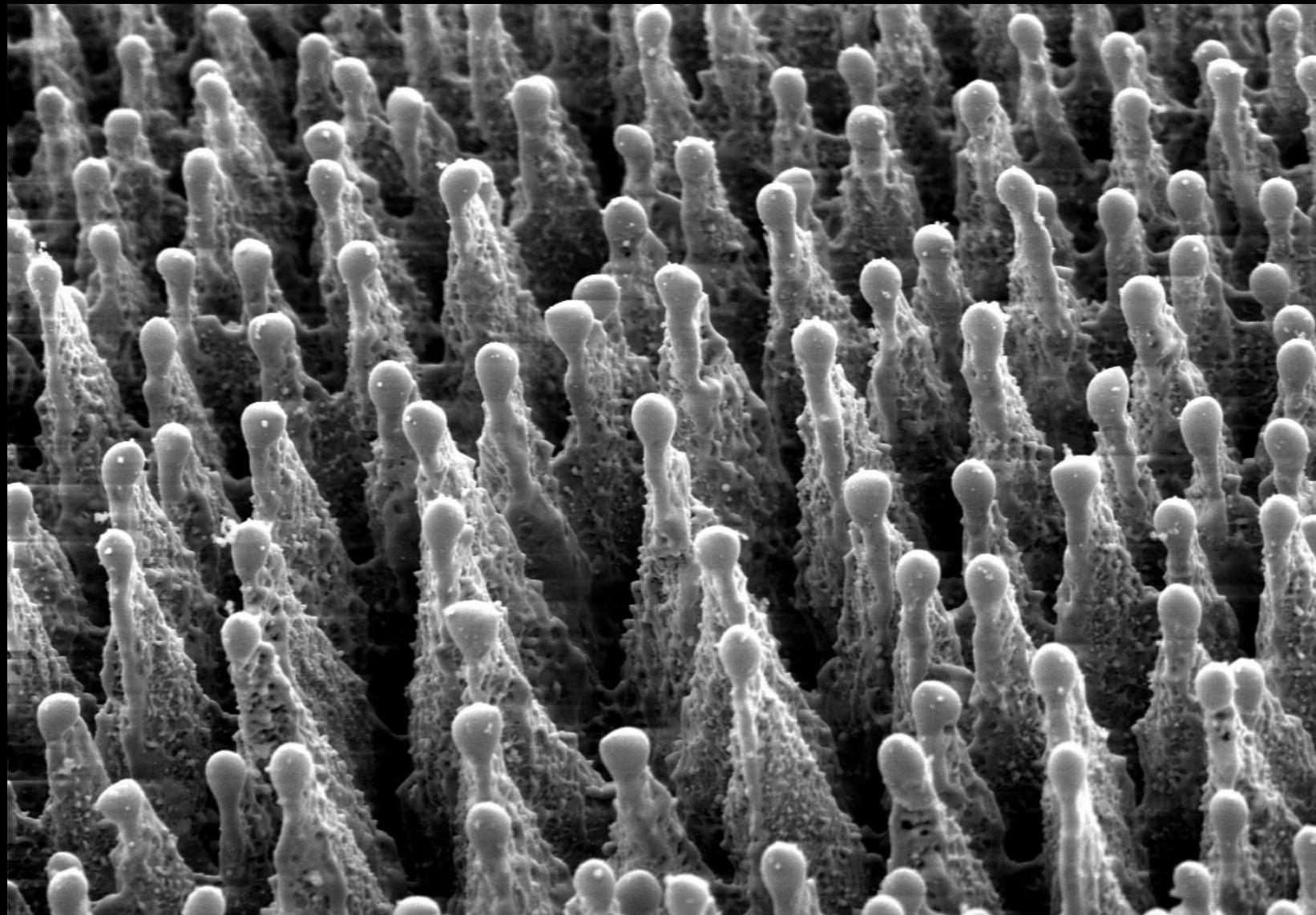
#3548

512 x 480

10kV

15mm

0100



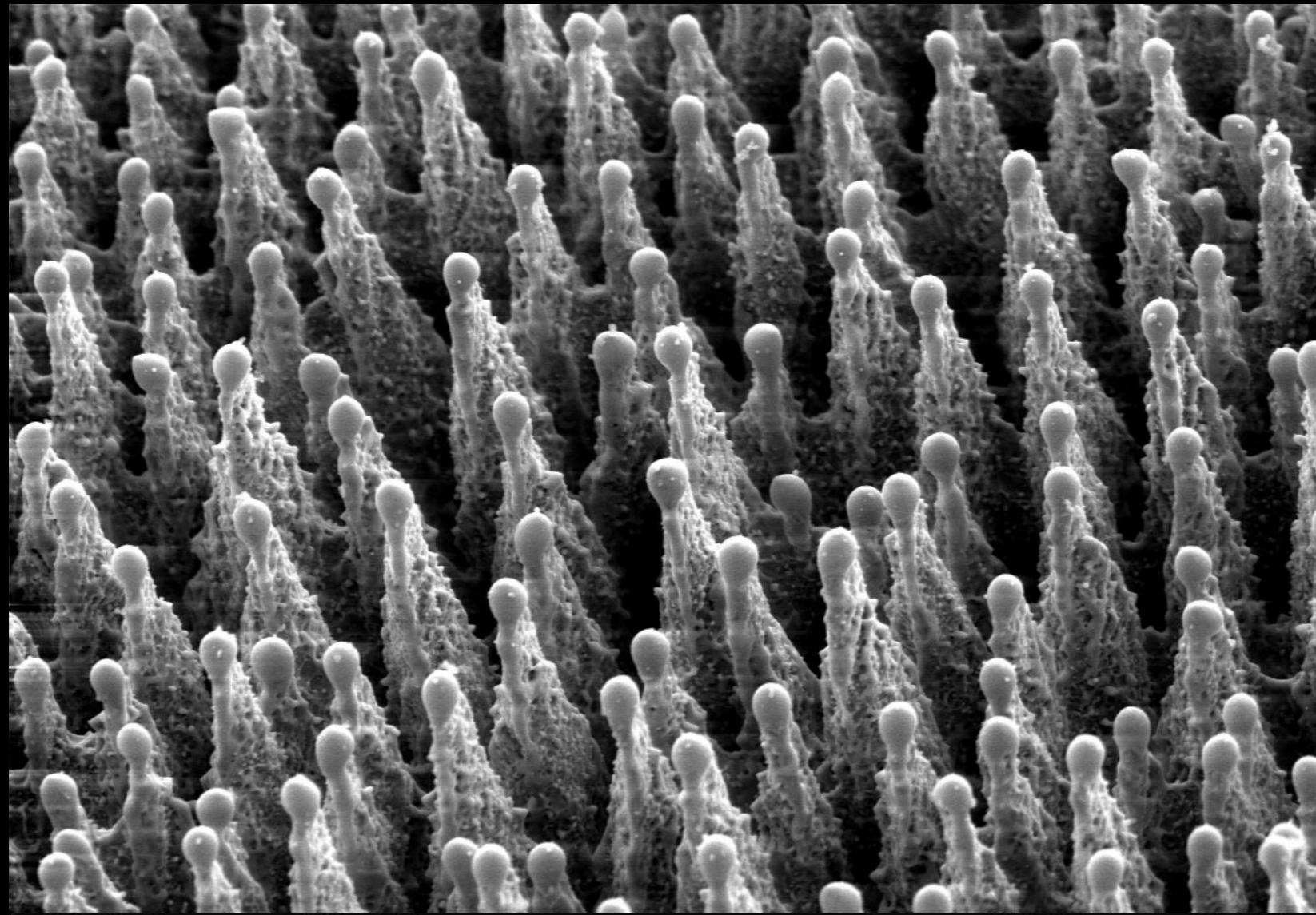
x2000
#3548
512 x 480

20 μ m

10kV

15mm

0200



x2000

20 μm

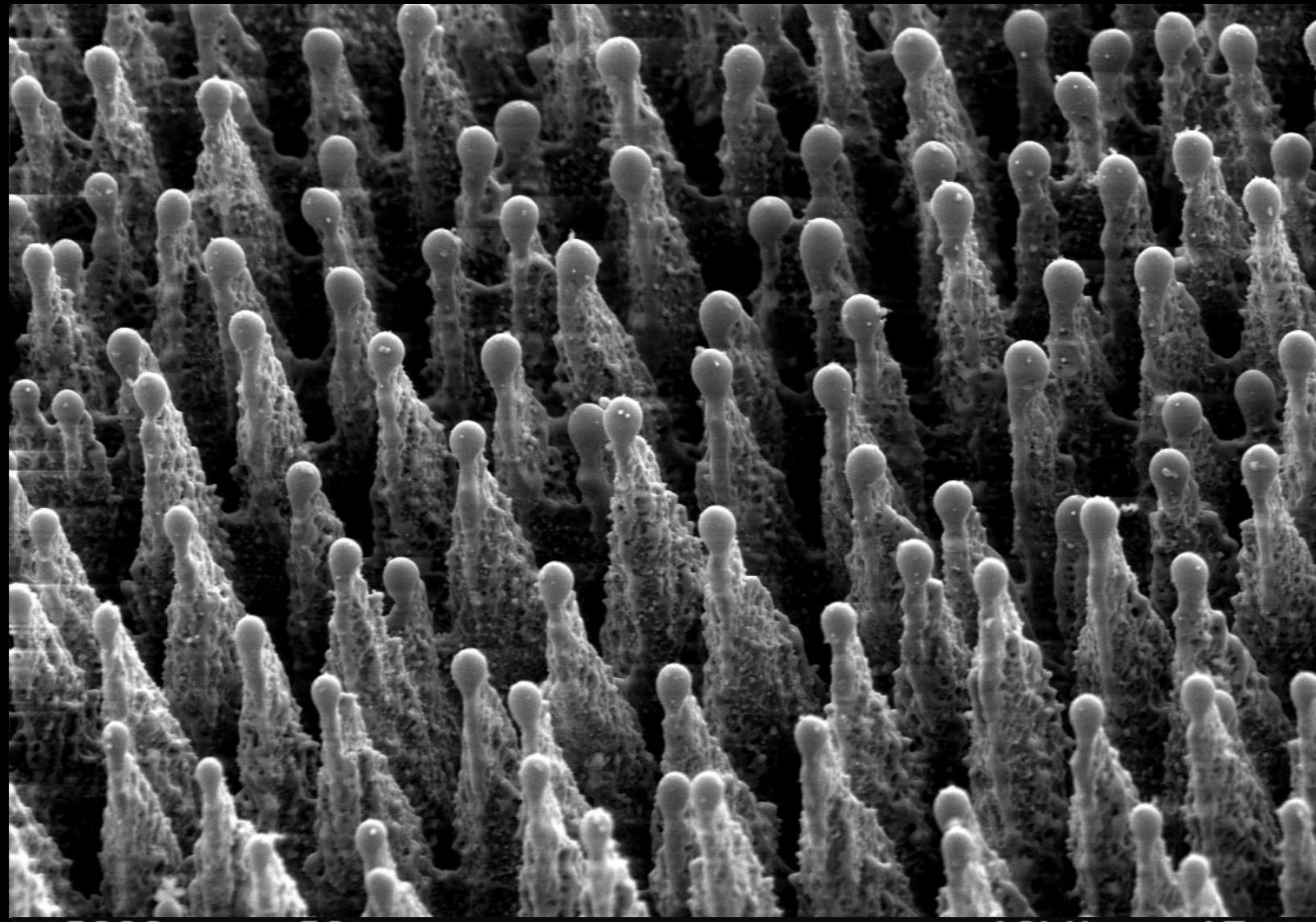
#3548

512 x 480

10kV

15mm

0400



x2000

#3548

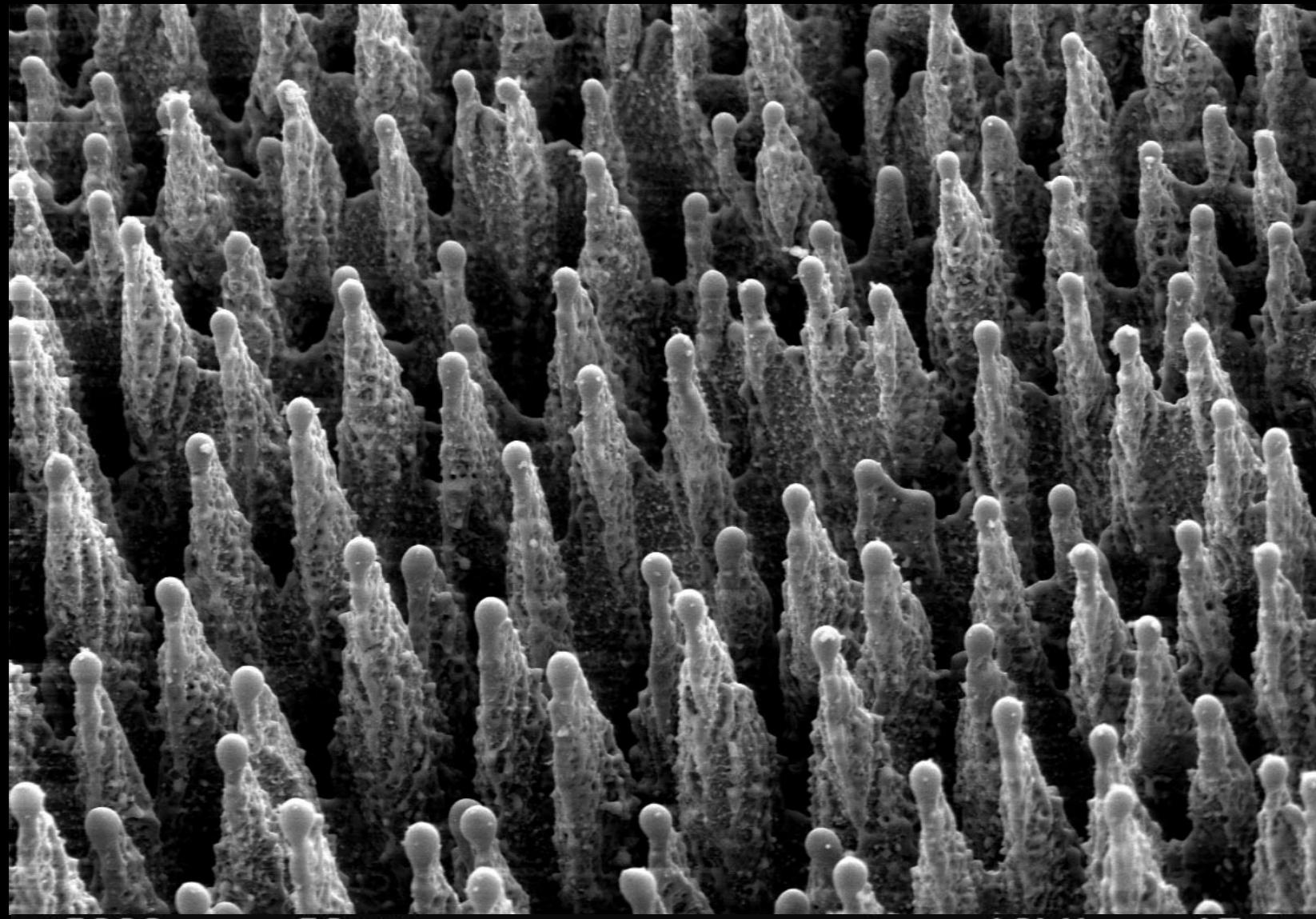
512 x 480

20 μm

10kV

15mm

0600



x2000

20 μm

#3548

512 x 480

10kV

15mm

1000

Formation process

How do ripples give way to spikes?

Follow evolution of spatial frequencies

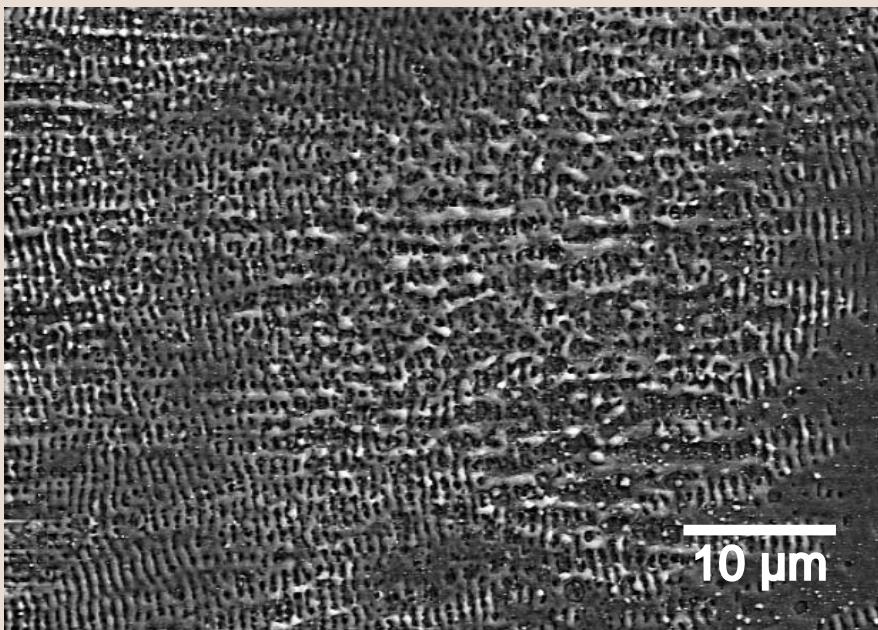
- ▶ vary number of laser pulses
- ▶ calculate Fourier transform of images

Formation process

ripples

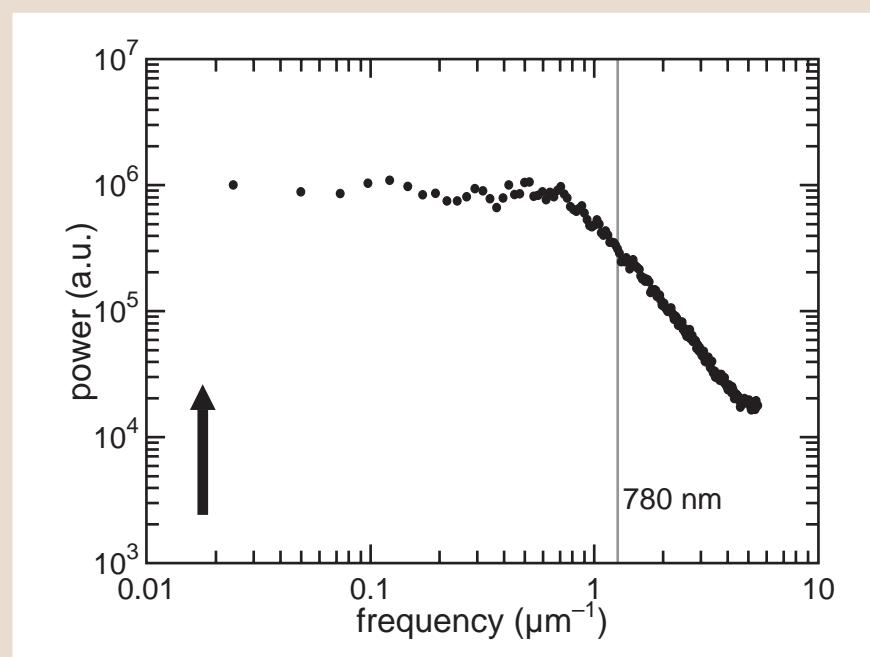
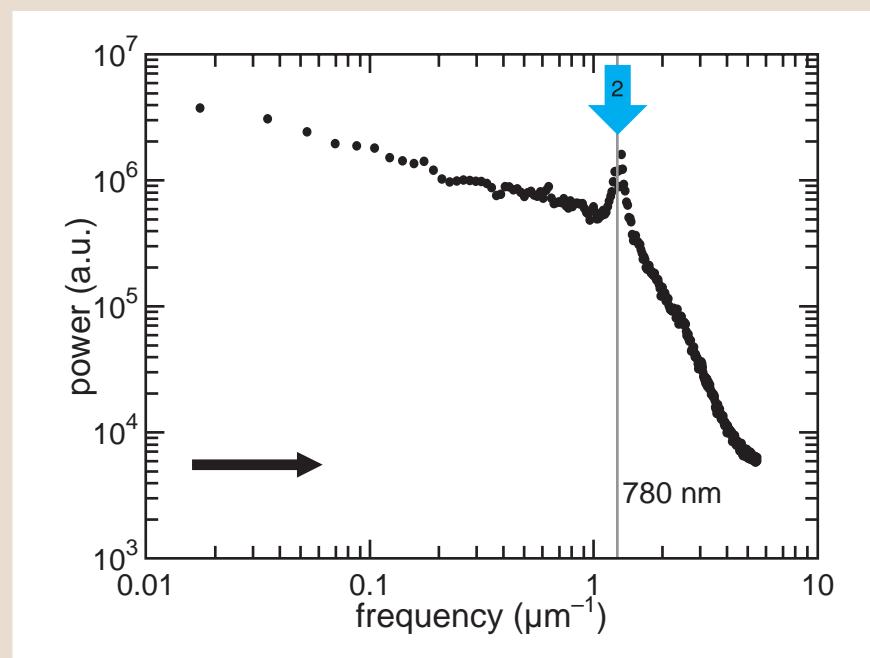
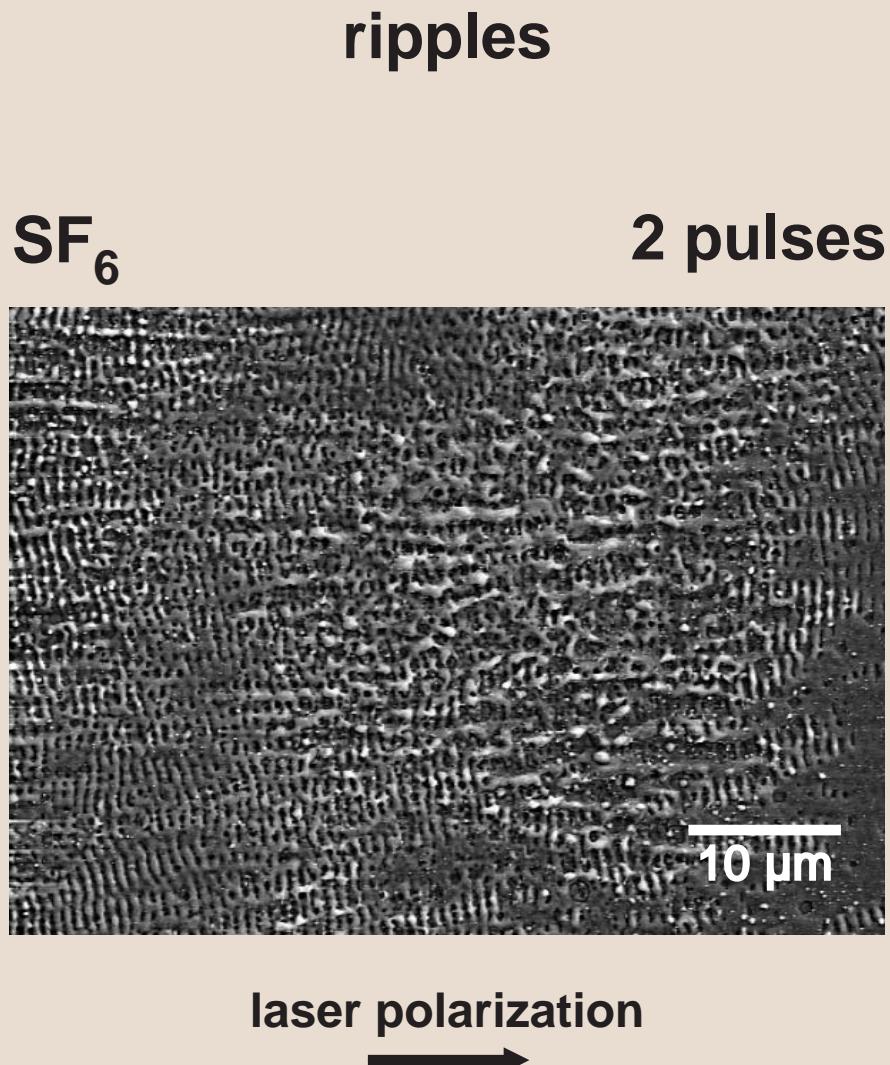
SF₆

2 pulses

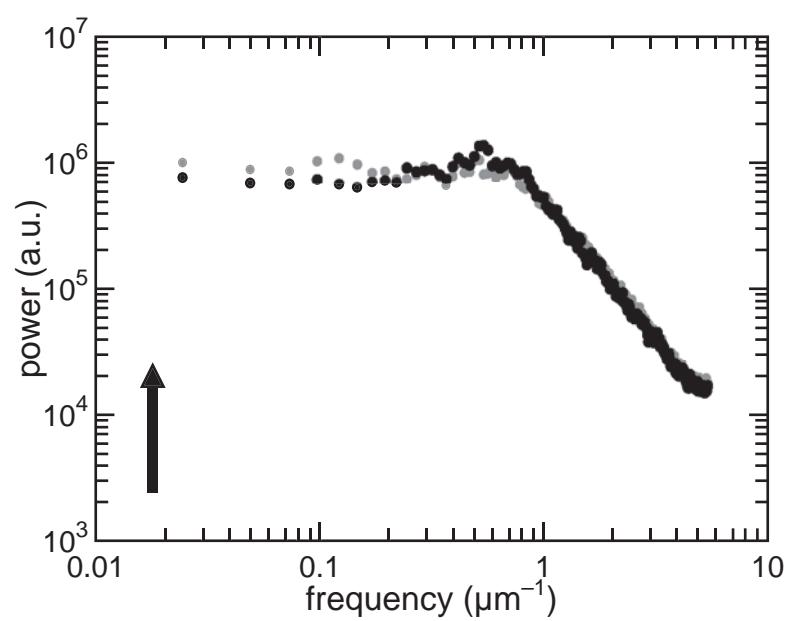
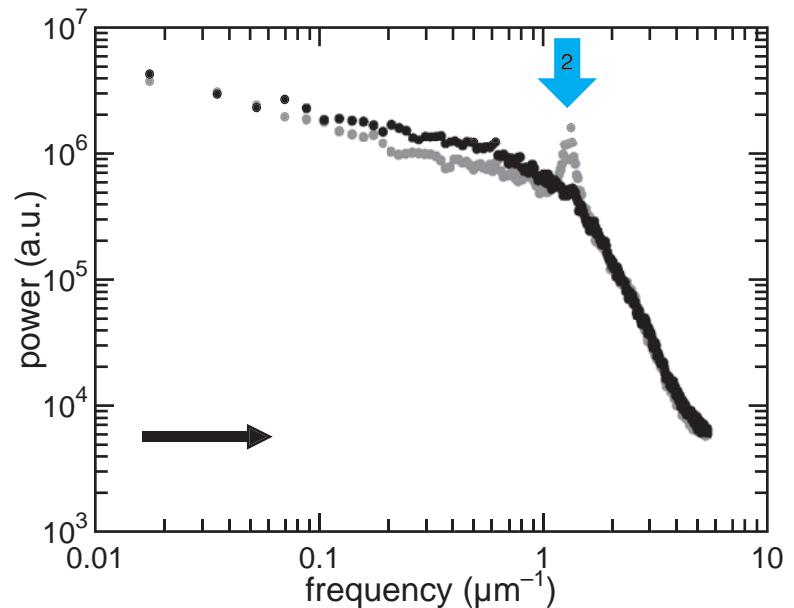
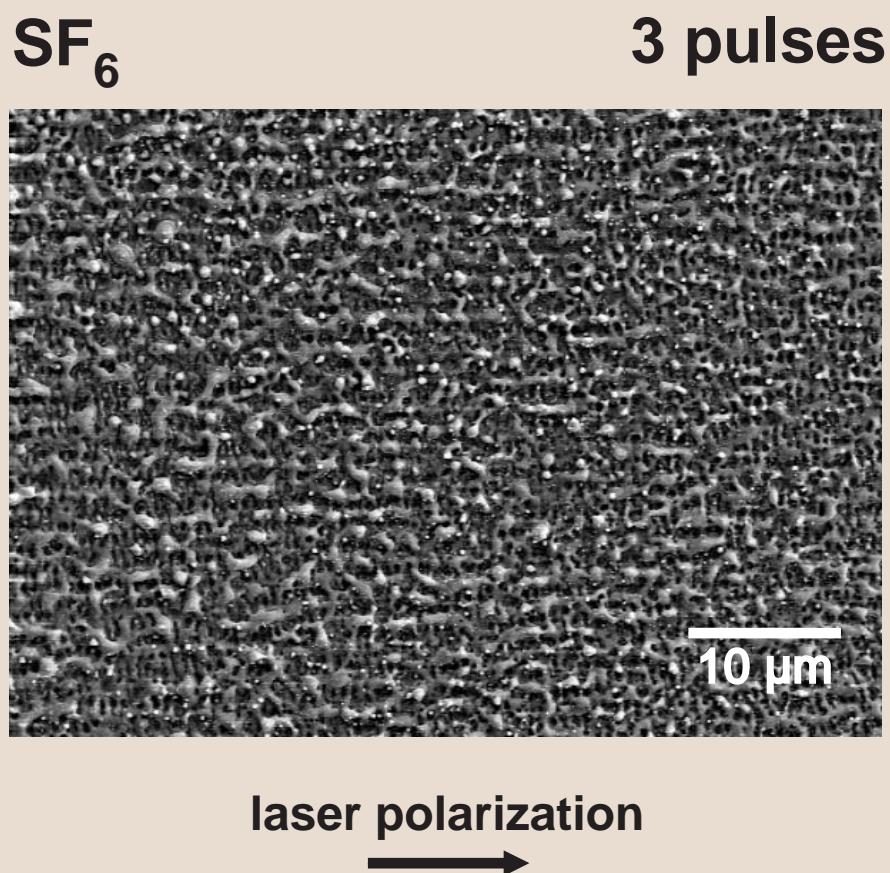


laser polarization
→

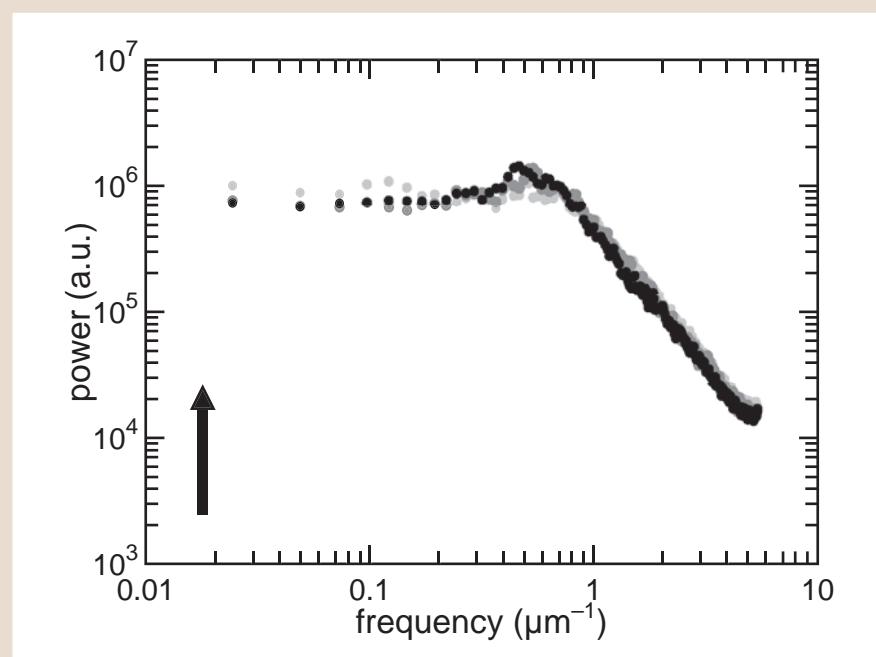
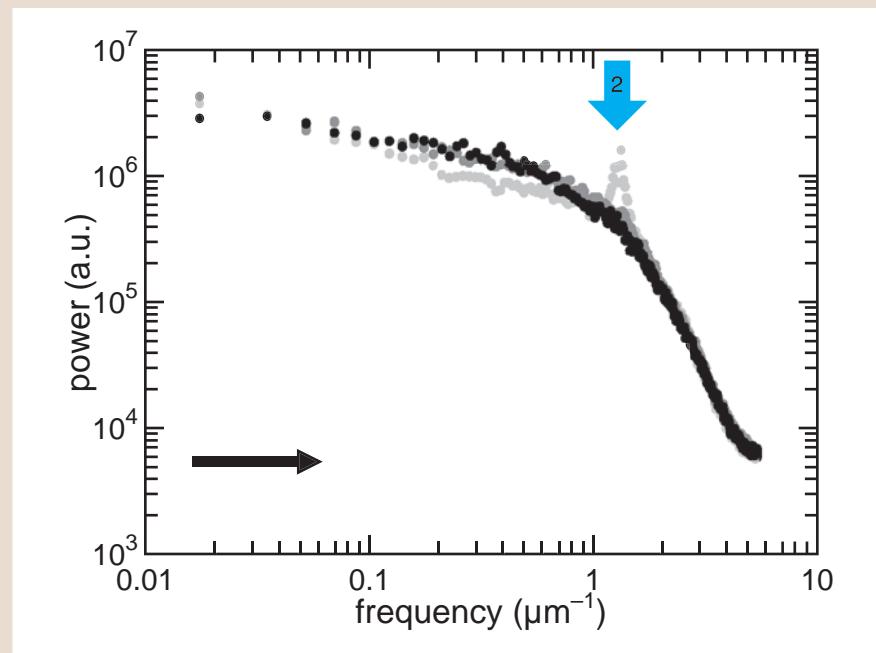
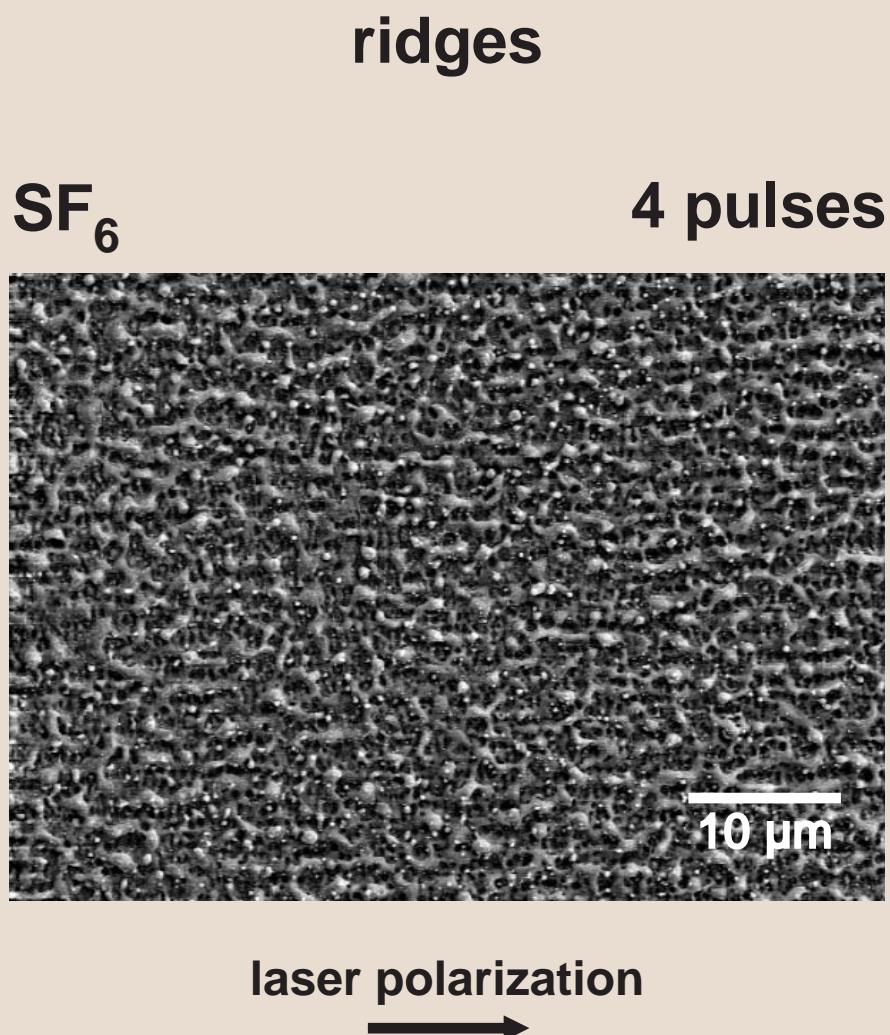
Formation process



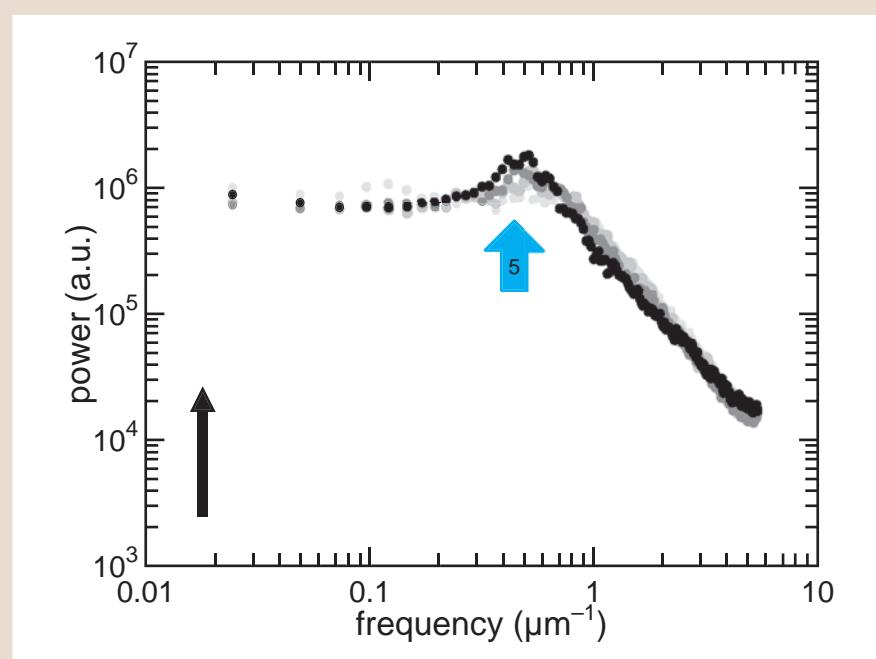
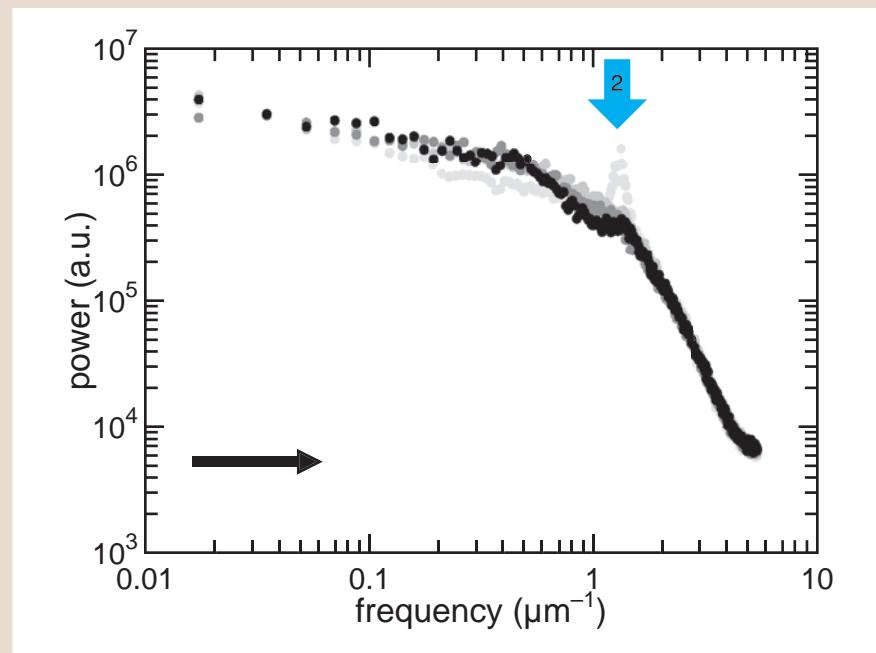
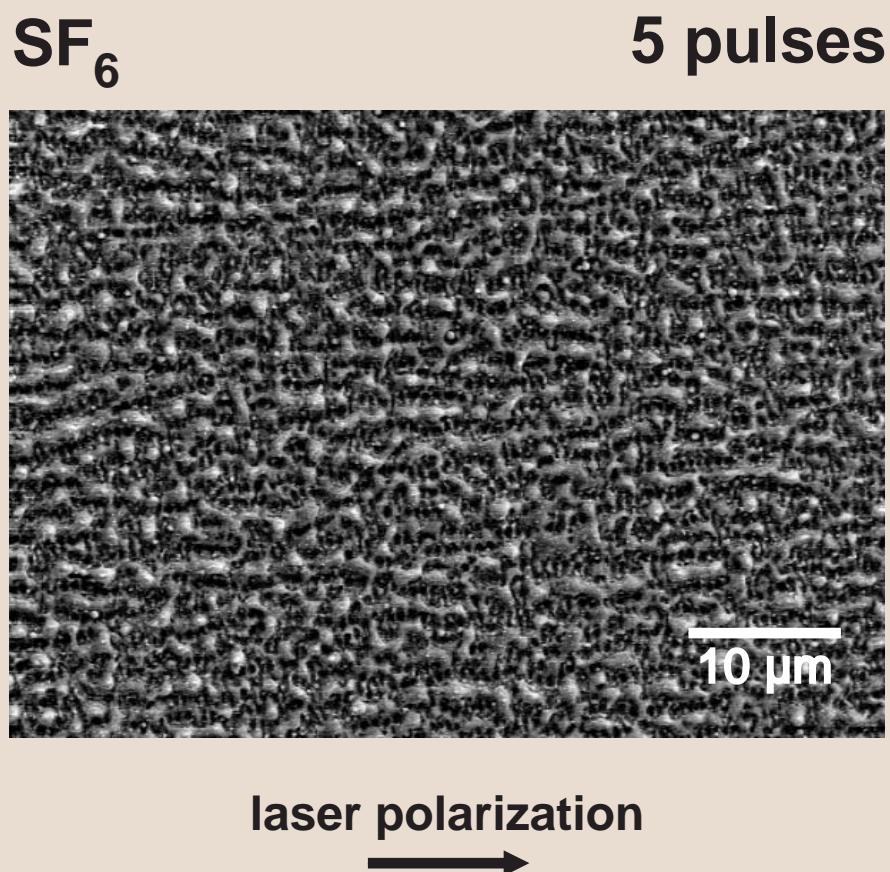
Formation process



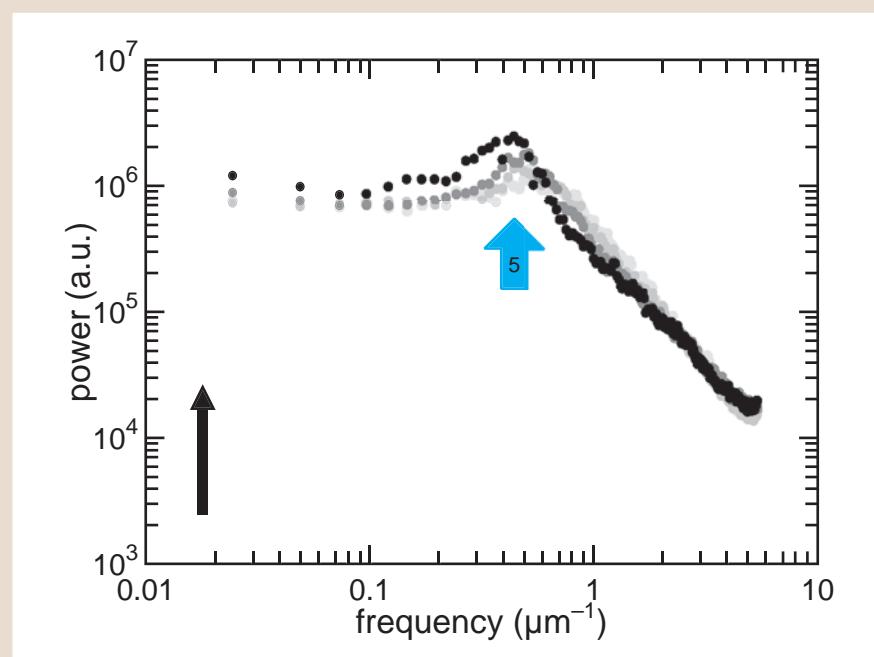
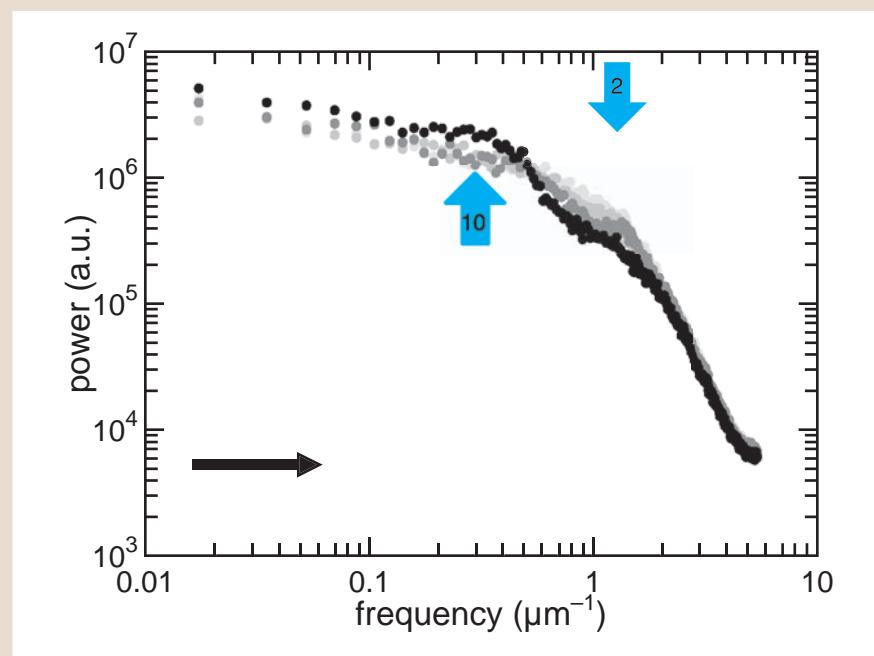
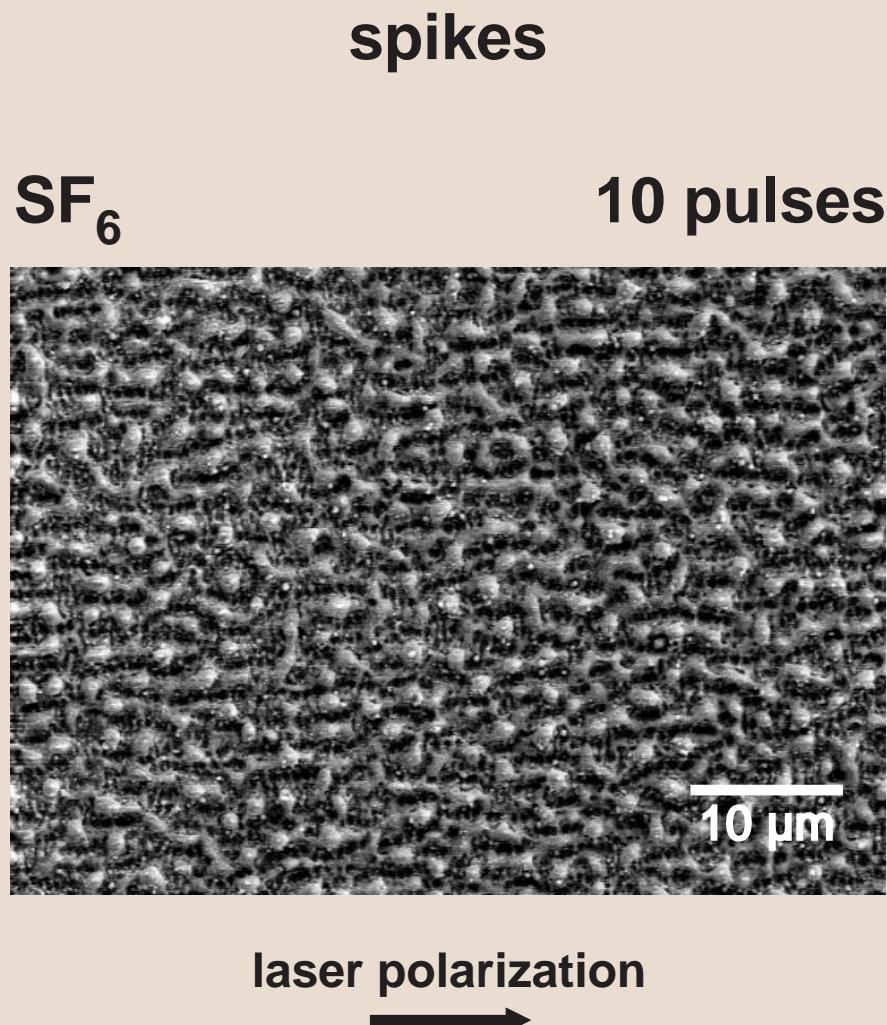
Formation process



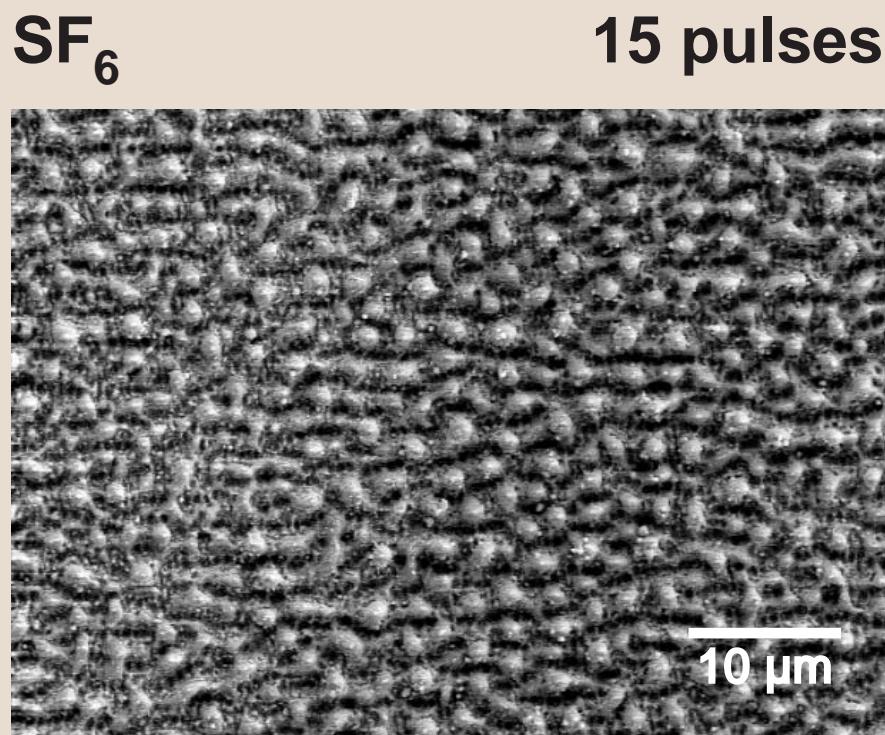
Formation process



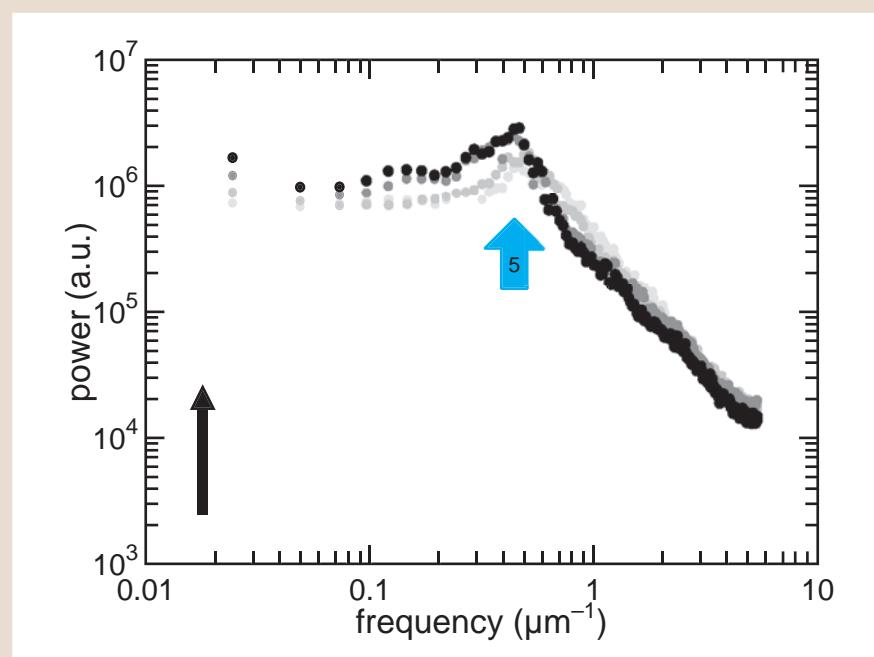
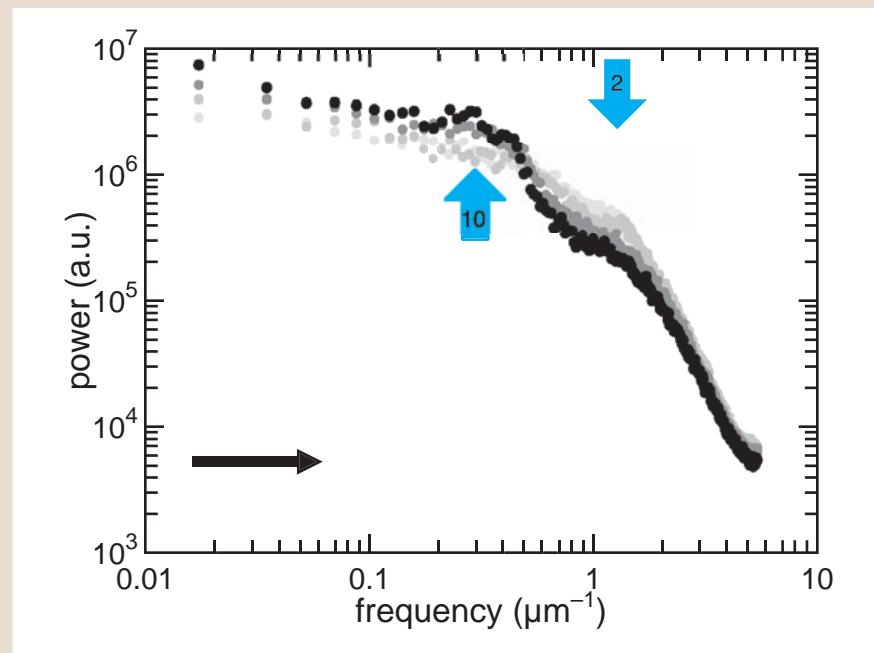
Formation process



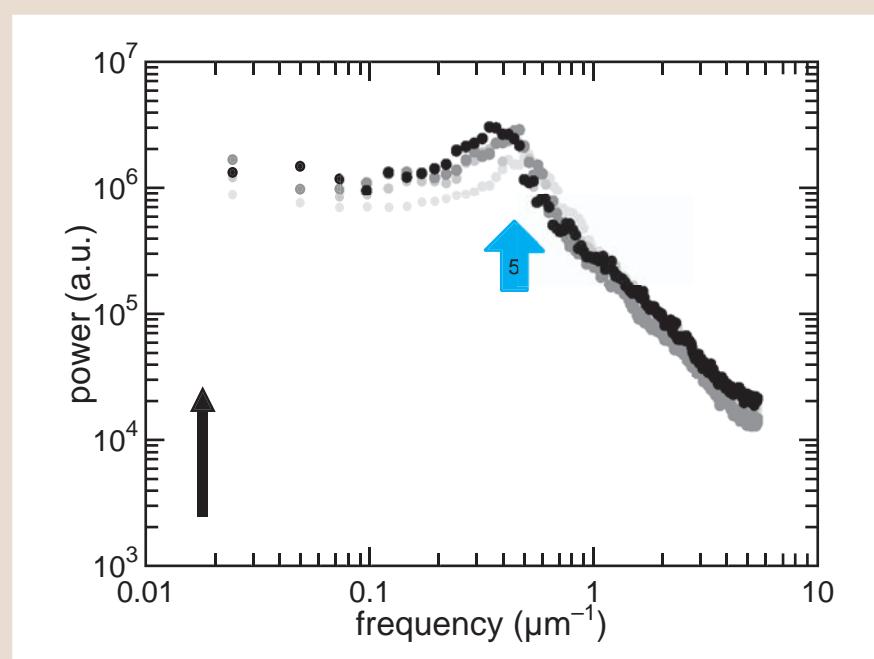
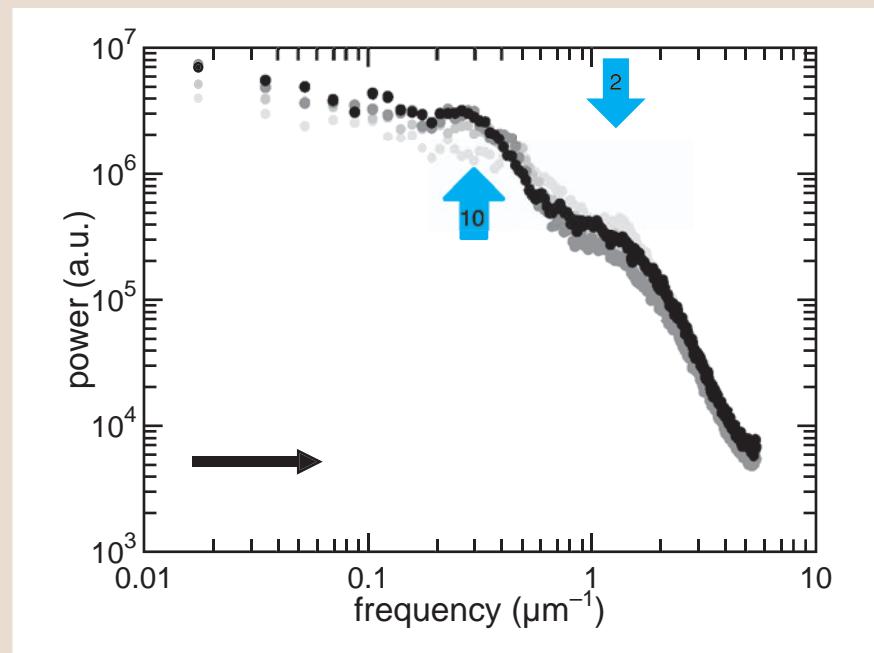
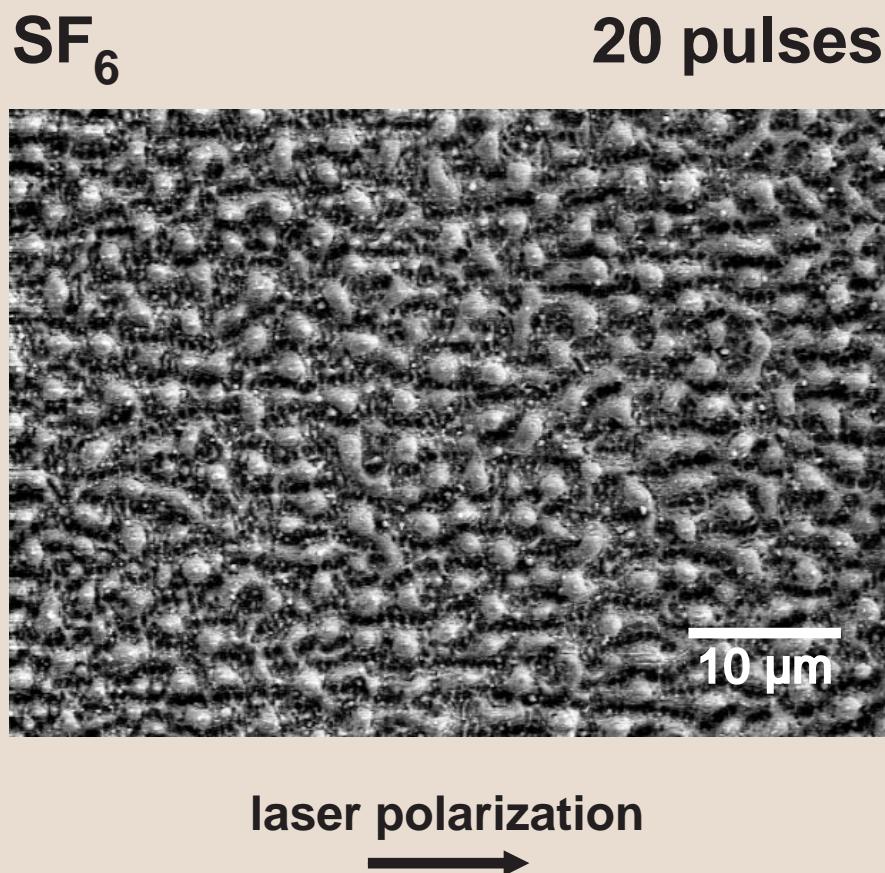
Formation process



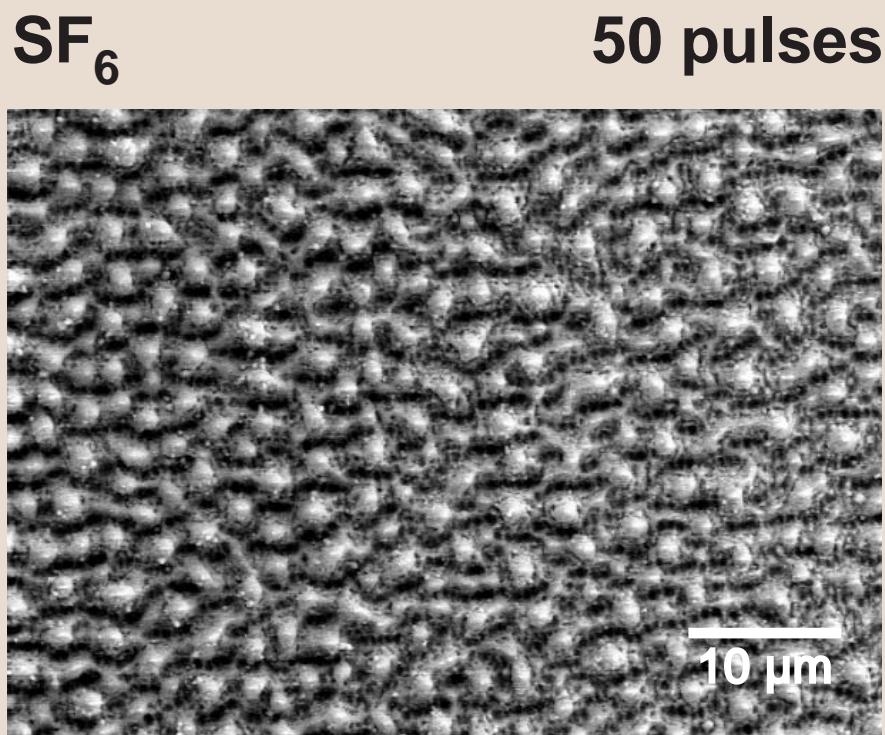
laser polarization
→



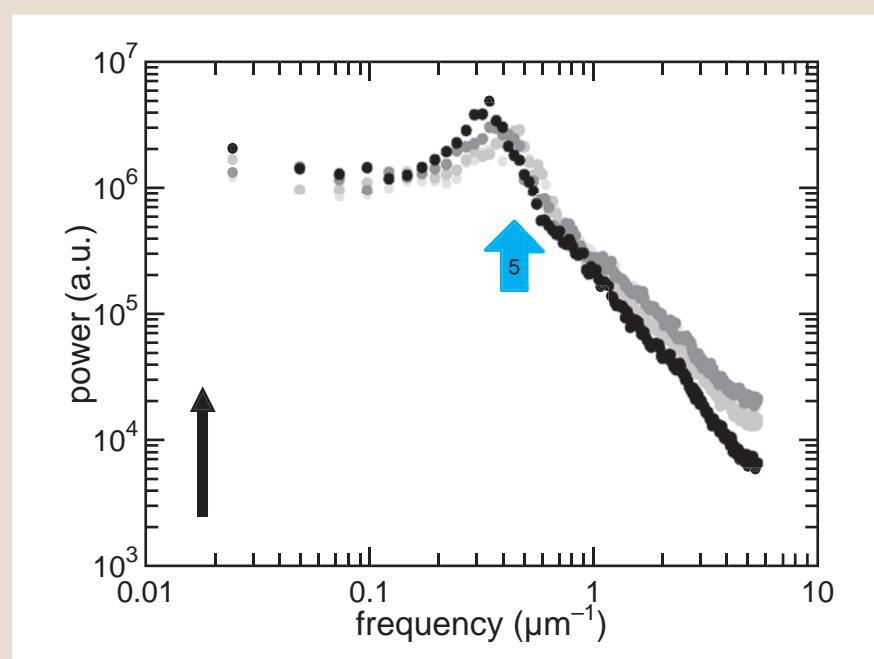
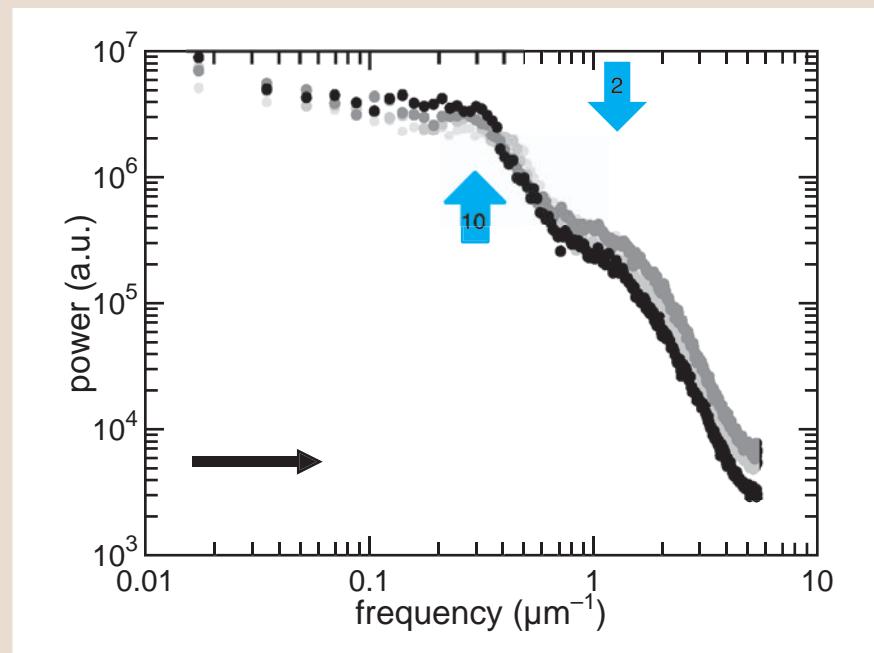
Formation process



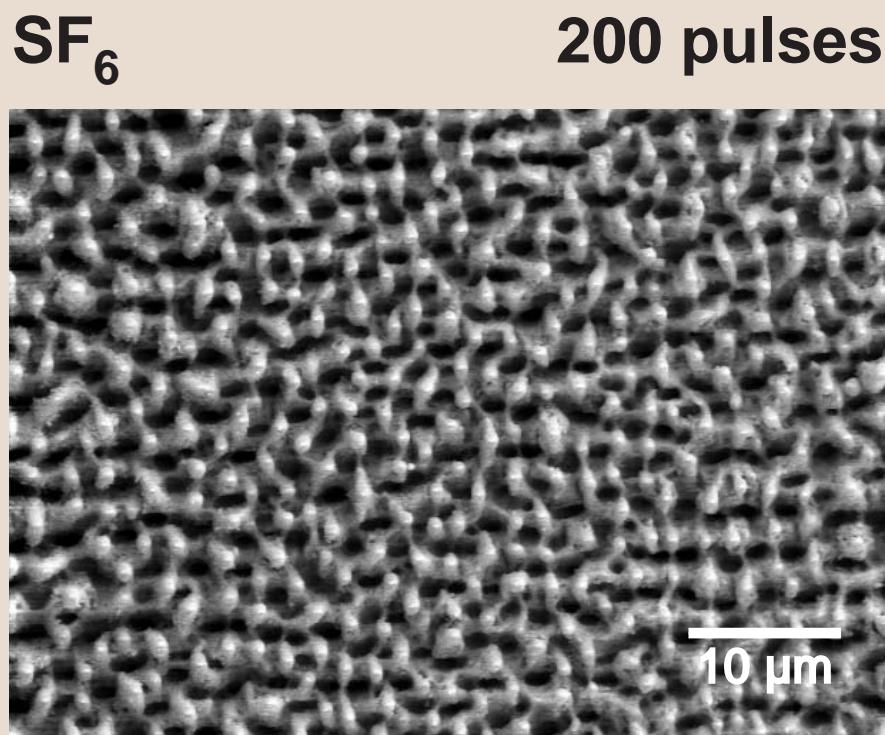
Formation process



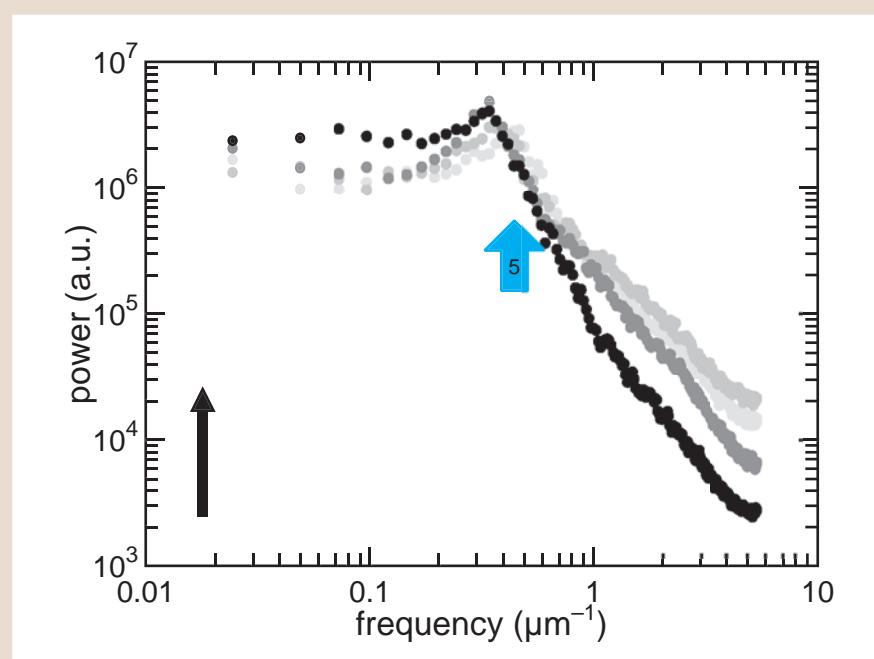
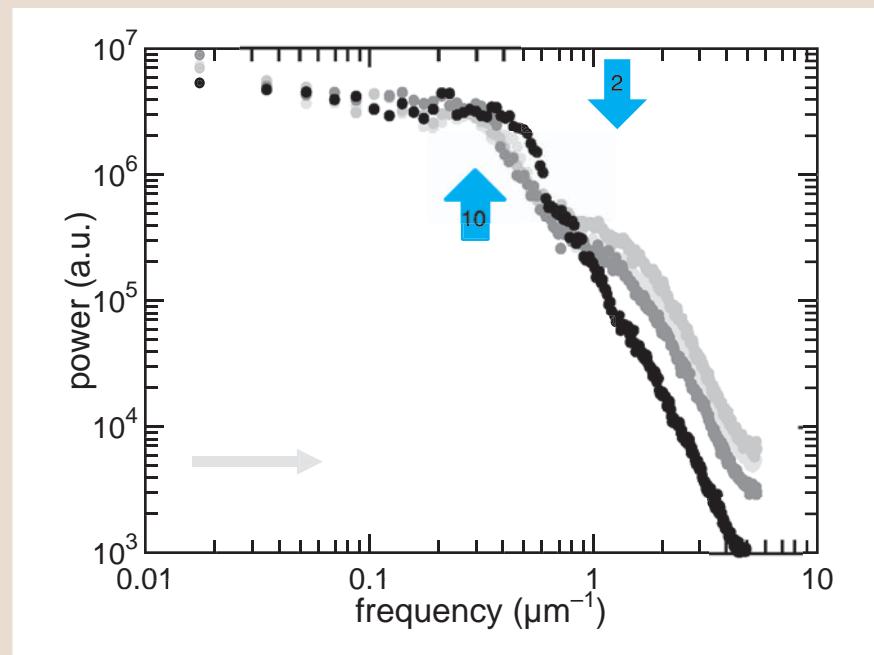
laser polarization
→



Formation process

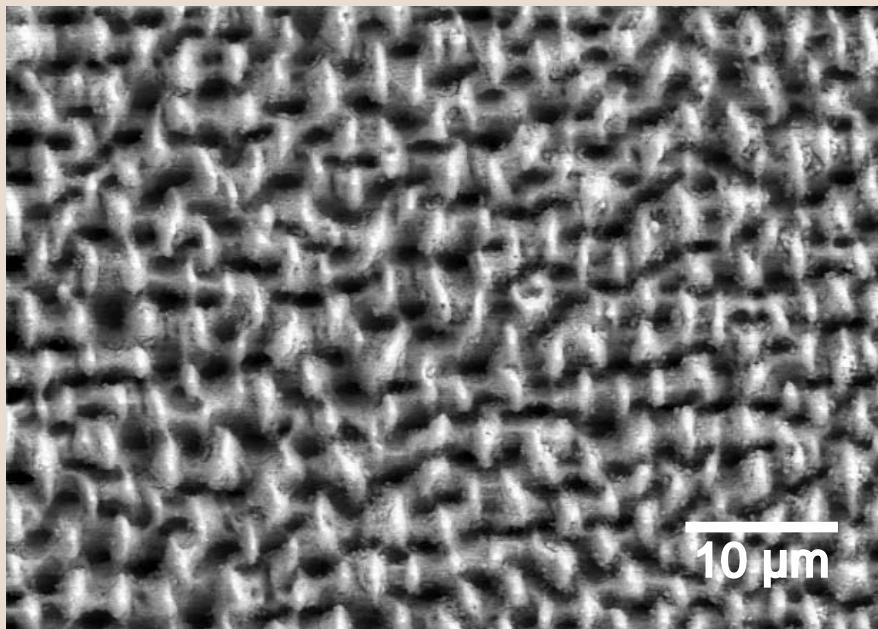


laser polarization
→

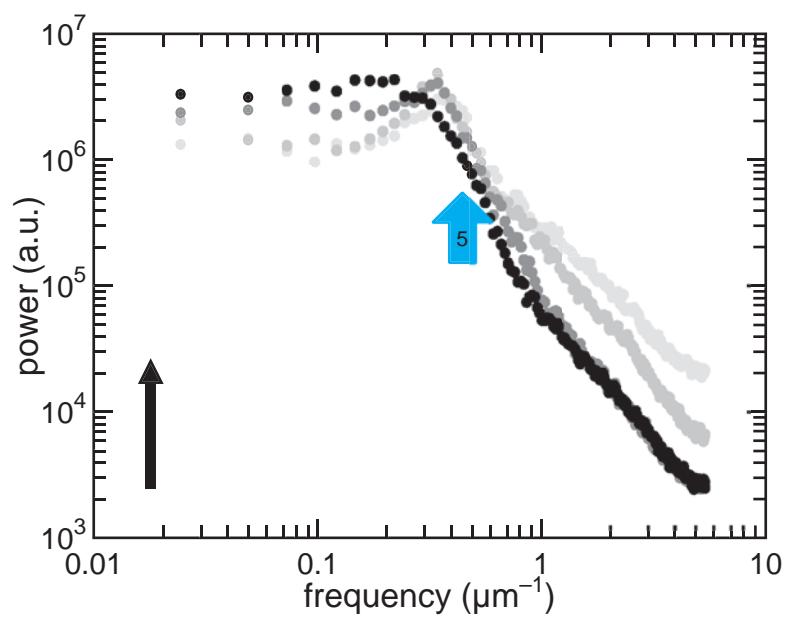
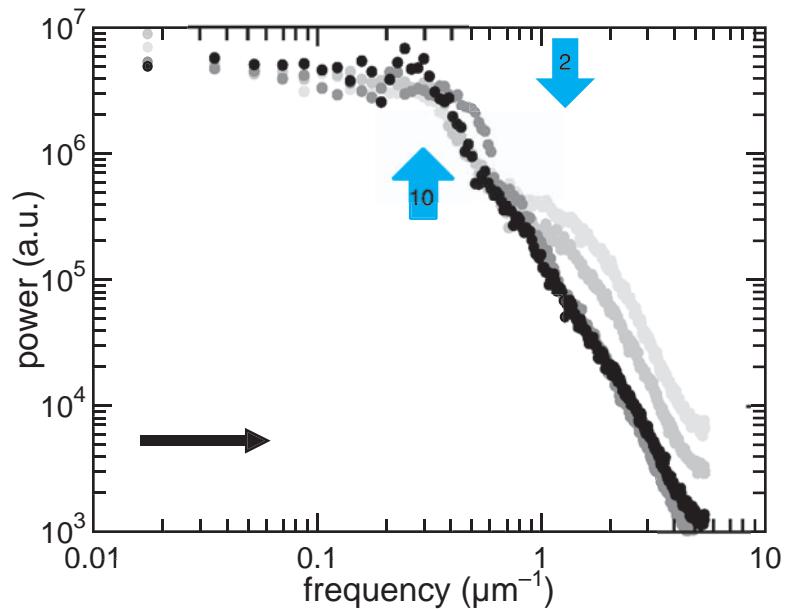


Formation process

SF₆ **500 pulses**

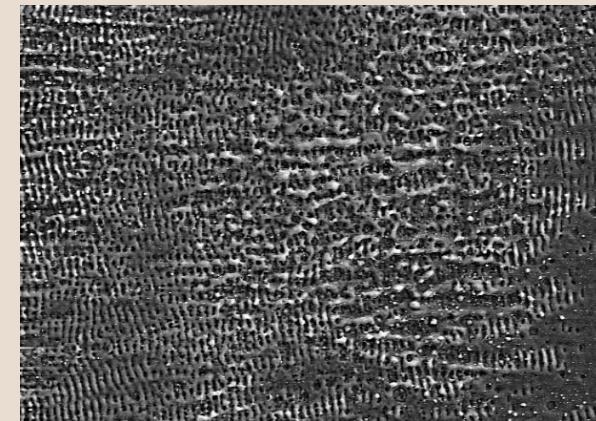


laser polarization
→



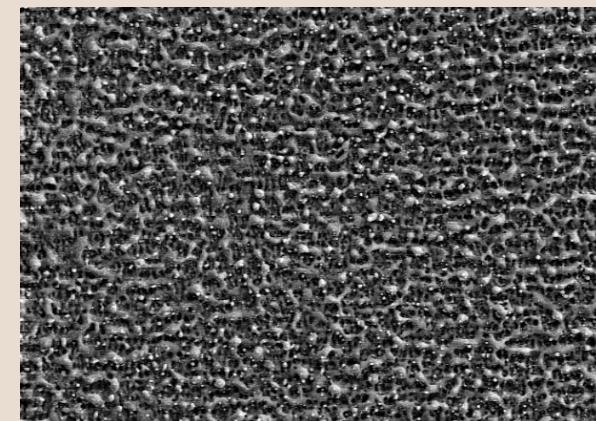
Formation process

**1. Interference ripples
(\perp to polarization)**



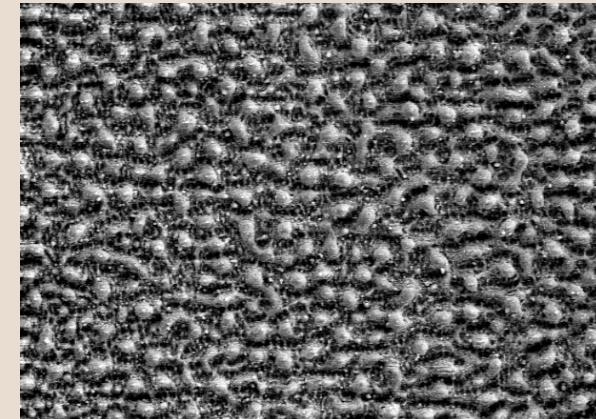
N = 2

**2. Coarsened ridges
(\perp to ripples)**



N = 4

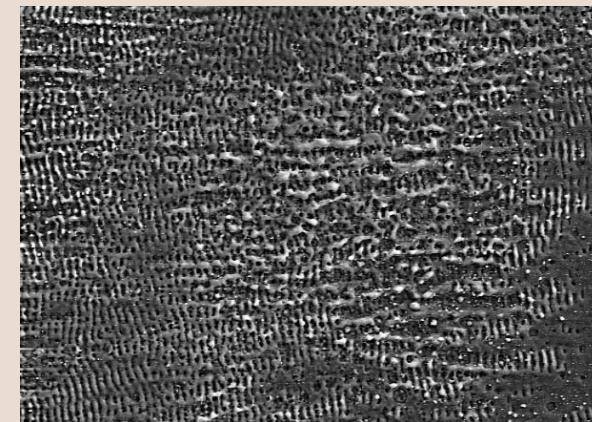
**3. Beads sharpening
into spikes**



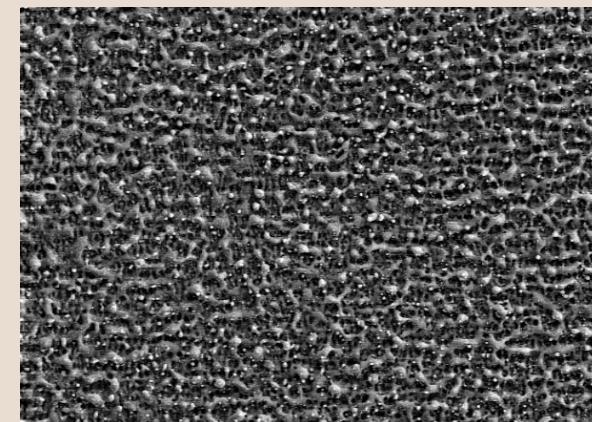
N = 10

Formation process

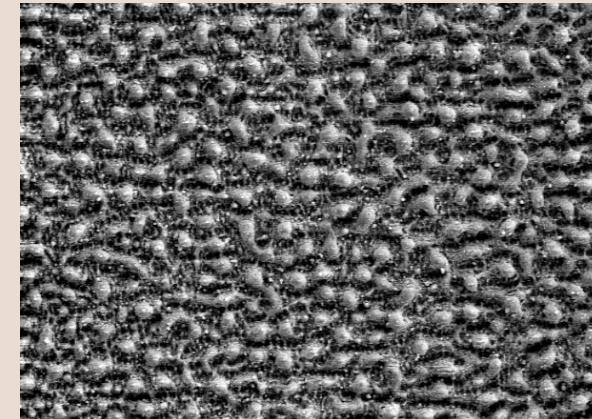
**Two distinct wavelengths:
ripples and spikes**



N = 2



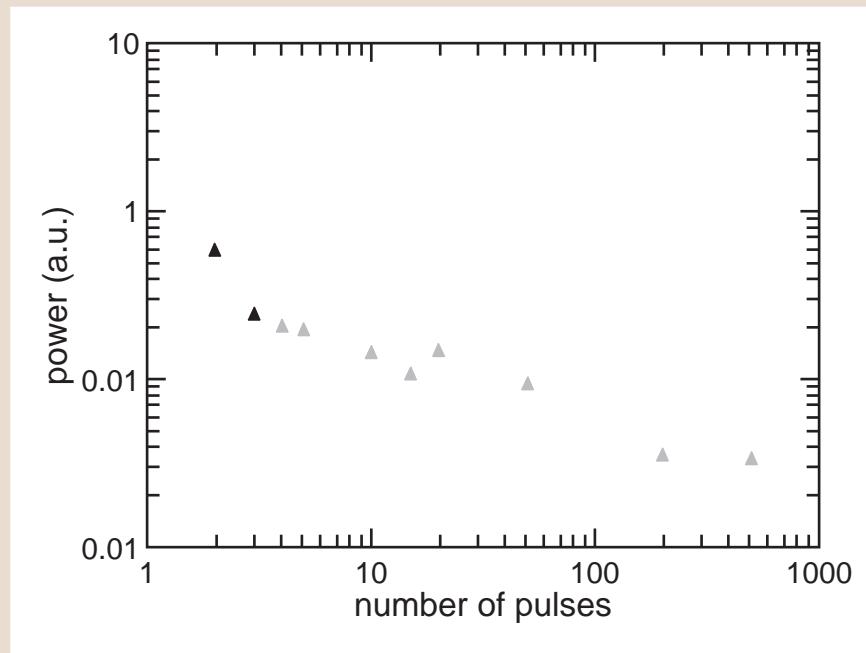
N = 4



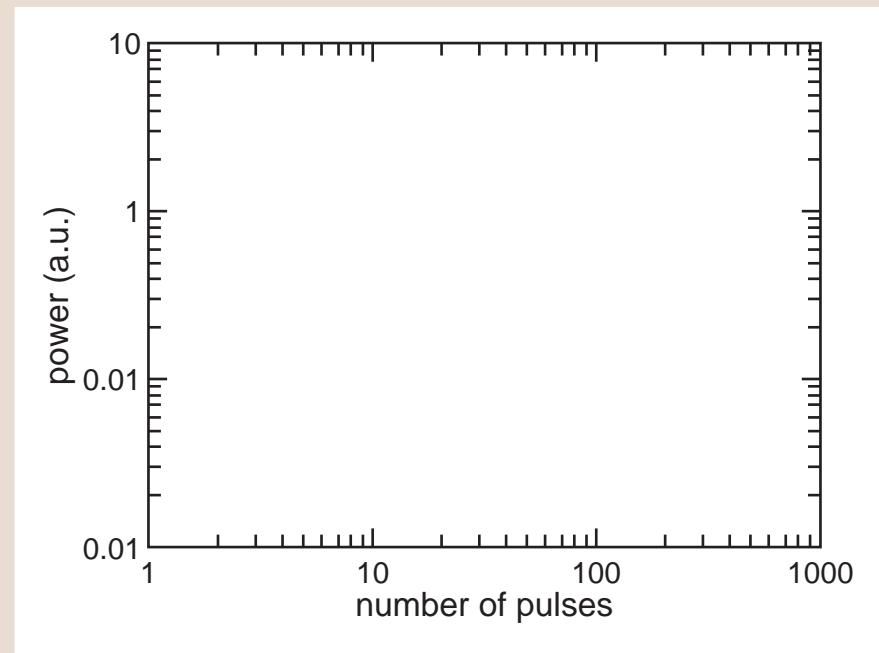
N = 10

feature intensities

SF₆ ripples



parallel

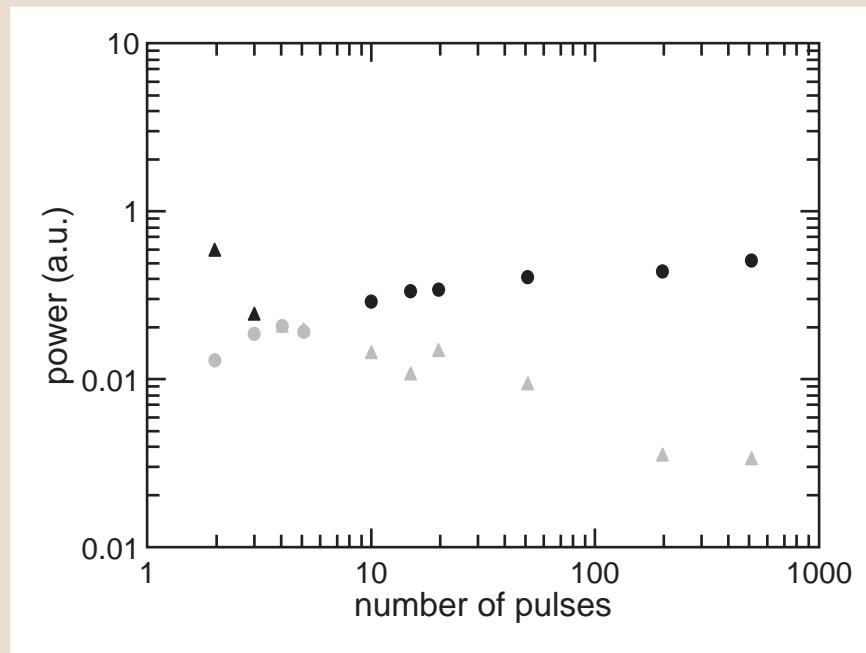


perpendicular

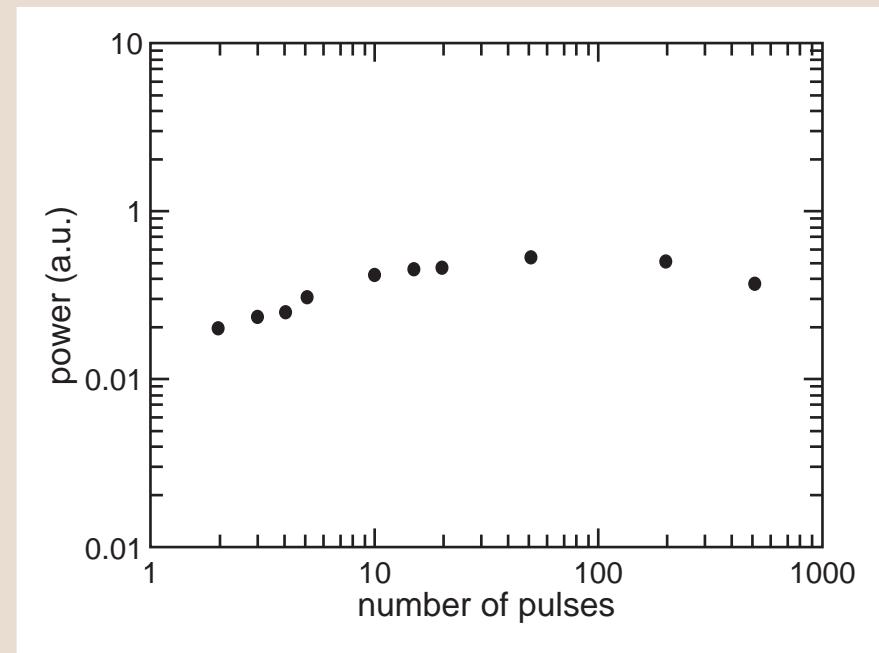
Formation process

feature intensities

SF₆ spikes



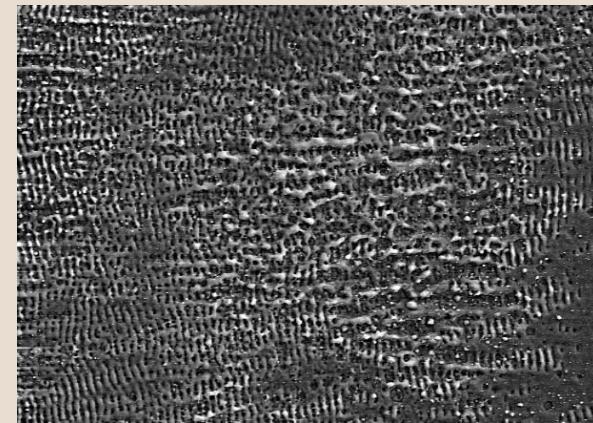
parallel



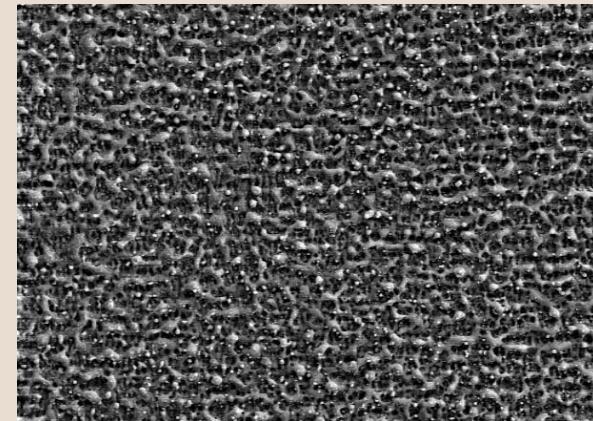
perpendicular

Formation process

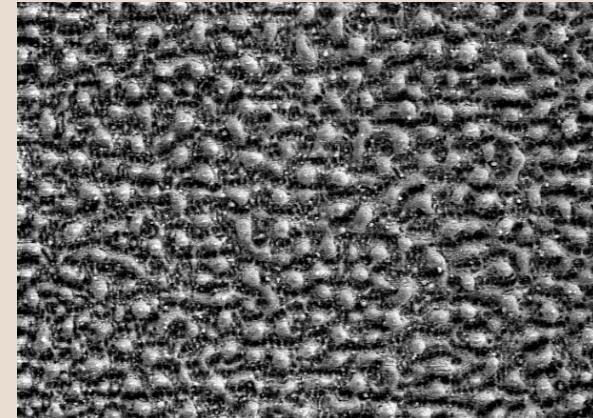
- ▶ **spike wavelength appears as ripple wavelength disappears**
- ▶ **spike wavelength appears first perpendicular to polarization**



N = 2



N = 4



N = 10

What sets the length scales?

- ▶ ripples: laser wavelength
- ▶ ridges and spikes: perhaps capillary waves

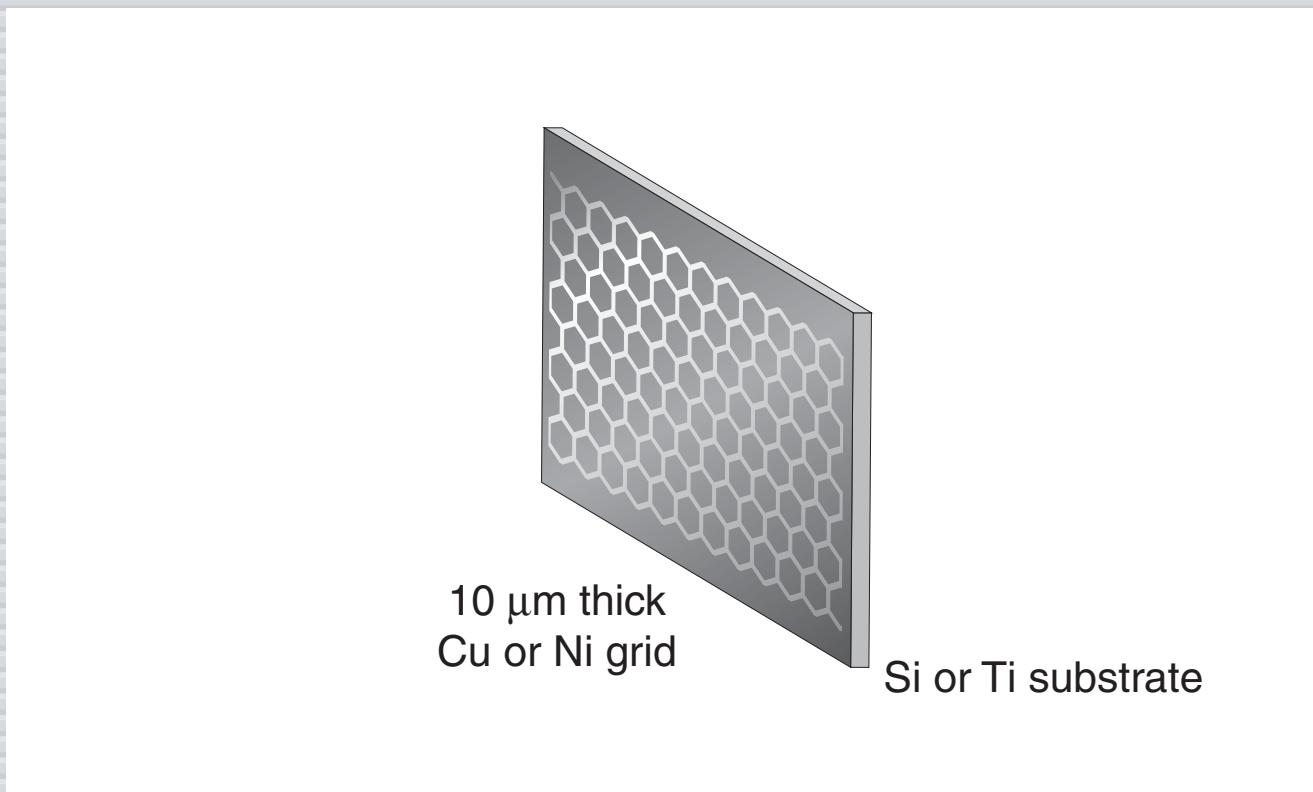
Capillary wavelength set by melt depth, duration

$$\lambda = \left[\frac{\sigma d}{\rho} \right]^{\frac{1}{4}} (2\pi\tau)^{\frac{1}{2}}$$

- ▶ longest wavelength similar to spike spacing (10 µm)
- ▶ both spike spacing and capillary wavelength increase with laser fluence

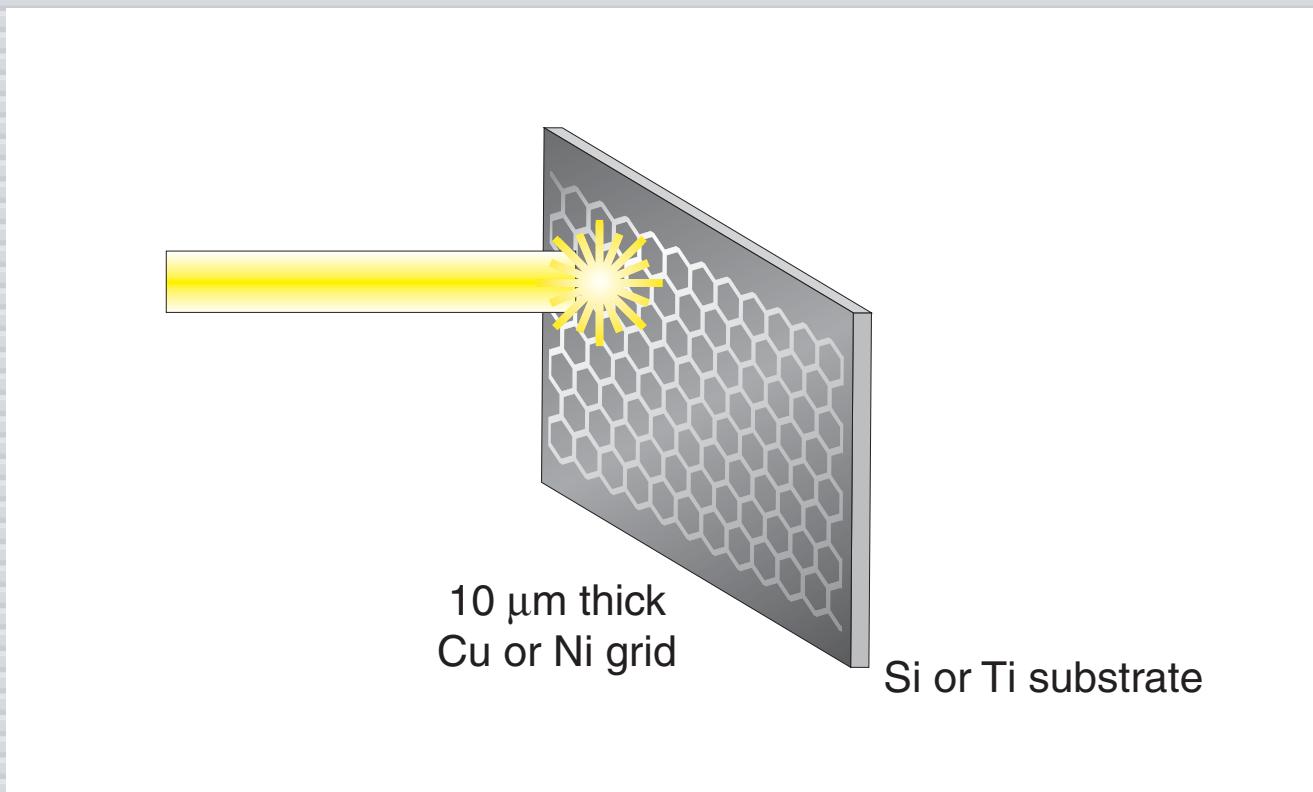
Ordering

place grid in front of substrate



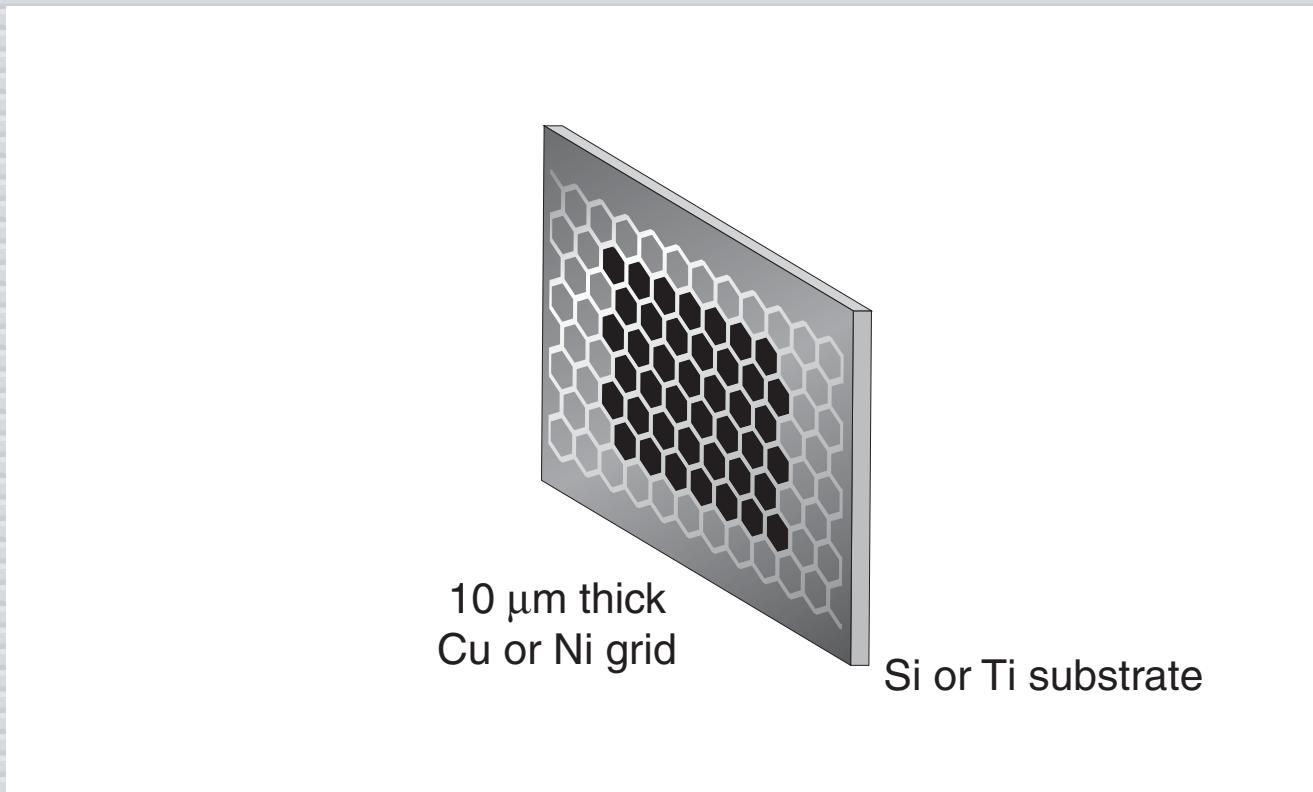
Ordering

scan laser beam



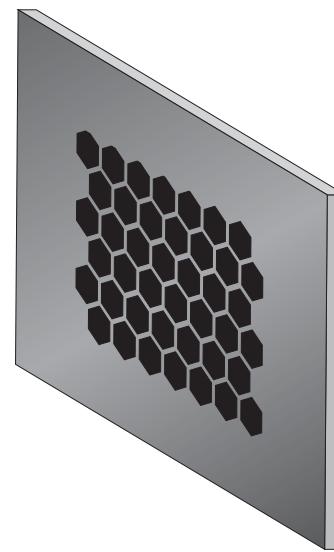
Ordering

scan laser beam

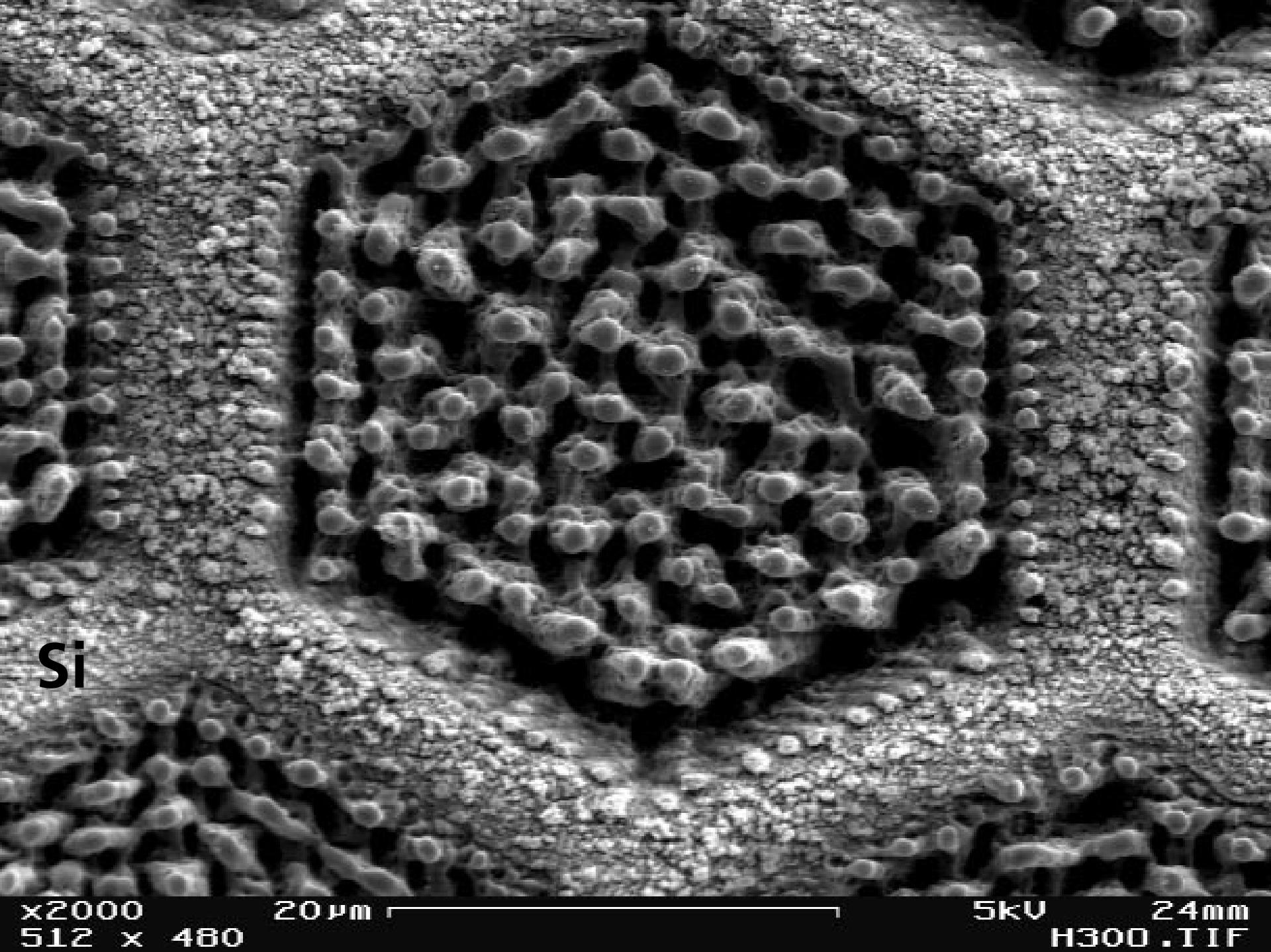


Ordering

remove grid



Si or Ti substrate



x2000

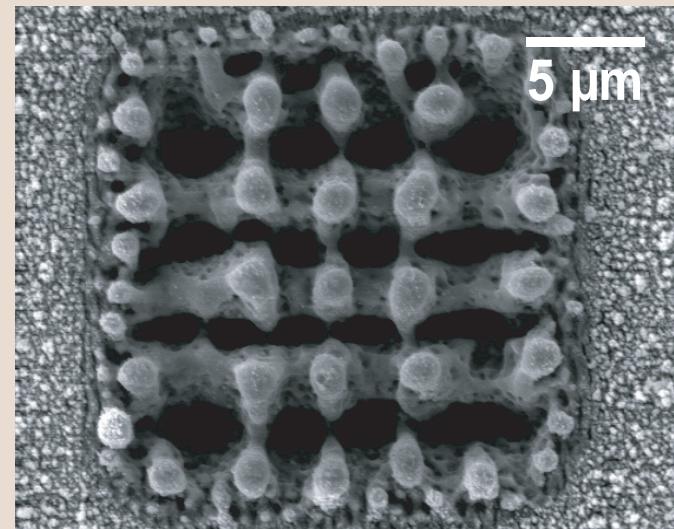
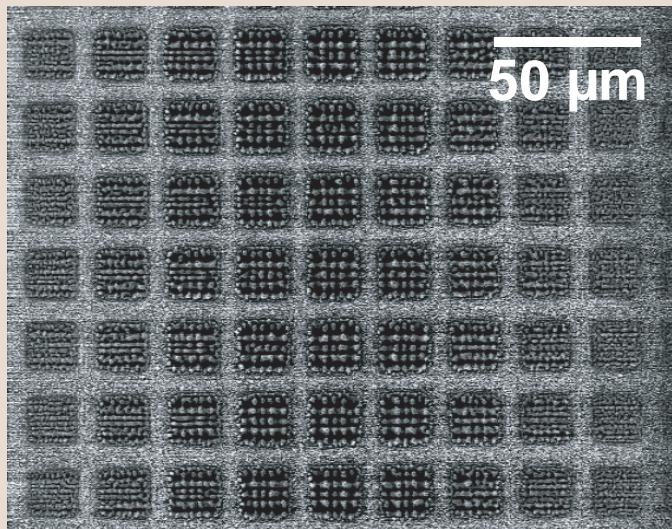
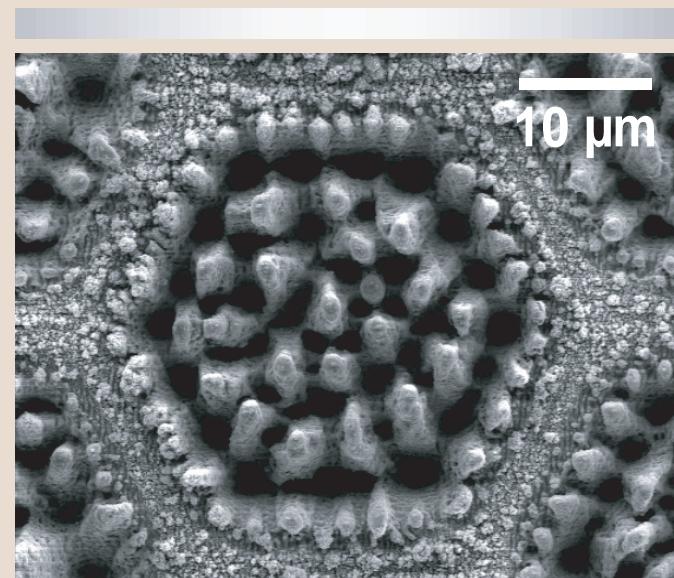
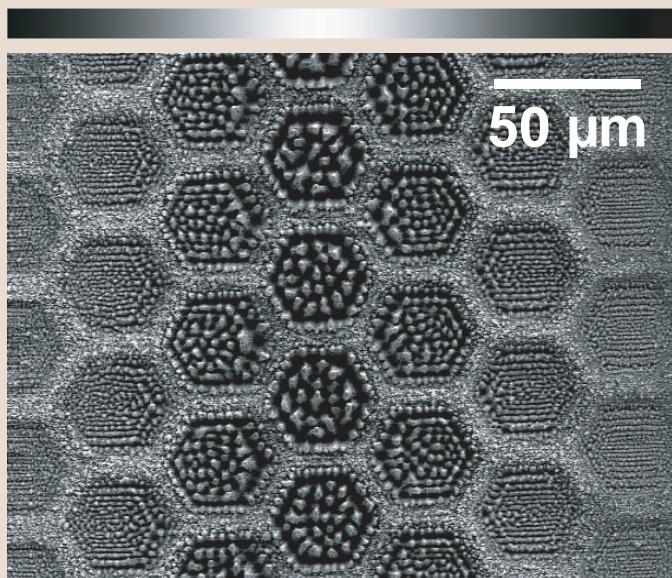
512 x 480

20 μm

5kV

24mm
H300.TIF

Ordering



Shen *et al.*, to appear in *Appl. Phys. Lett.*

Black silicon

Applications

3 μm

Black silicon:

- ▶ near-unity absorption from near-UV to near-IR
- ▶ p -type sulfur impurity band below CB edge
- ▶ self-organized surface microstructures
- ▶ many promising applications!

Acknowledgements

**Collaborators: Jim Carey, John Chervinsky,
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Shen, Jeffrey Warrender, Rebecca Younkin**

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Michael Aziz, Cynthia Friend, Howard Stone**

**Funding: Department of Energy, National
Science Foundation (Harvard MRSEC)**

For a copy of this talk and
additional information:
<http://mazur-www.harvard.edu>

Could nanostructures explain infrared absorption?

Structure less likely than sulfur:

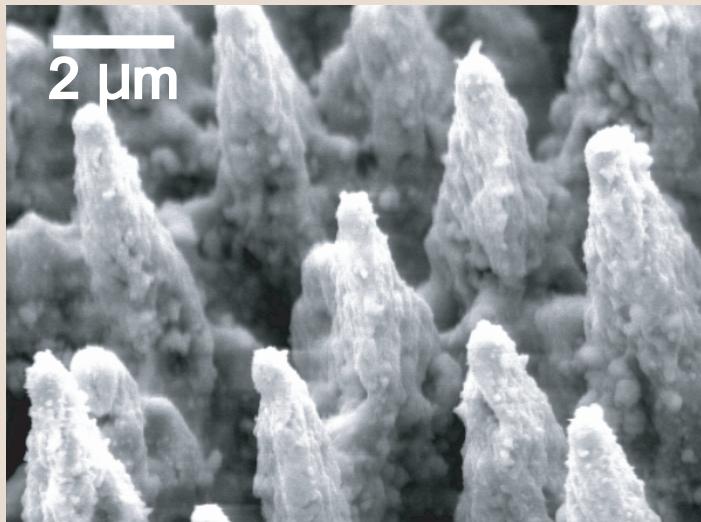
annealing

ns pulses

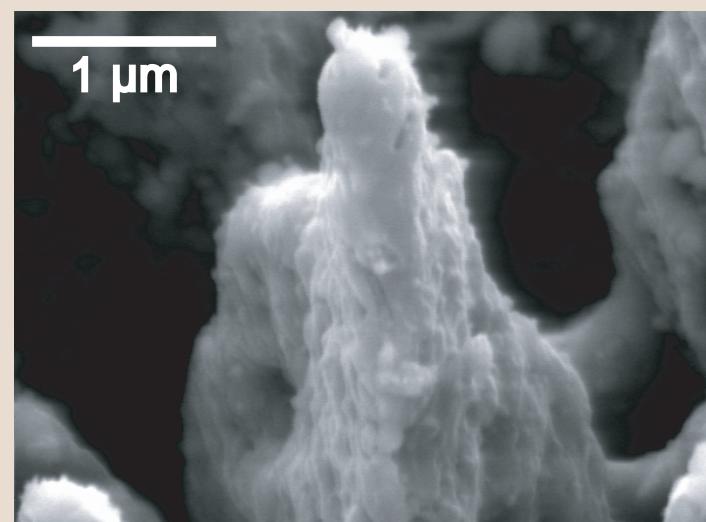
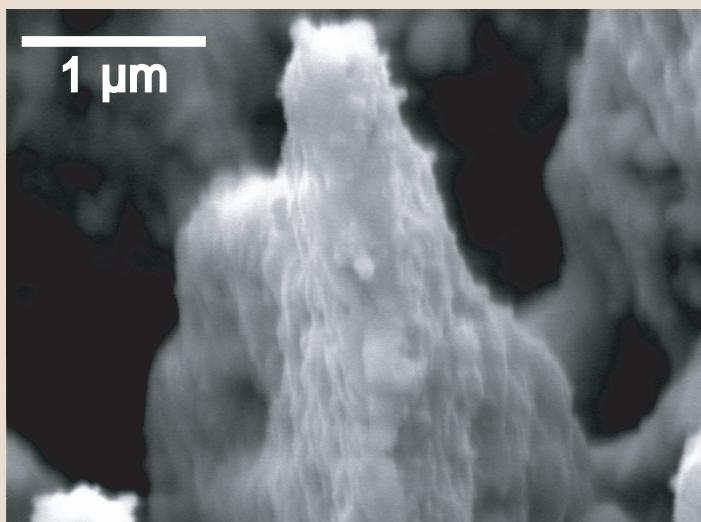
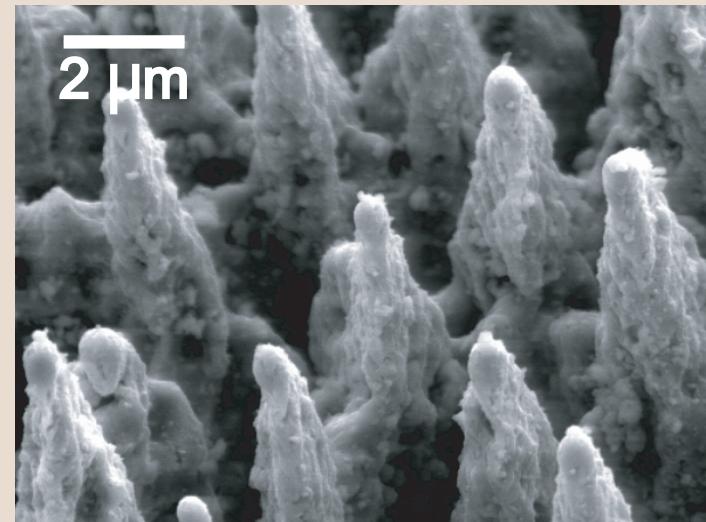
different gases

Structural analysis

before annealing



after annealing



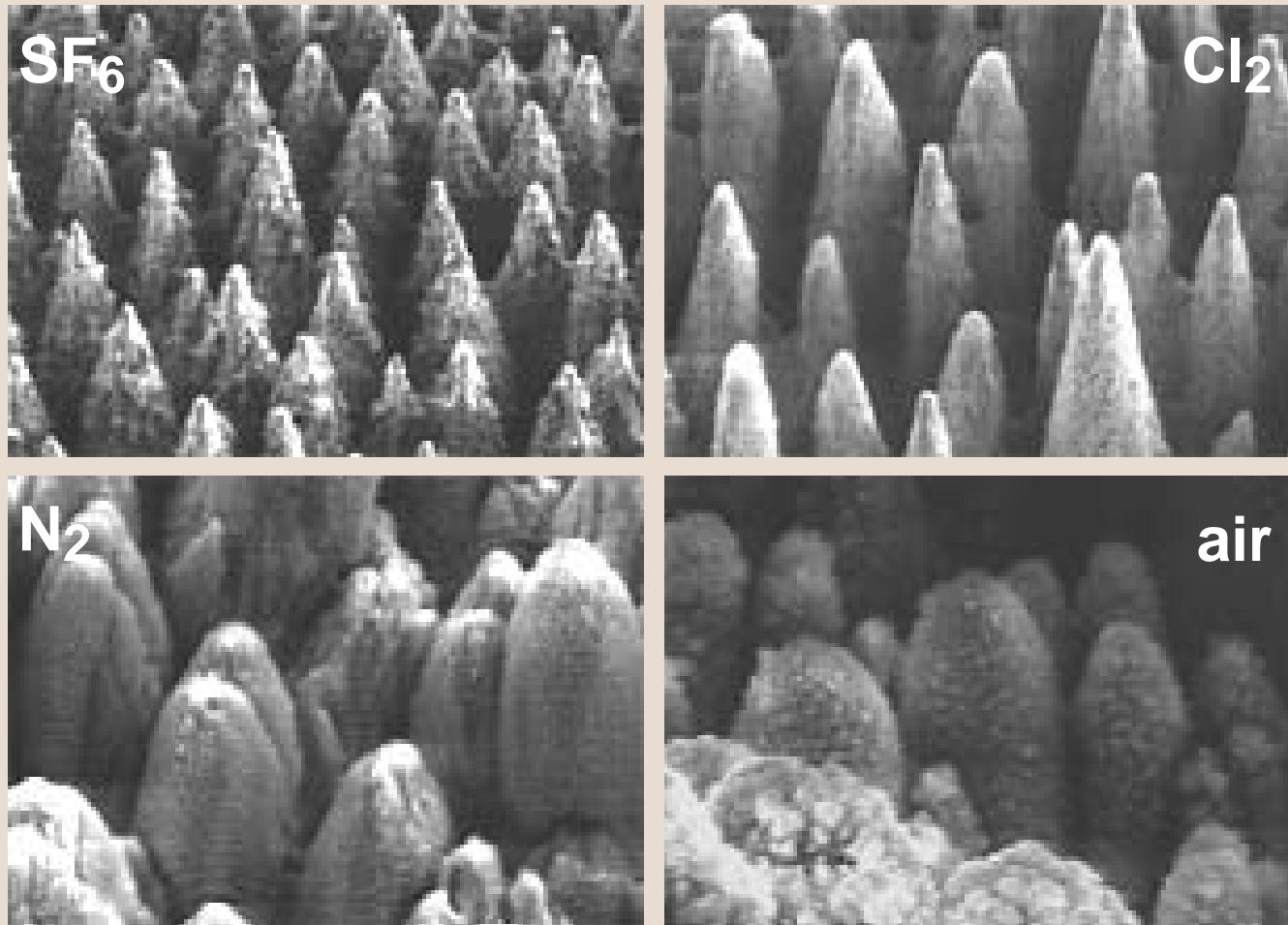
Structure less likely than sulfur:

no evident structural change with annealing
(consistent with multiple reflections in visible)

Structure less likely than sulfur:

no evident structural change with annealing
ns pulses produce very different structure, but
same composition and optical properties

Structural analysis

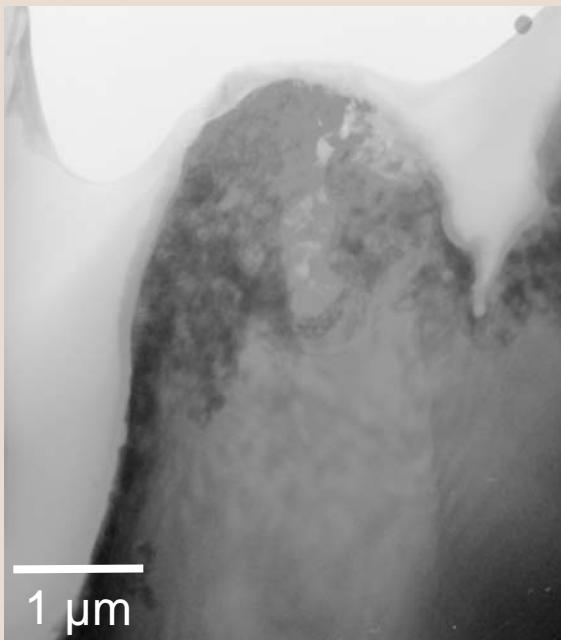


10 μm

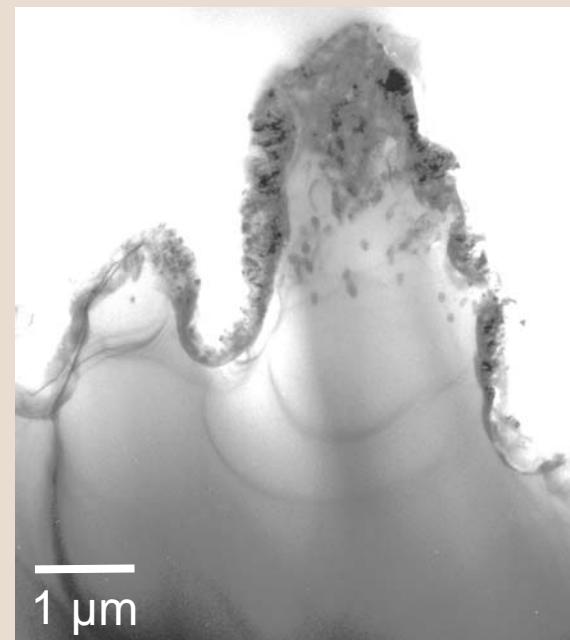
all except Cl₂ show surface nanostructure

Structural analysis

air



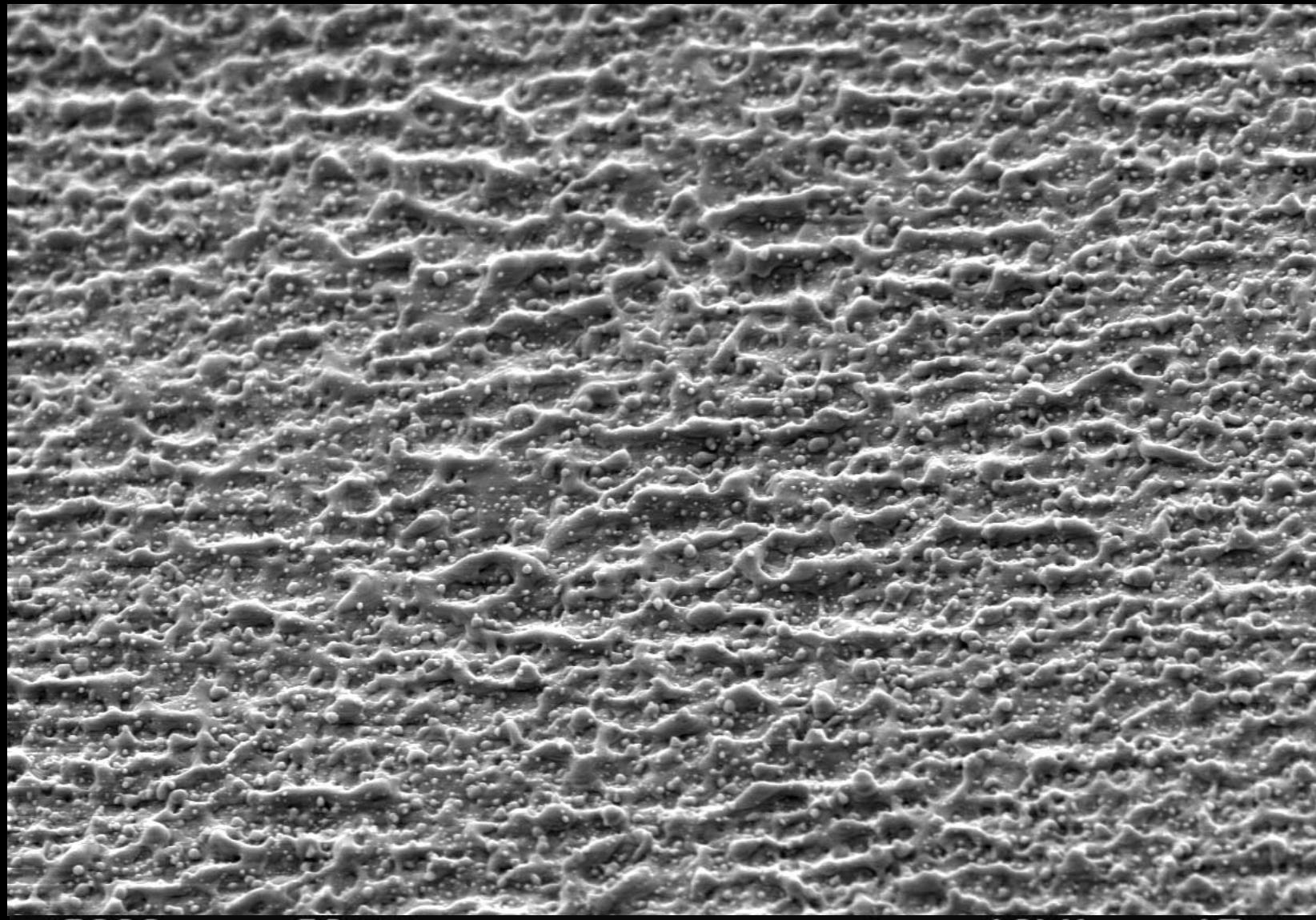
SF₆



surface disorder present in air sample

Structure less likely than sulfur:

- no evident structural change with annealing
- ns pulses produce very different structure,
same composition and optical properties
- different gases all produce nanostructures



x2000
#3548
512 x 480

20 μ m

10kV

15mm

0006